



# 国内のナノテクノロジーの現状と将来

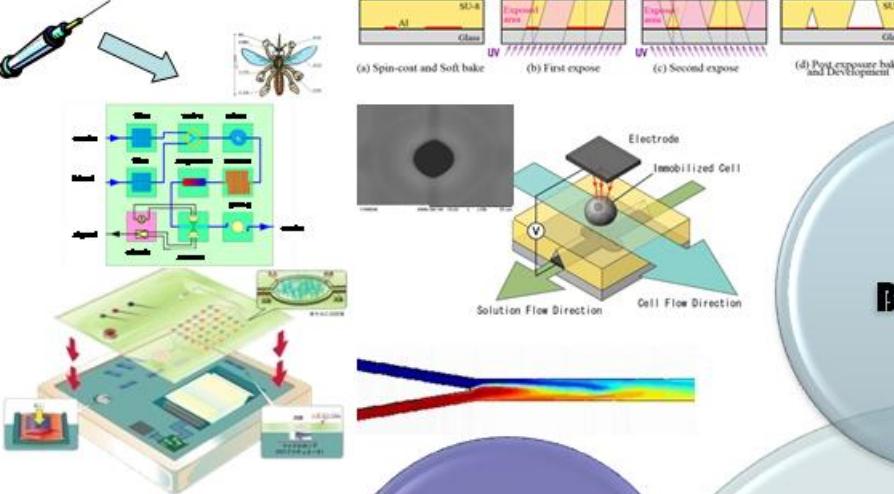
Hidetoshi Kotera

<sup>1</sup>Micro engineering department, Postgraduate school of Engineering,  
**Kyoto University**

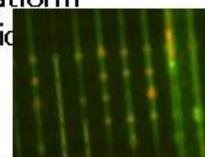
Yoshidahonmachi, Sakyo-ku, Kyoto 606-8501, JAPAN

**NEDO**(New Energy and Industrial Technology Development Organization)





## Bio Nano hybrid platform and 3D Fabrication



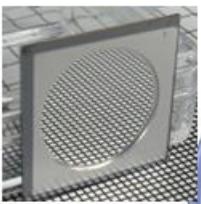
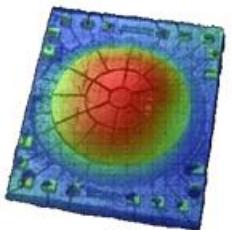
2

Micro Fluidics/ Micro TAS and SPR



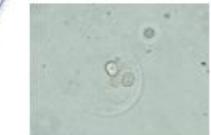
## CLINICAL LAB. TEST

Point of Care



Piezoelectric material &  
Actuator

## OPHTHAL- MOLOGY



## Implantation

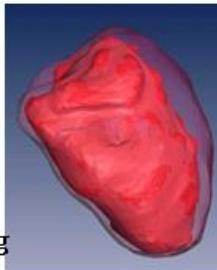
**NANO**

**MEDICINE**

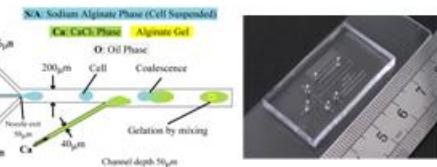
**Education &  
Fabrication**

## PHYSIOLOGY

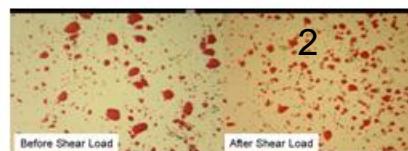
Model and Simulator /  
Micro TAS for measuring  
cell performance



## DIABETES/ METABOLISM



Bio-Nano Plat form/Micro Fluidic  
system and micro sensor for  
single molecule



# History of MEMS

**1824 : Discovery of silicon (Berzelius)**

**1910 : First patent on the MOS transistor concept**

**1939 : First PN junction (Schottky)**

**1947 : Fabrication of the first bipolar transistor (Shockley)**

**1955 : Evidence of piezoresistive effect in Si and Ge (Smith)**

**1958 : First integrated circuit (Oscillator)**

**1959 : R. Feynman Famous Talk : 'There is plenty of room at the bottom'**

**1960 : Fabrication of the first piezoresistive sensor –pressure– (Kulite) –accel. in 1970**

**1967 : First Surface Micro-machining process (H. Nathanson) : resonant gate transistor**

**1970 : Silicon-glass bonding**

**1972 : National Semiconductor : Commercialize a Pressure Sensor**

**1977 : IBM – HP : Micro-machined Ink Jet Nozzle**

**1978 : Silicon Bulk Micromachining : K. Bean**

**1978 : Structure obtained by Micromoulding (LIGA)**

**1982 : Famous Review paper « Silicon as a Mechanical material » (K. Petersen)**

**1985 : Assembly of silicon wafers (Si/Si fusion bonding) : Lasky, et al.**

**1985 : IC-compatible surface micromachining -> Polysilicon comb structures**

**1988 : Electrostatic micromotor (UC -Berkeley BSAC)**

**1988 : 1st MEMS conference (1st Transducers conference was held in 1987)**

**1992 : First MUMPS process (MCNC) (with support of DARPA). Now owned by Memscap**

**1992 : SCREAM Process (Cornell)**

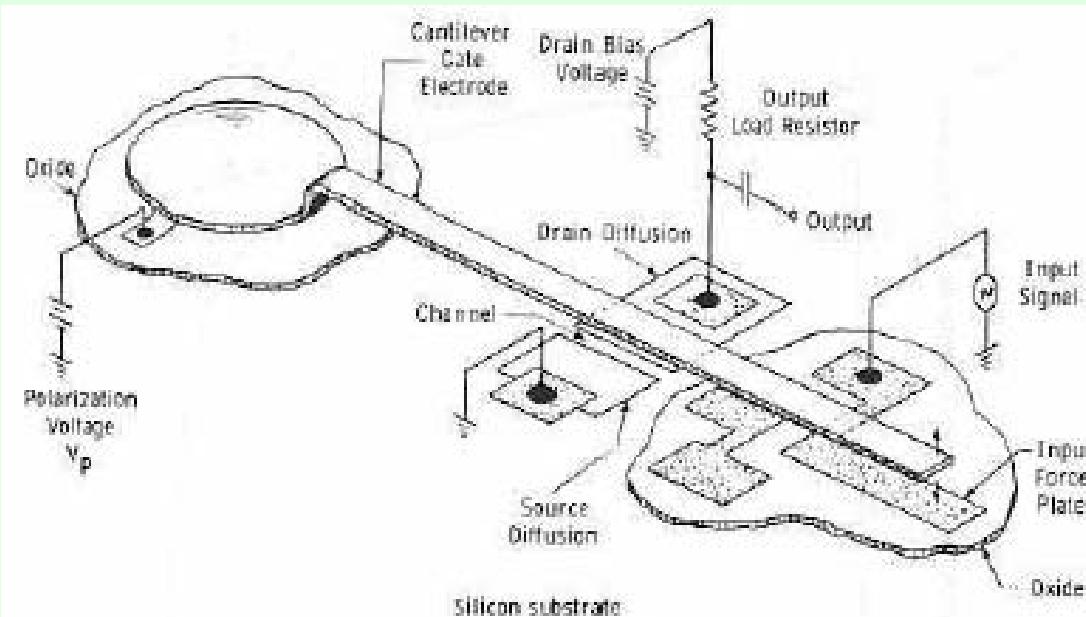
**1993 : Analog Devices : Commercialize Multi-axis Accelerometer integrating electronics**

**1993 : Texas Instrument : Commercialize the Digital Mirror Display (DMD)**

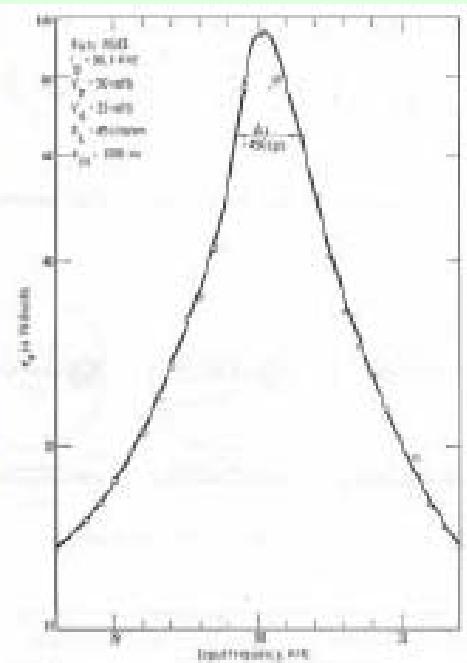
**1996 : DRIE (Bosch Process)**

# MEMSの定義 : Micro Electro-Mechanical Systems

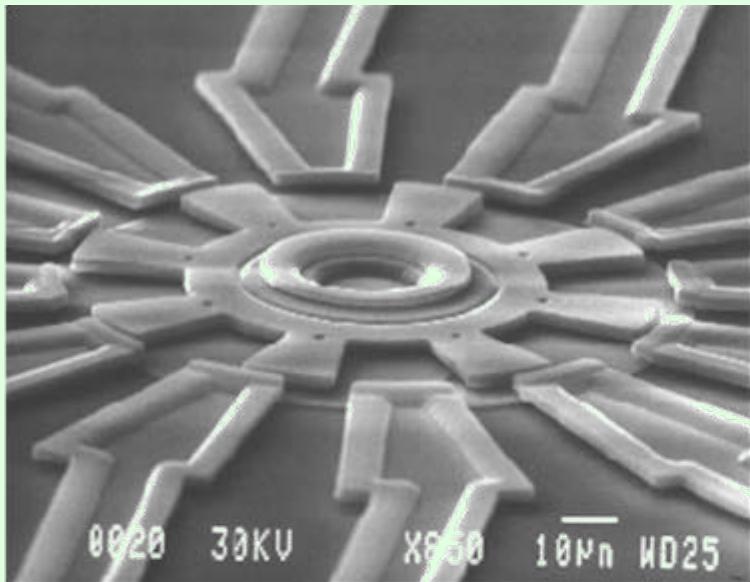
First MEMS Concept is The Resonant Gate Transistor in 1967



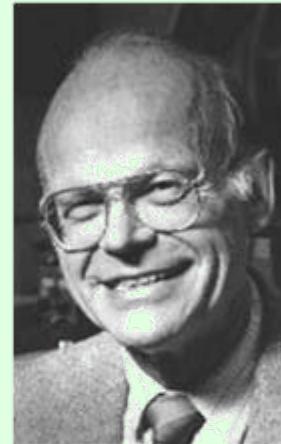
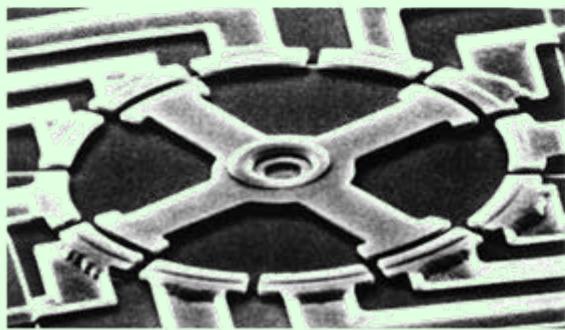
- The gate is a movable Gold cantilever
- Photoresist sacrificial layer
- Drain current modulation by the cantilever motion



Frequency response :  
 $f_0 \approx 30\text{ khz}$



Transducers U.C. Berkeley

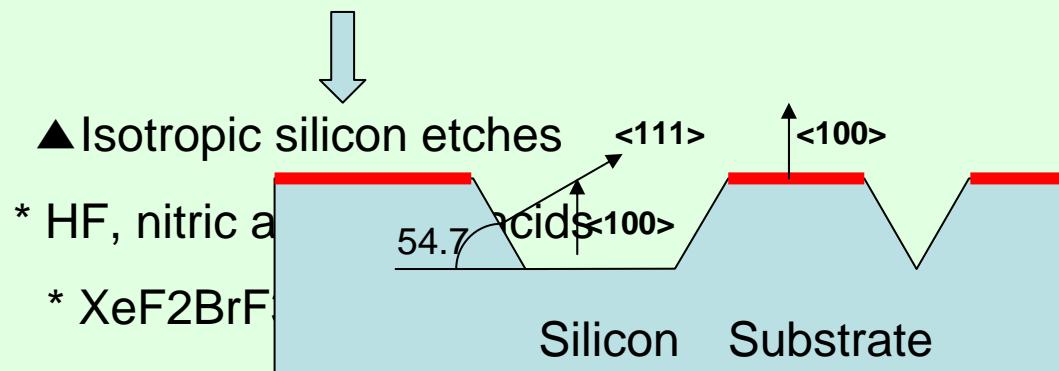


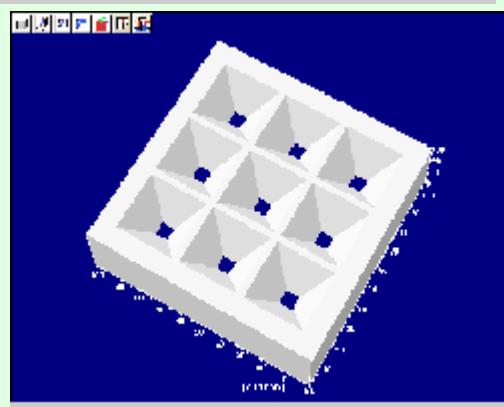
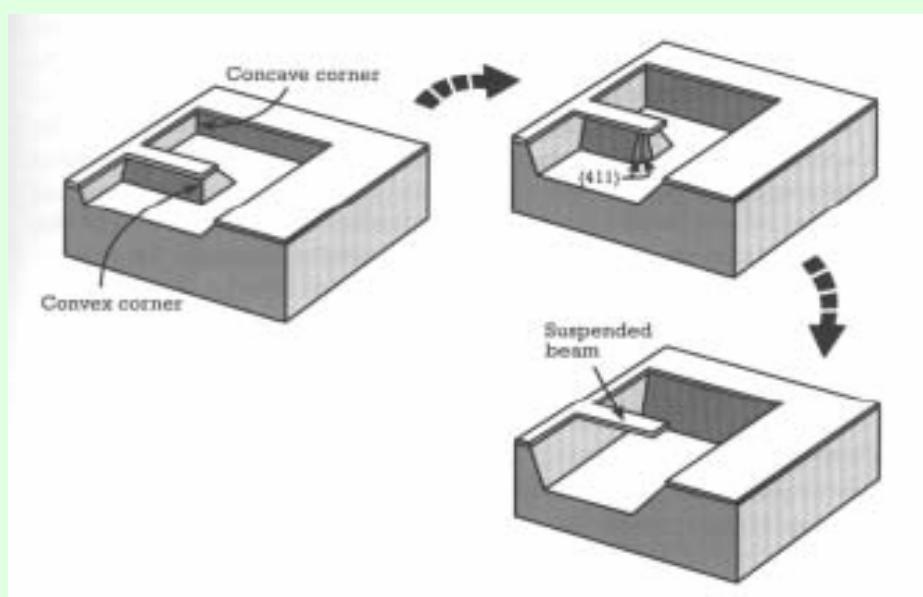
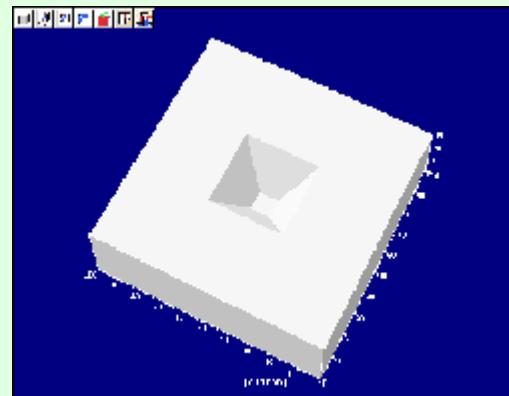
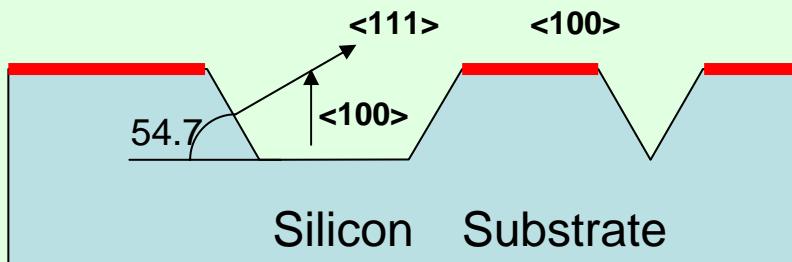
**Professor Richard S. Muller**

# Bulk Micromachining

- ▲ Liquid etching; etch rate differences in different crystal directions
  - <111> etch rate is slowest, <100> and <110> fastest
  - Its rate is more than 400 times

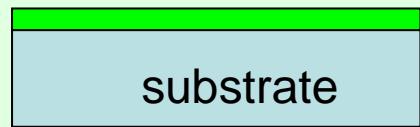
Commonly; anisotropic etches in silicon include KOH, TMAH (Tetramethyl Ammonium Hydroxide) and EDP ( Ethlene Diamine Pyrocatecol)





# Surface Micromachining

Thin film technology + sacrificial layer



sacrificial layer



Photo resists



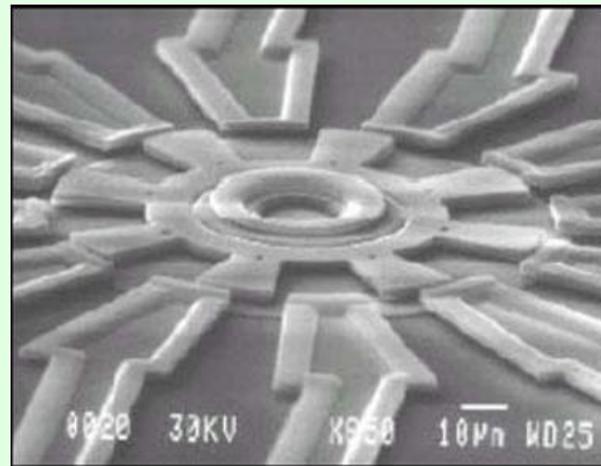
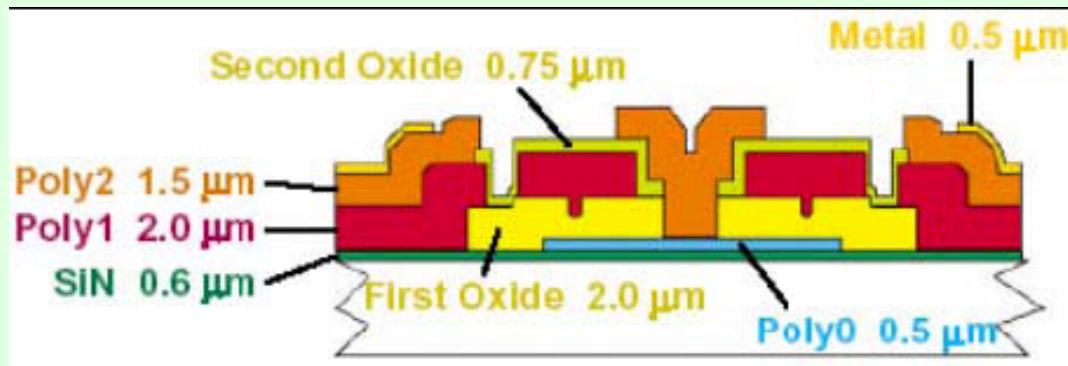
Deposit structural layer



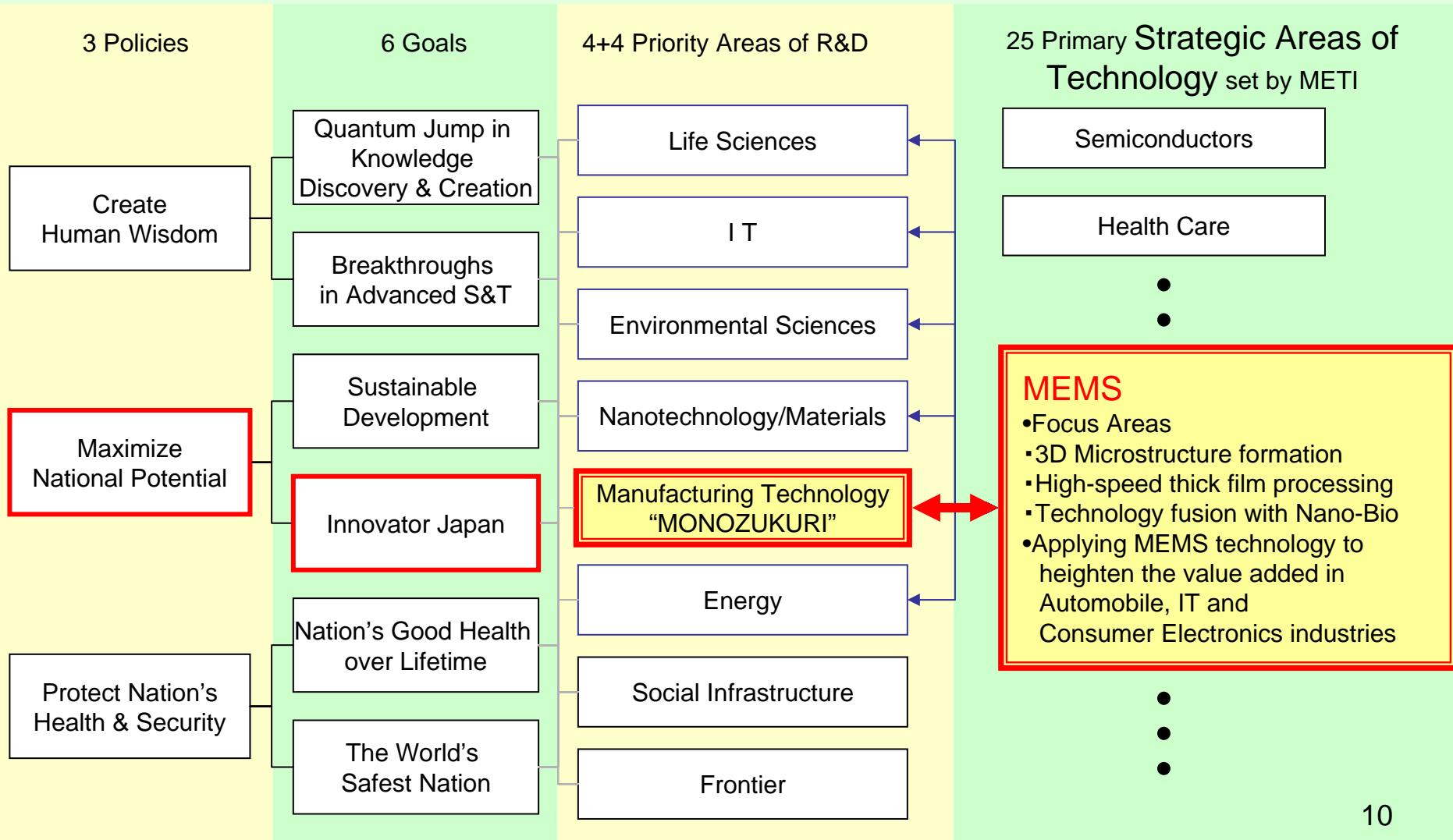
UV + DV + Etching



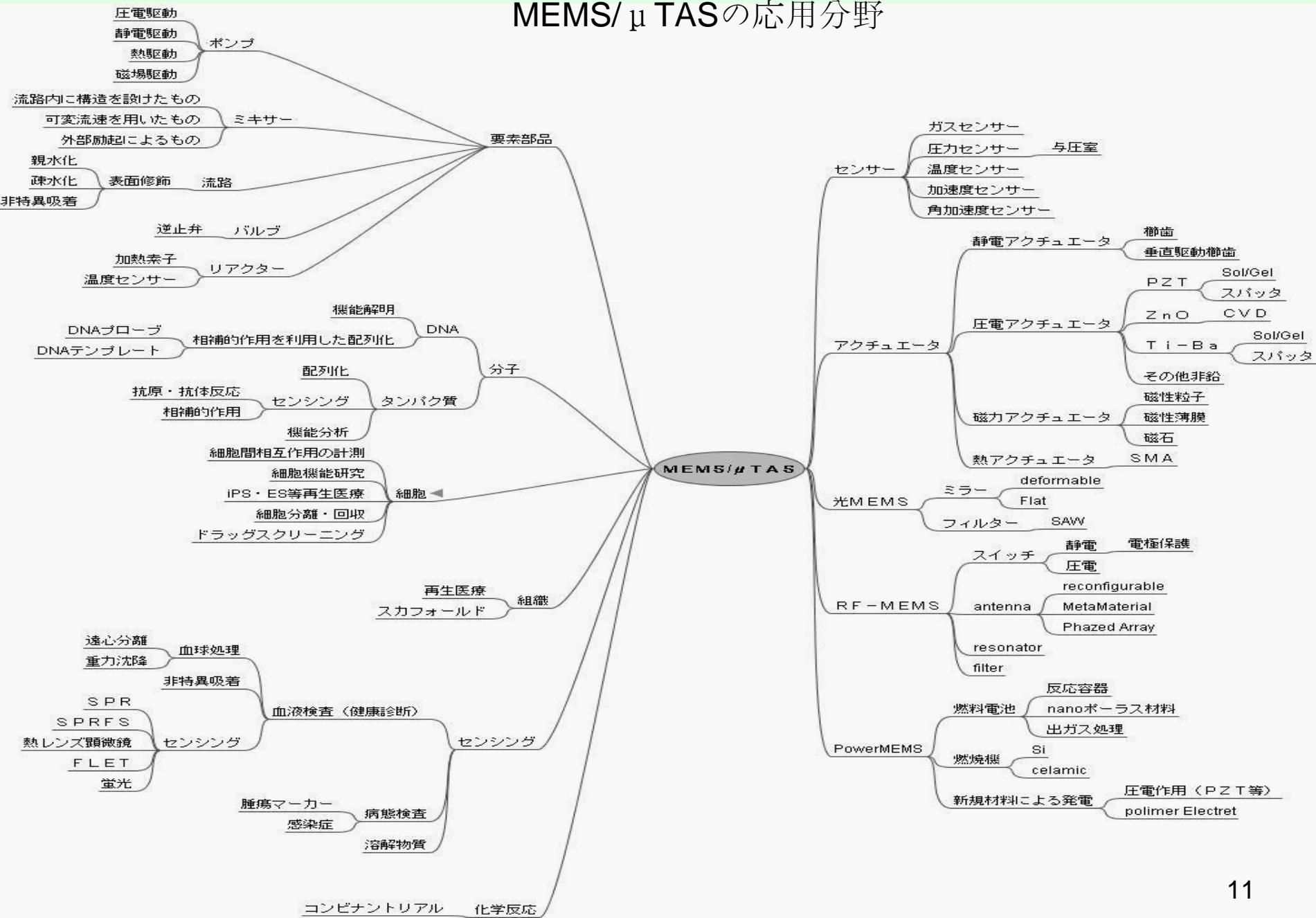
Etching ( wet chemical or  
dry plasma etching)



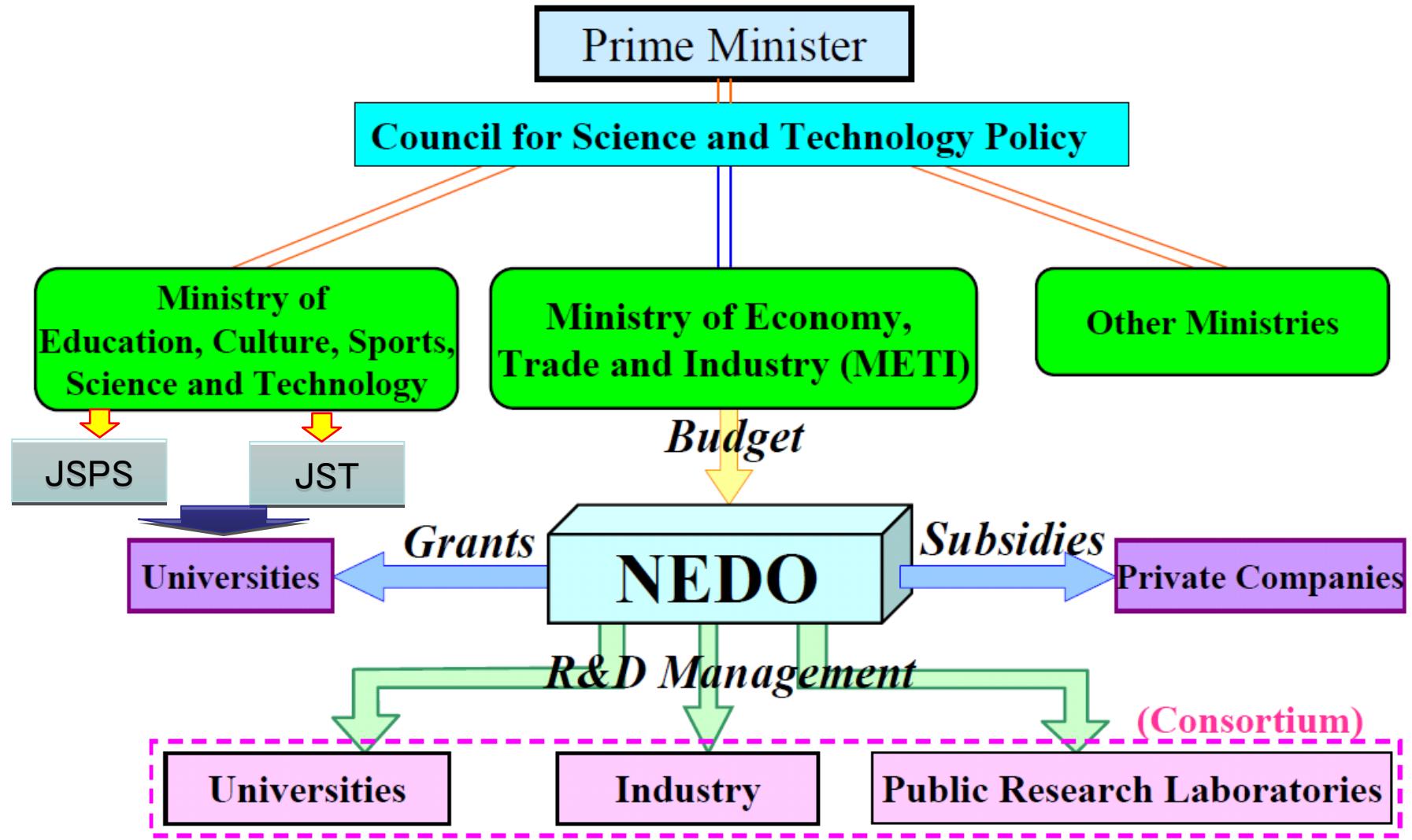
# JAPAN's the 3rd Science and Technology Basic Plan & MEMS position (FY2006-2010)



# MEMS/μTASの応用分野

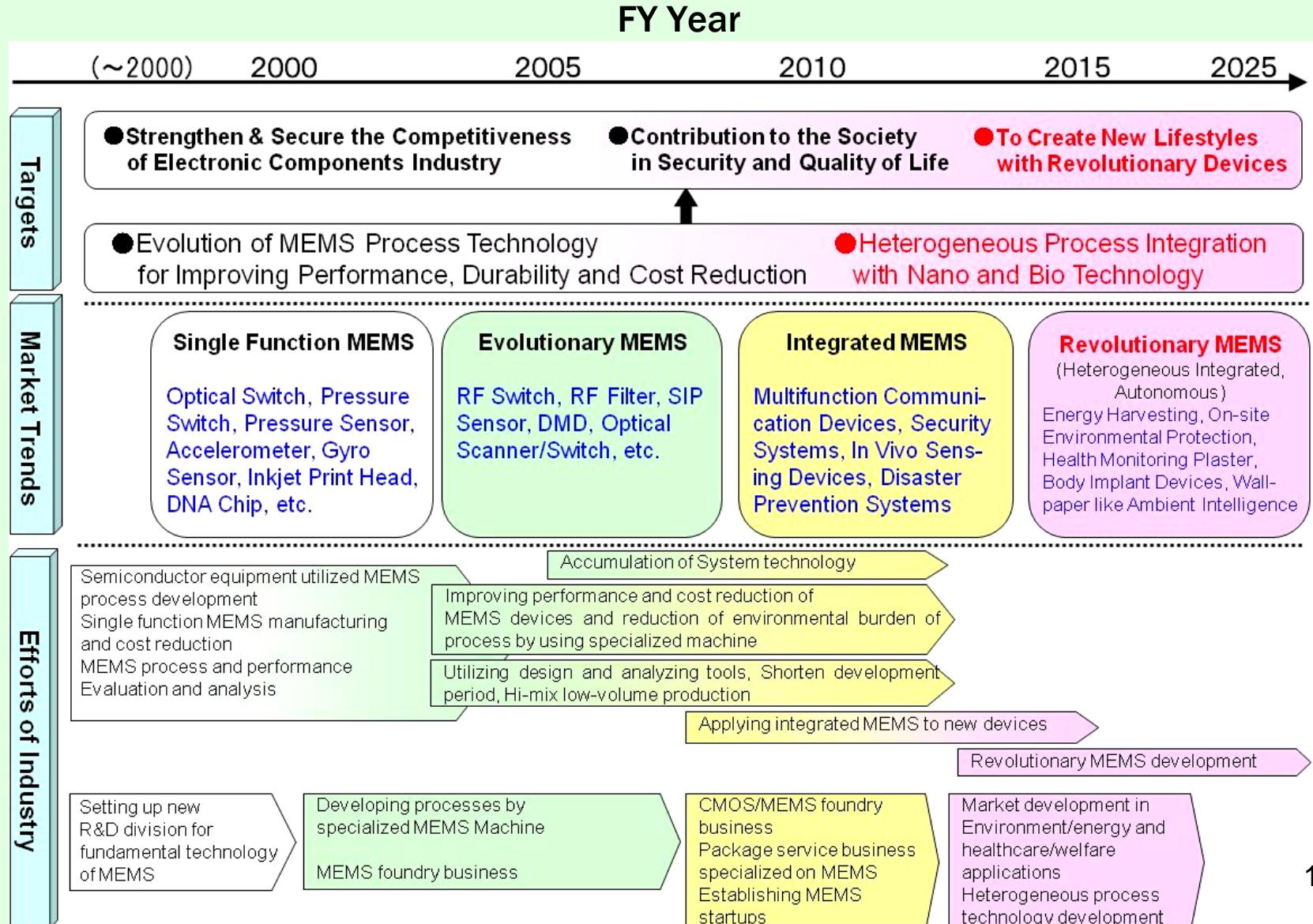


# Japan's R&D Promotion Scheme

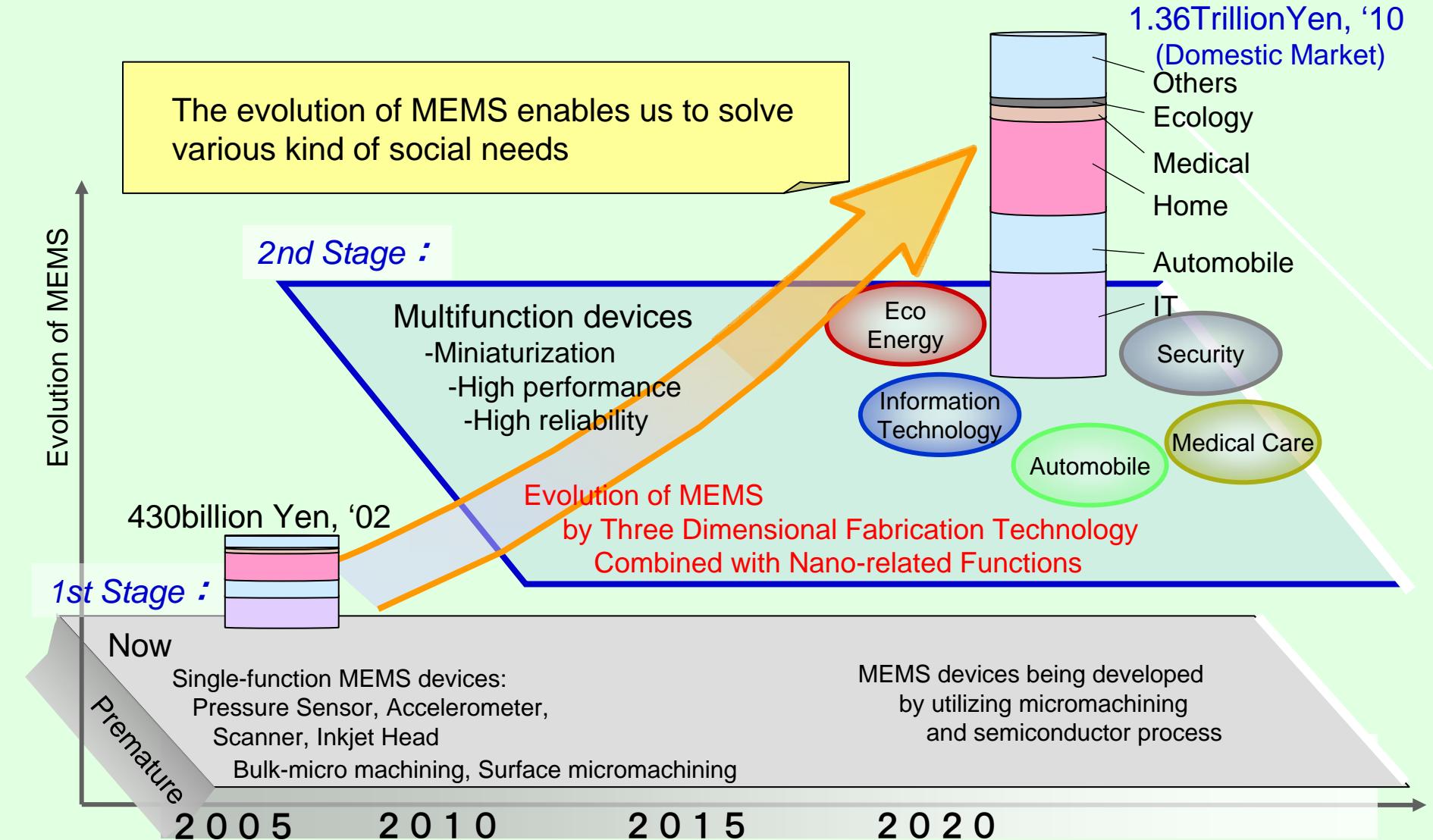


# Scenario for Dissemination 1/2

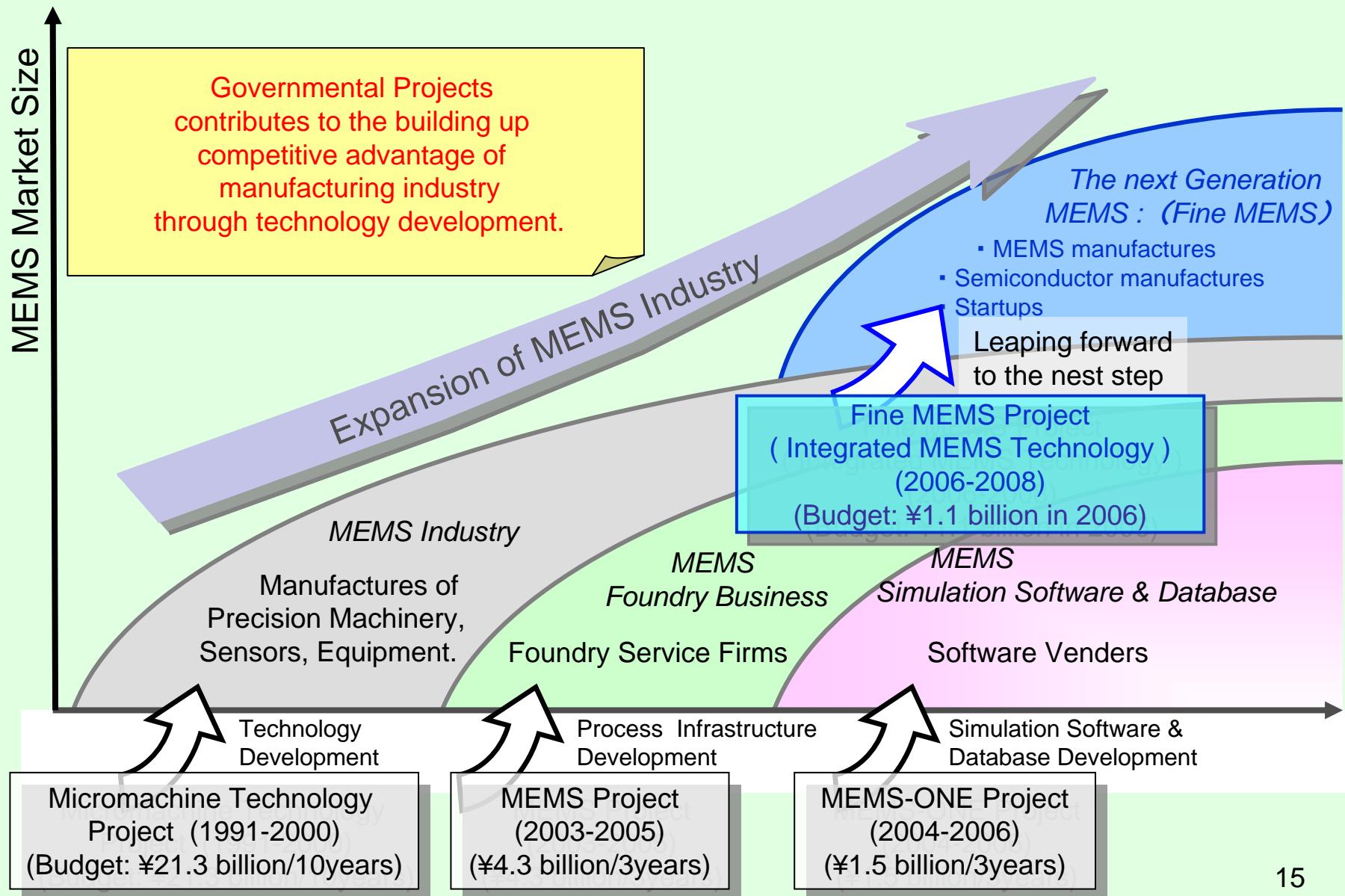
Shows the paths through which R&D outcomes go out into the world as well as relevant measures involved



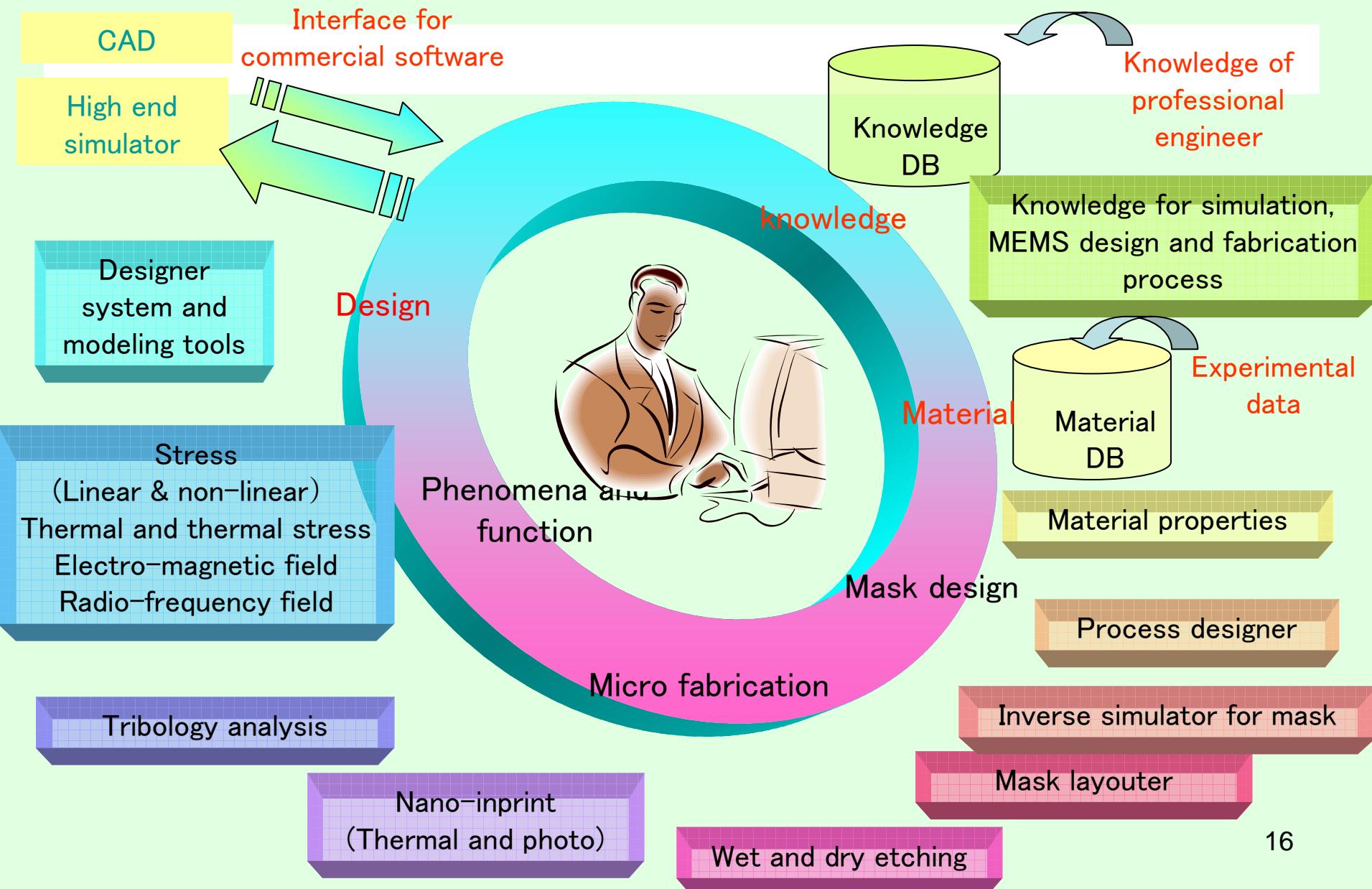
# MEMS Industrialization Strategy & Scenario



# Technology Development for MEMS Industry Expansion

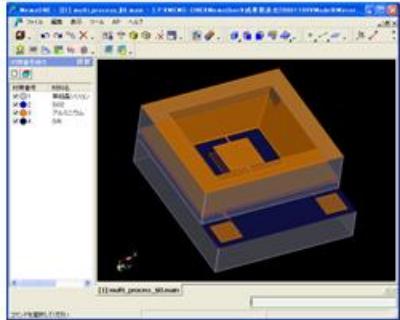


# Technical Concept of MemsONE

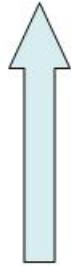
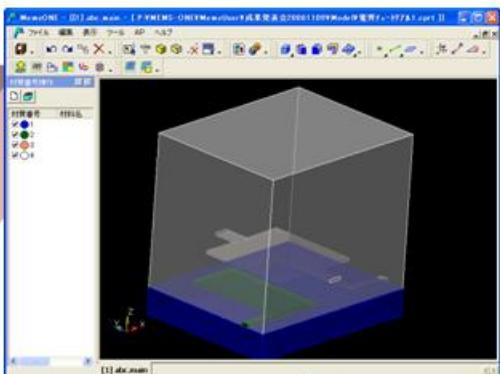


## Auto mesh generation

Design system

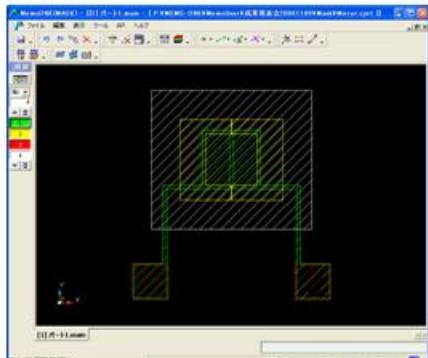


Mesh Generator

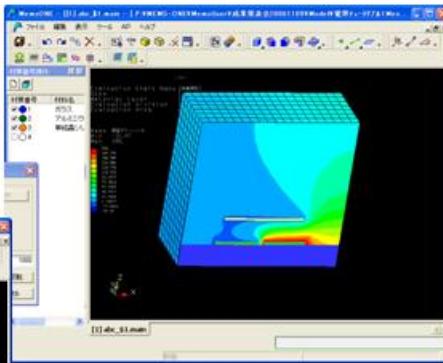
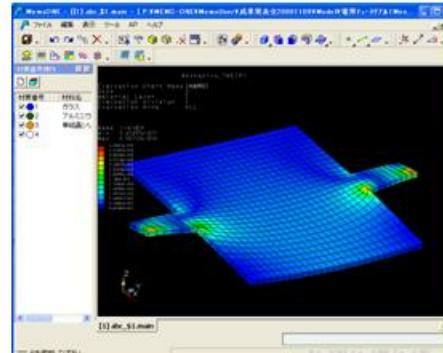


CAD and Solid modeler

Process recipe



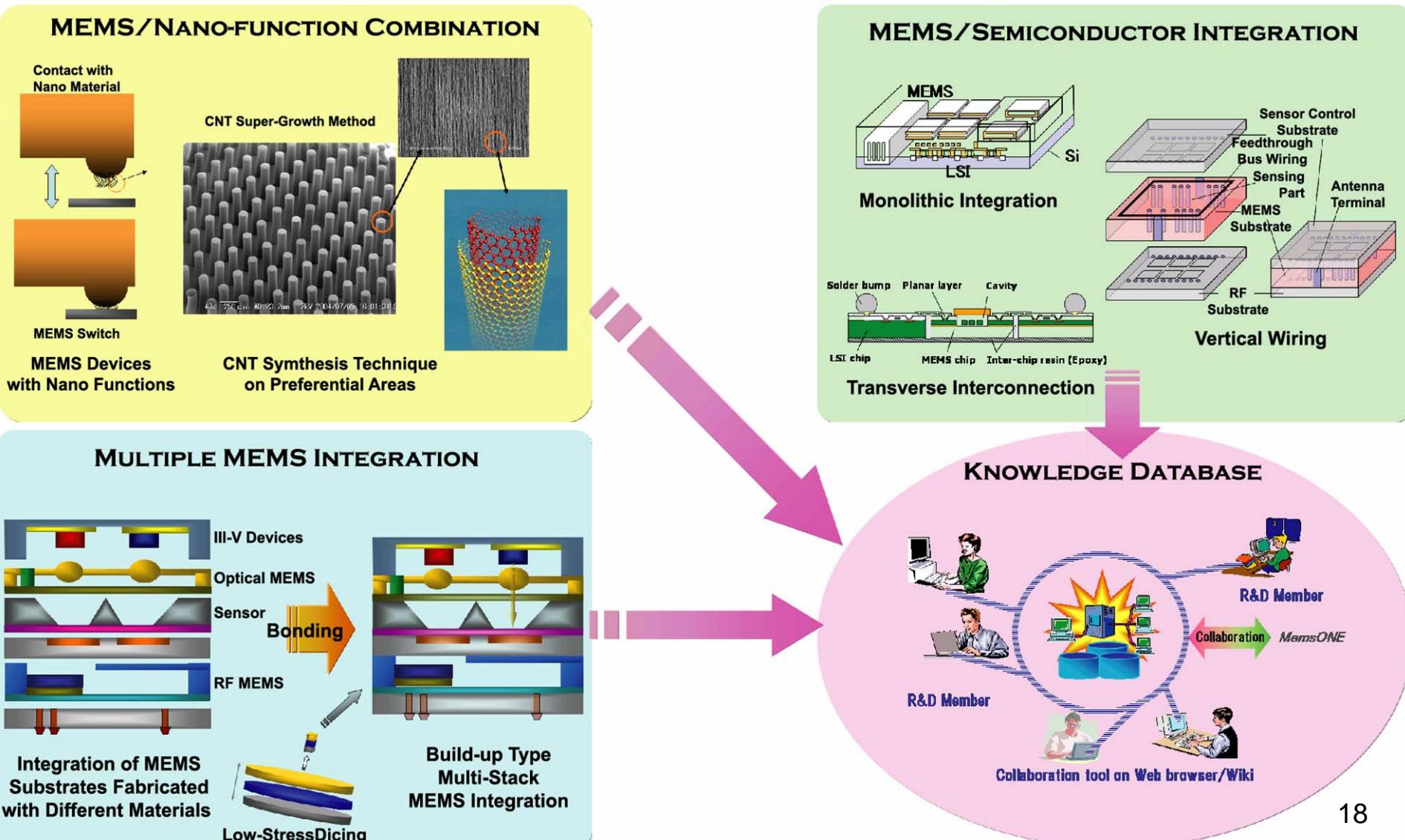
Post-processing



Knowledge database

# fine MEMS Project 2006-2008

## Target Areas for Technology Development



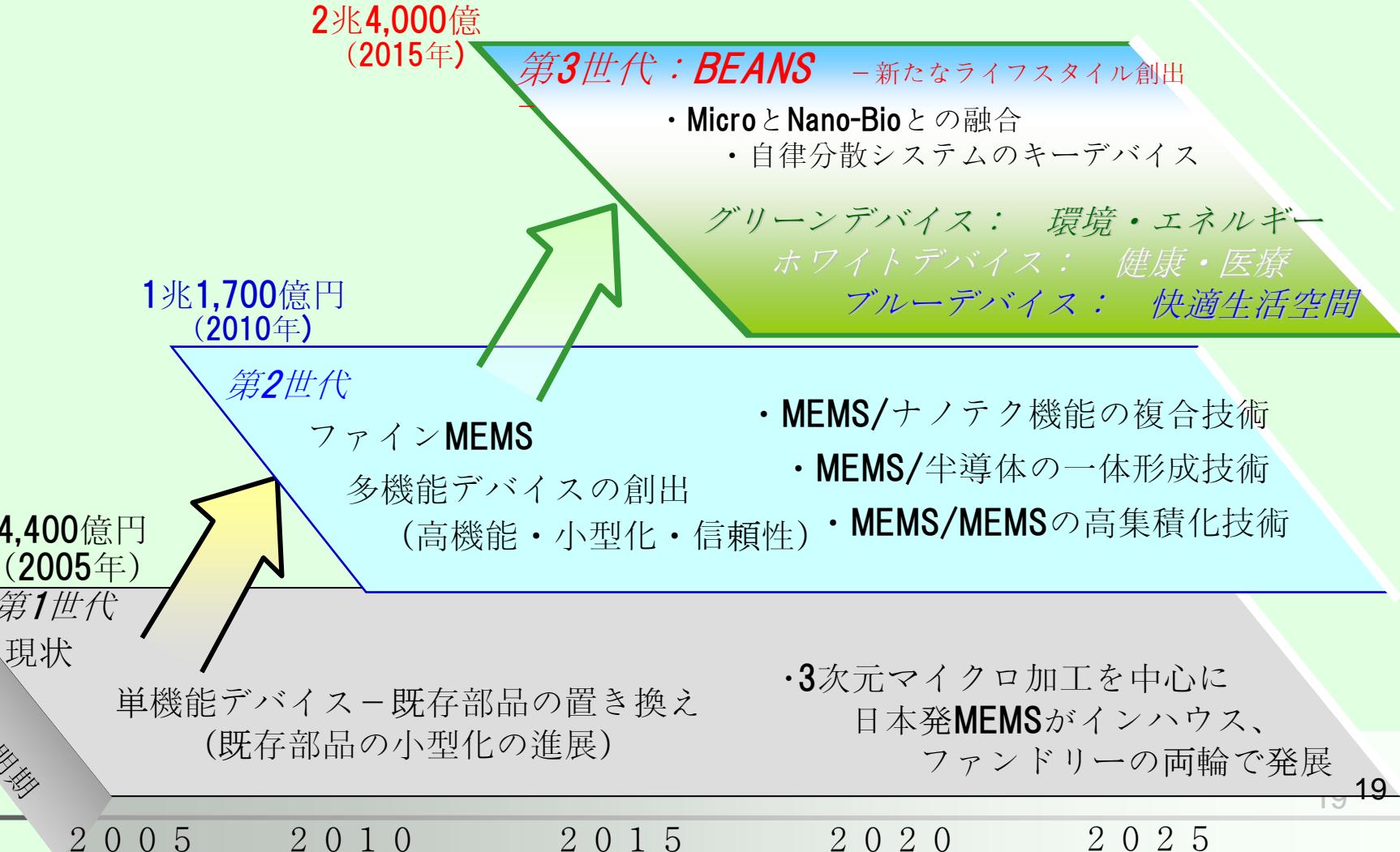
### 3 - 1 MEMS産業・技術ロードマップ

#### BEANS

Bio Electro-mechanical Autonomous Nano Systems

ナノ・バイオと電気機械を融合、自律分散で機能するデバイス・システム

産業高度化(技術の発展と市場の拡大)



## 3 - 2 MEMSデバイスの応用例

### 第3世代MEMS : BEANS

新たなライフスタイルの創生

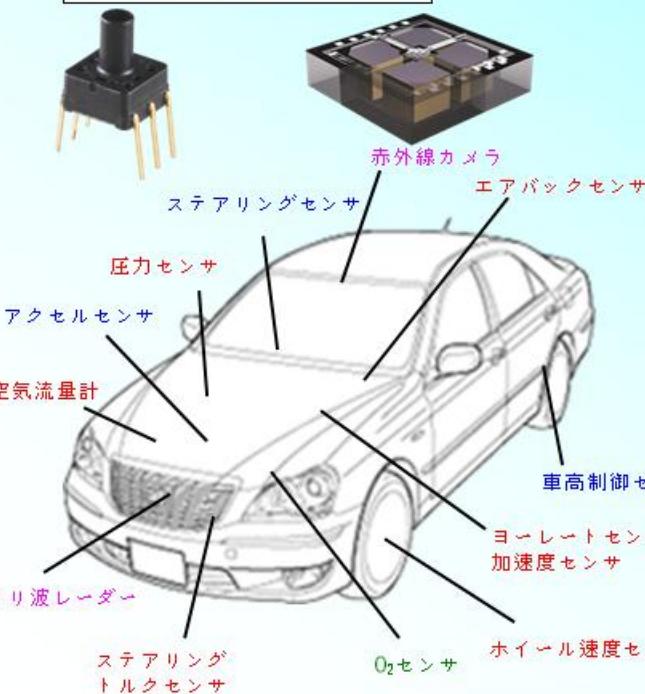
### 第2世代MEMS

集積化・複合化による  
多機能・超小型デバイス

### 第1世代MEMS

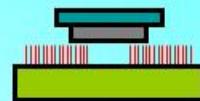
自動車  
1,350億円

エアバッグ 車両安定制  
エンジン制御横転防止

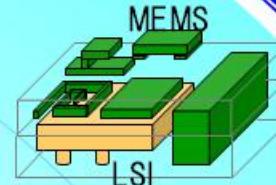


・ MEMS/ナノテク機能複合

CNT応用スイッチ



・ MEMS/半導体一体形成



情報通信  
1,490億円

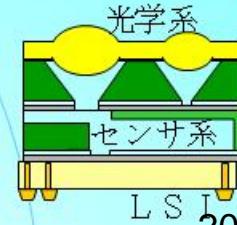
RF MEMS



プロジェクター  
(DMD)



・ MEMS/MEMS高集積化



体内埋込  
デバイス  
生体機械  
ハイブリッドデバイス

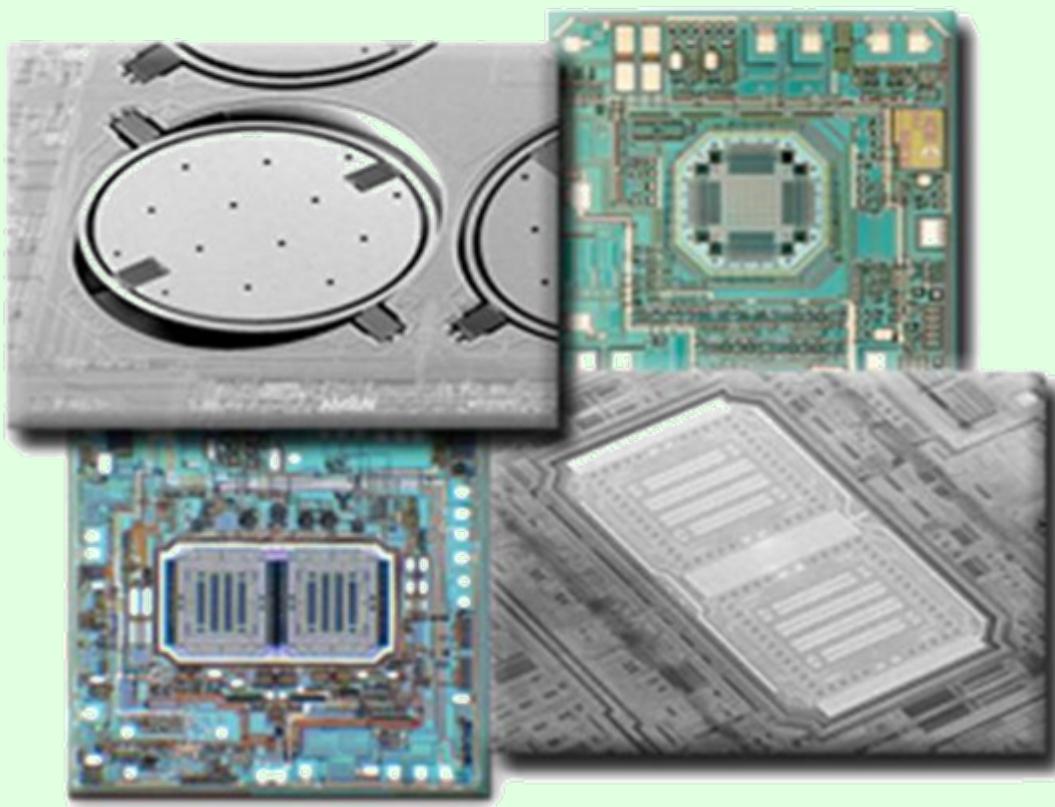
雰囲気  
伝送・再生  
デバイス

シート型  
健康管理  
デバイス

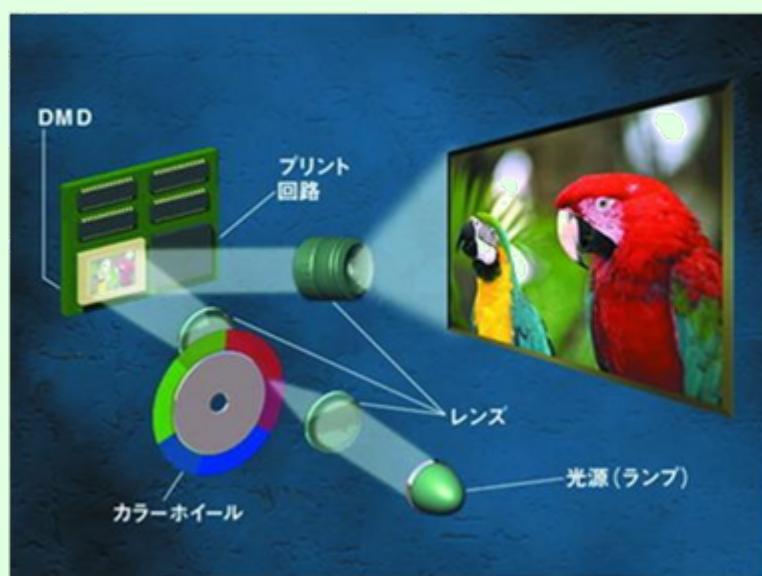
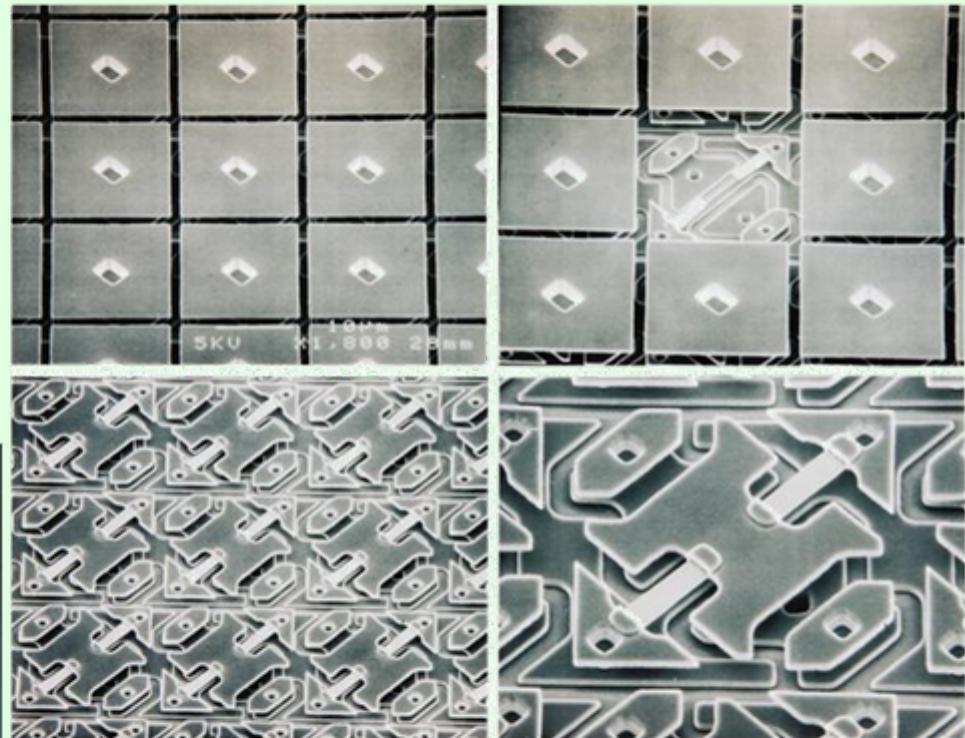
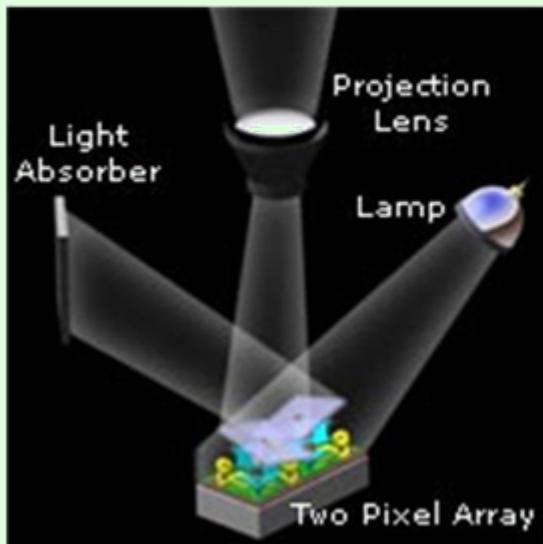
壁紙型  
アンビエント  
インテリジェンス

L S I 20

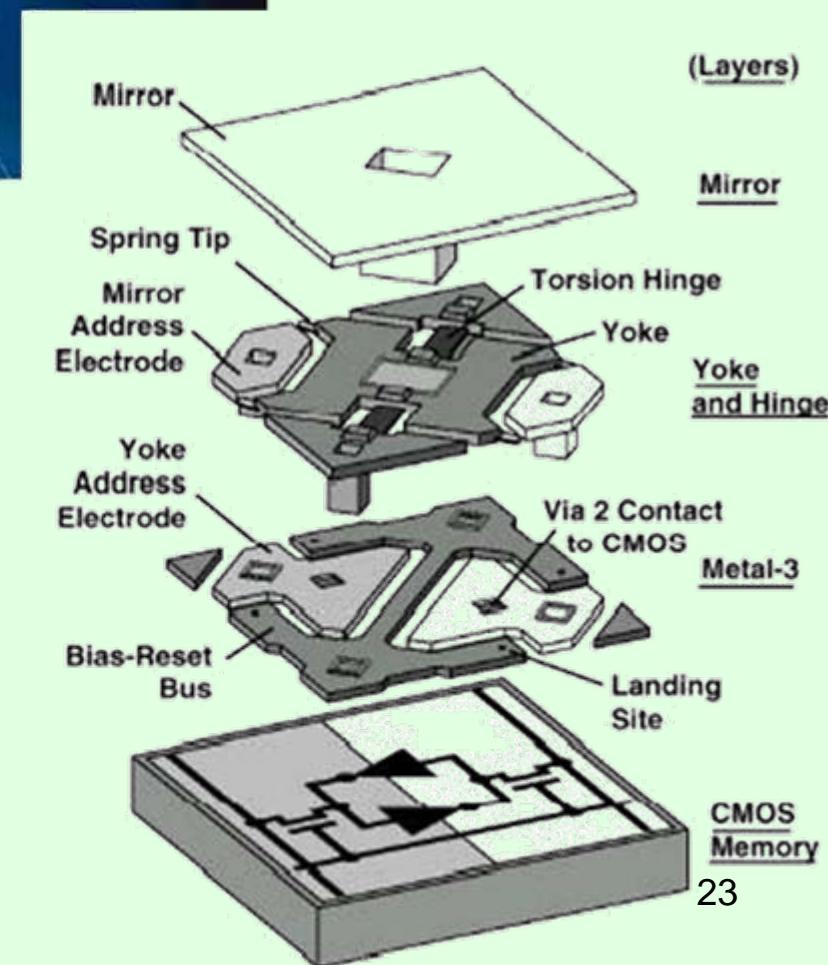
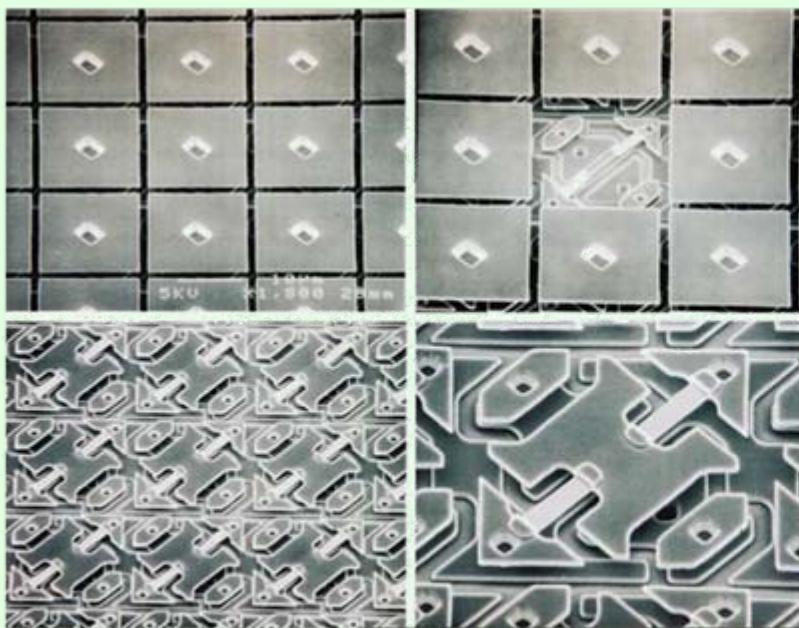
## ***Application of Micro-sensors***



## Digital Mirror Device : TEXAS INSTRUMENTS



# Digital Mirror Device : TEXAS INSTRUMENTS

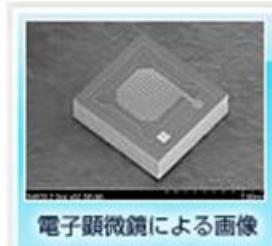


Reference [www.ti.com/dlp/resource/library/](http://www.ti.com/dlp/resource/library/)

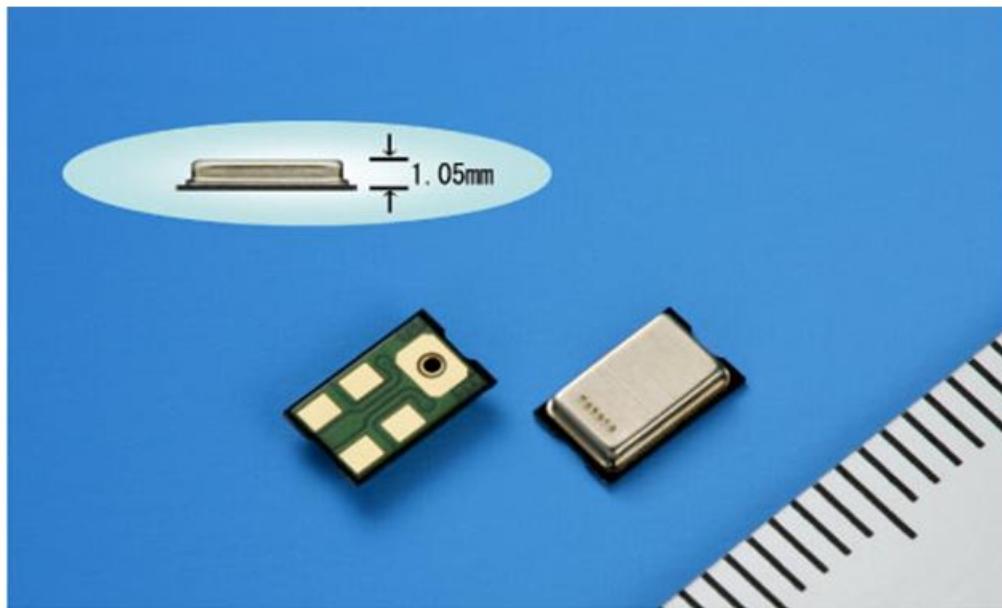
P.F. Van Kessel et al., T.I., Proc. IEEE, Vol. 86, p 1687, 1998

モバイルを変える、ミクロの音響革命。

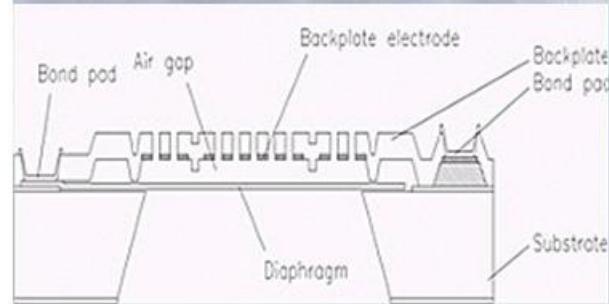
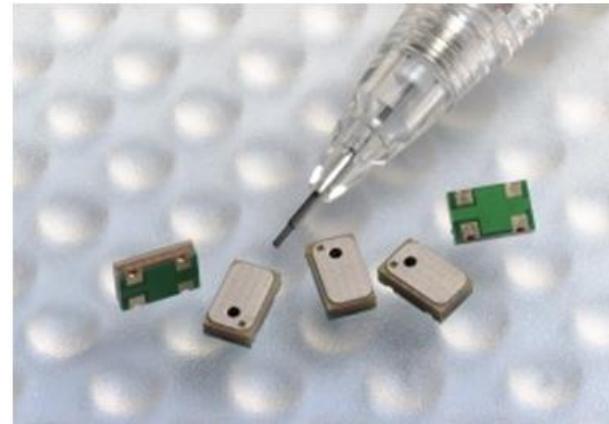
# MEMSマイクロフォン



[http://www.omron.co.jp/ecb/products/me  
msmicro/phonechip/](http://www.omron.co.jp/ecb/products/me msmicro/phonechip/)



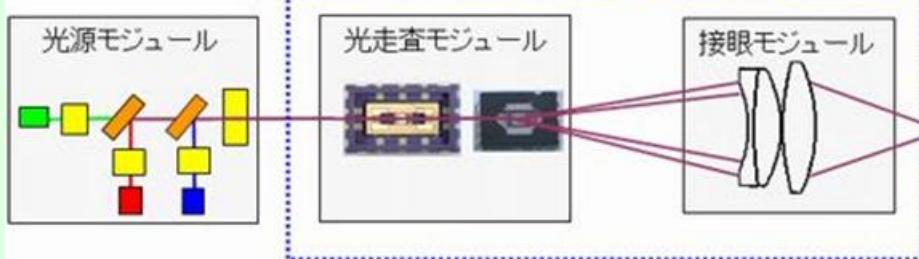
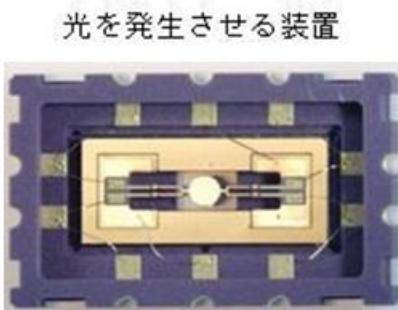
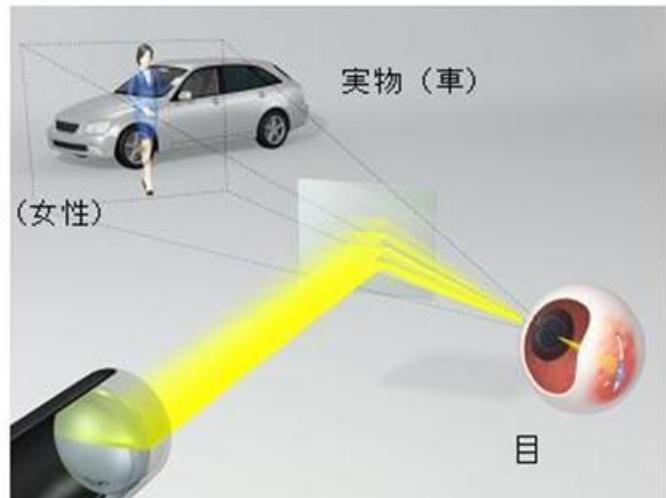
<http://panasonic.co.jp/corp/news/official.data.dir/jn070517-1/jn070517-1.html>



<http://www.knowles.com/search/>

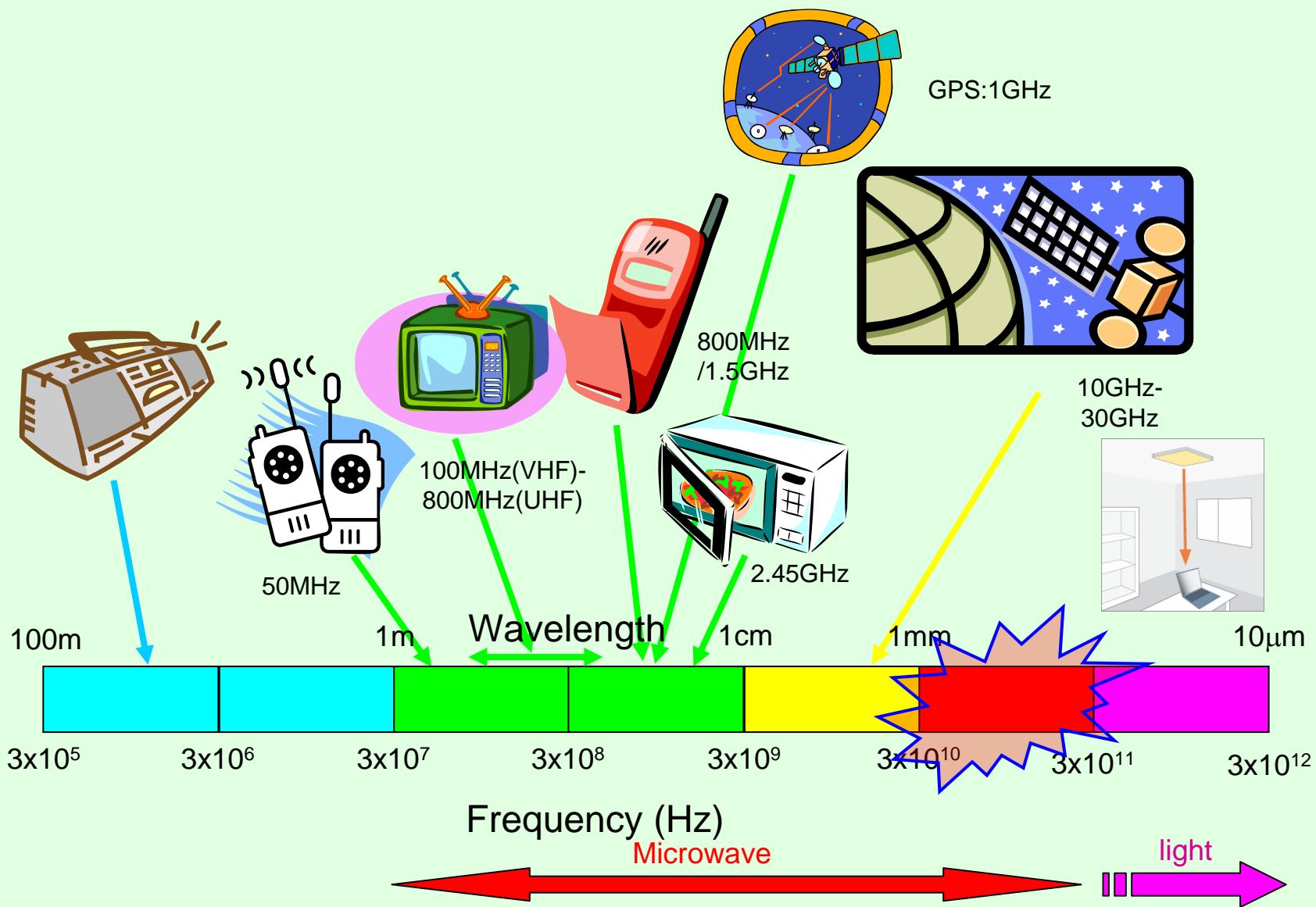
# メガネ型網膜走査ディスプレイを開発

<http://www.brother.co.jp/news/2008/rid/index.htm>



駆動方式  
ミラー径  
光学振角  
周波数  
サイズ : 駆動方式(ピエゾ方式) 共振駆動  
: 約φ1mm  
: 約20°  
: 約30KHz  
: 約 12mm(L)×8mm(W)×2mm(T)

# RF-MEMS



# Application of Wireless Network(1)



## Ubiquitous

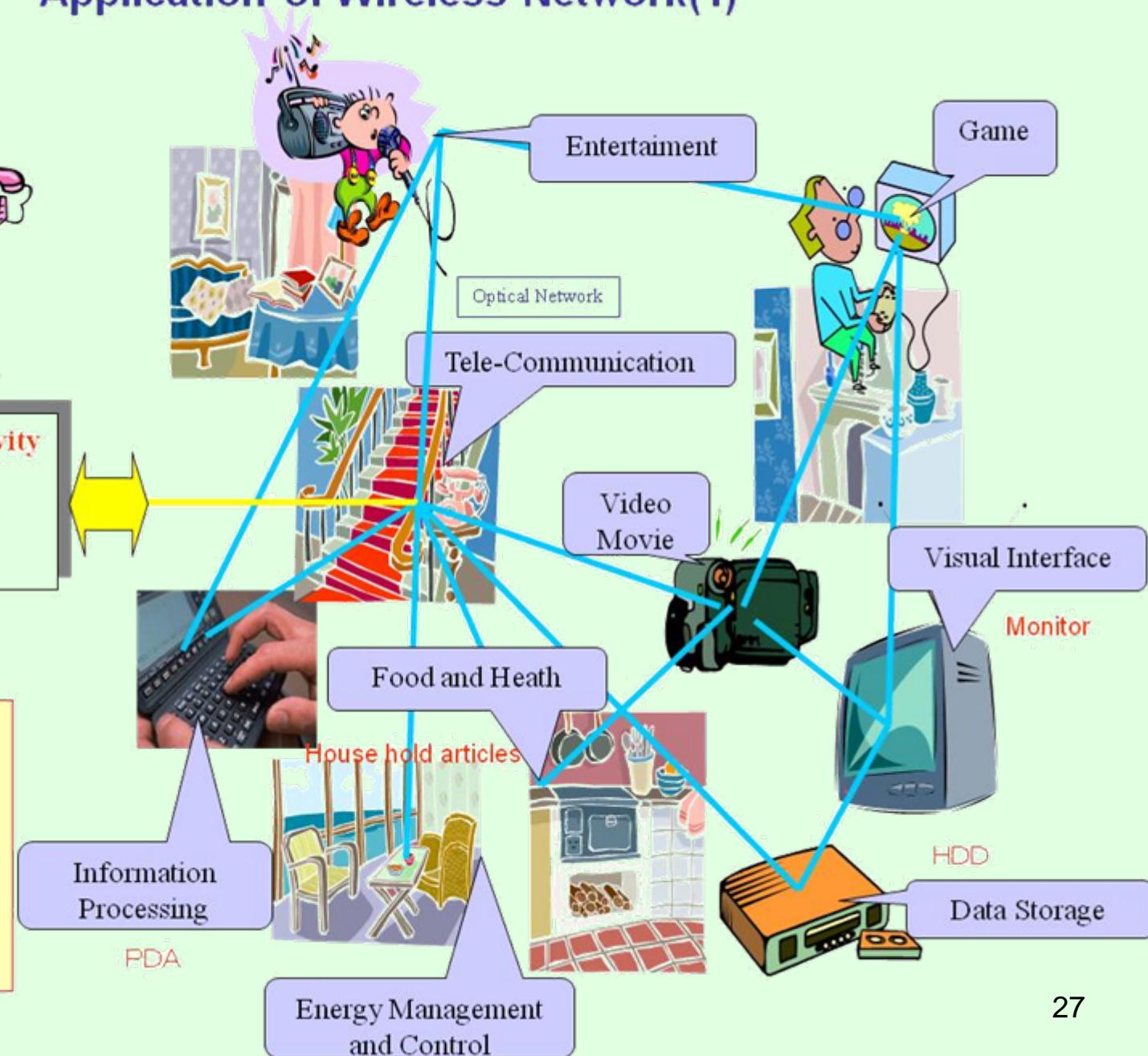
Seamless Connectivity  
with FTTH  
(Fiber To The Home)  
; Last 5m



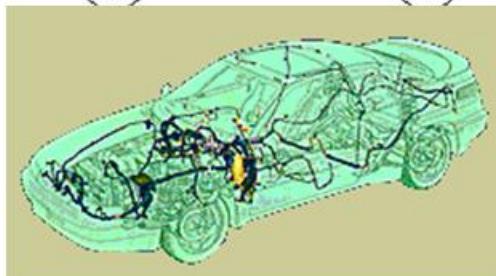
Optical network?

Microwave network?

! Quality comparable  
between wire-line  
network and wireless  
network



# Application of Wireless Network(2)



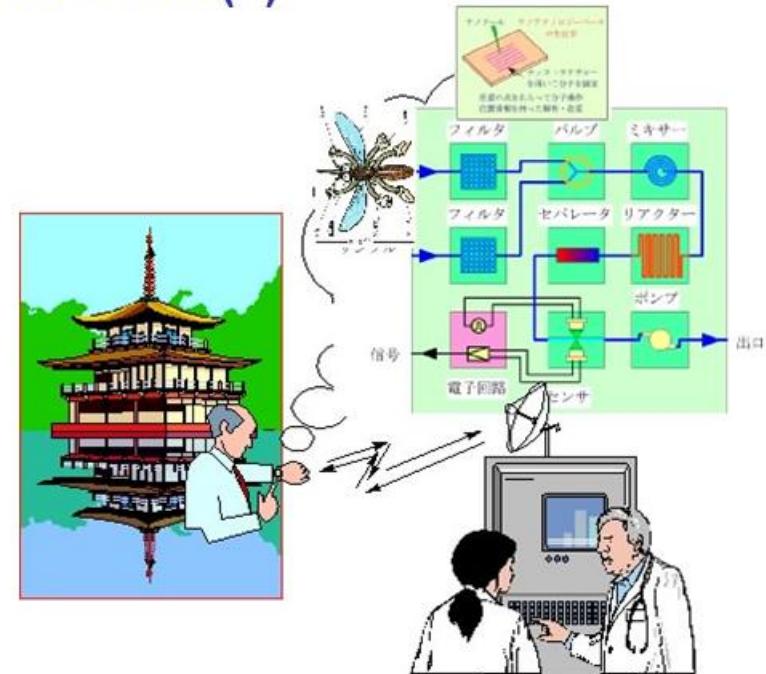
[http://www.fujikura.co.jp/mach\\_elec\\_mate/  
carwire/carwire.htm](http://www.fujikura.co.jp/mach_elec_mate/carwire/carwire.htm)



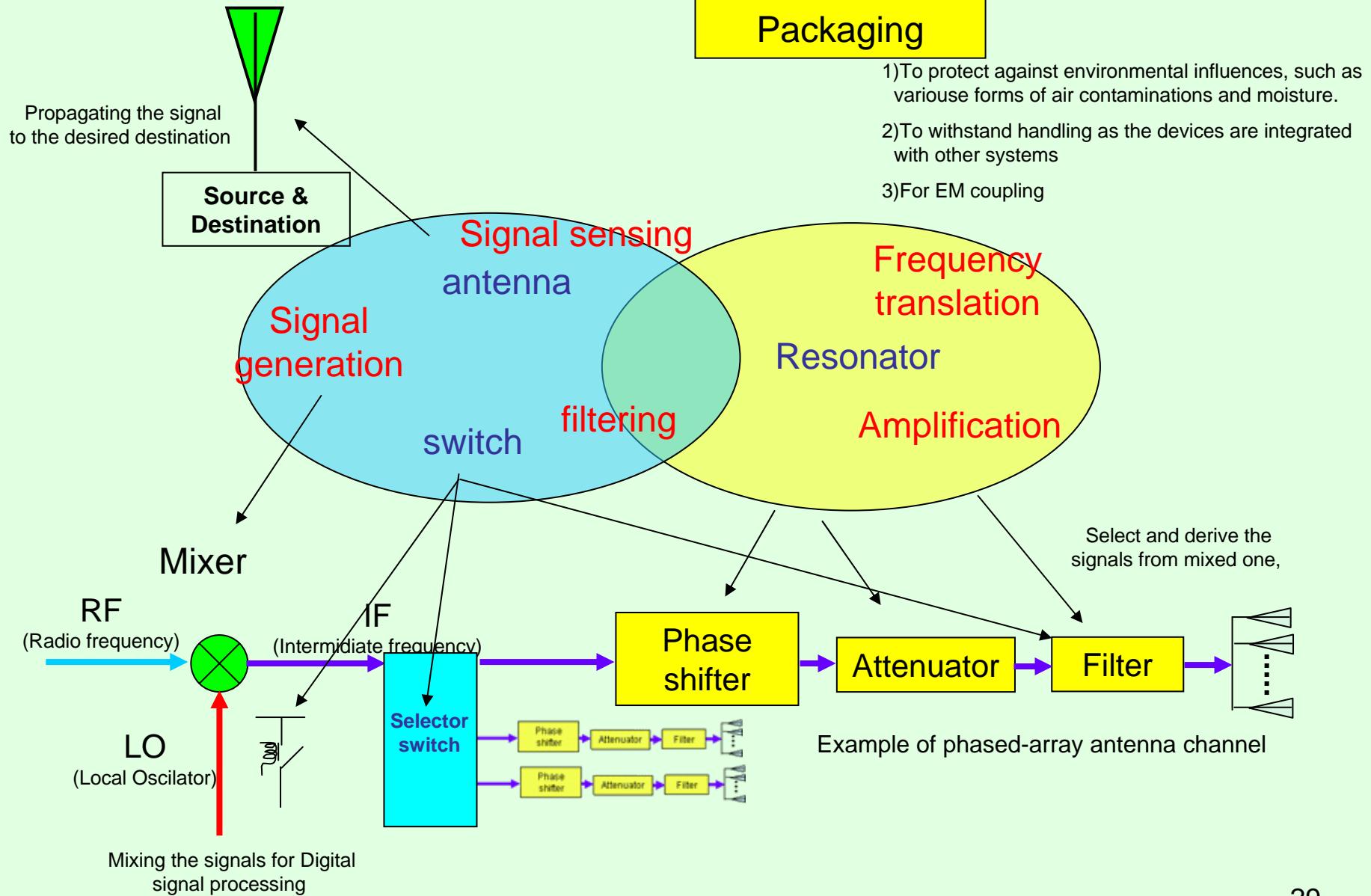
<http://www.is.aist.go.jp/humanoid/hrp-2p/hrp-2p.htm>



Tele-monitoring



# Components for RF communication



## Switching speed relates to the resonant frequency of the switch

$$f = \frac{1}{2\pi} \sqrt{K/M}$$

K is equivalent Young's Modulus and M is Mass

INTEGRATED FIVE-BIT RF MEMS PHASE SHIFTER FOR SATELLITE BROADCASTING/COMMUNICATION SYSTEMS

Young J. Ko, Jae Y. Park, Hong T. Kim and Jong U. Bu

Microsystem Group,

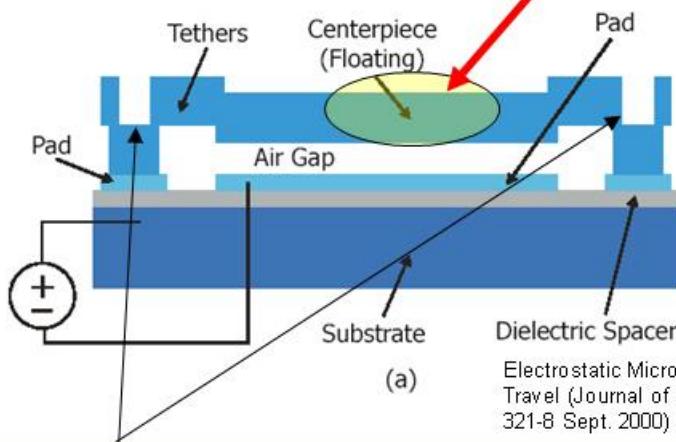
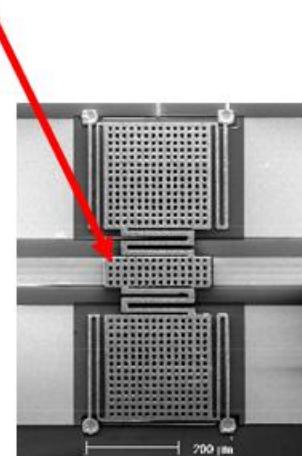
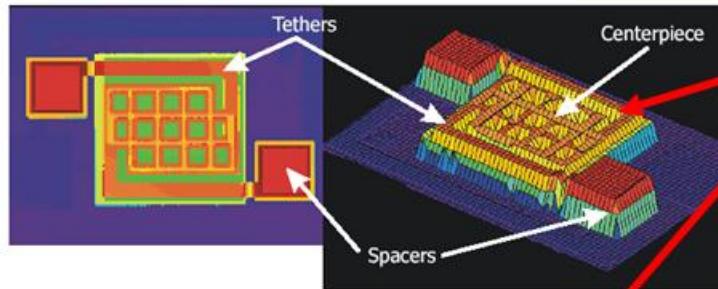
Materials and Devices Laboratory,

LG Electronics Institute of Technology,

16 Woomyeon-Dong, Seocho-Gu, Seoul, 137-724, Korea

Telephone: 82-2-526-4486, Fax: 82-2-3461-3508, E-mail: kojoon@lge.com

There are through holes to reduce the total mass and to decrease the Reynold's stress



Electrostatic Micromechanical Actuator with Extended Range of Travel (Journal of Microelectromechanical Systems, Vol. 9, No. 3, pp. 321-8 Sept. 2000) Edward Chang and R.Dutton

Reduce K to gain the deflection and to reduce the driving voltage

Driving voltage may be 20V up to 50V

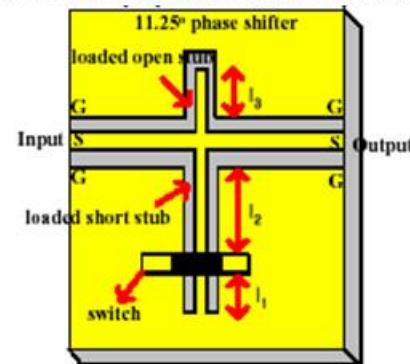


Figure 6. Schematic drawing of the phase shifter with 11.25°-phase bit.

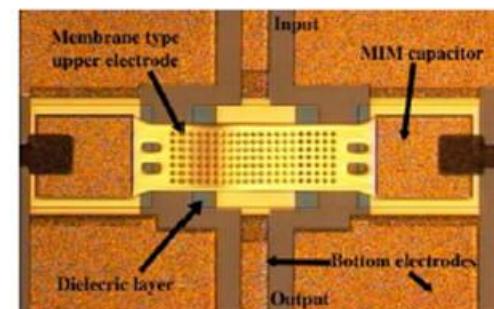
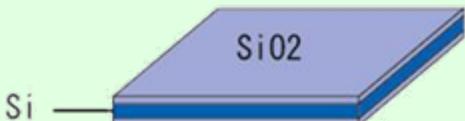


Figure 2. Photograph of MEMS capacitive shunt switch

MEMS2003 pp.144

# Fabrication process of the X-bar type actuator



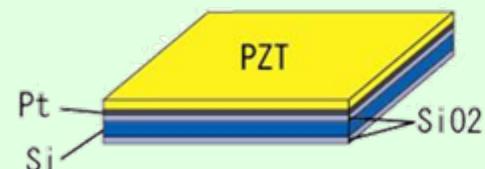
(1) Prepare the thermal-oxidized Si substrate



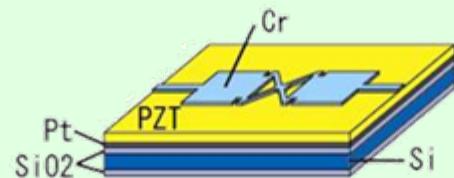
(2) Ti sputtering



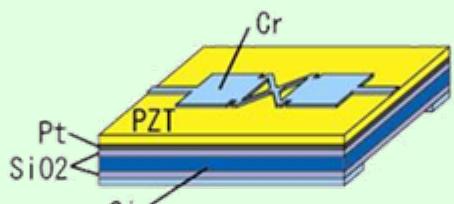
(3) Pt sputtering



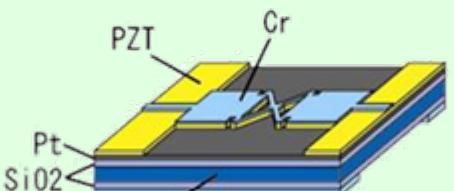
(4) PZT sputtering



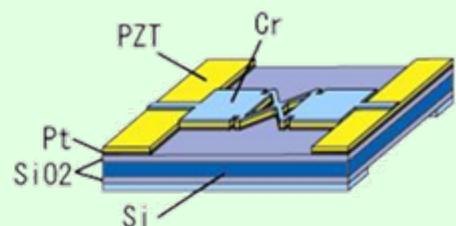
(5) Cr patterning by lift off process  
(Electrode)



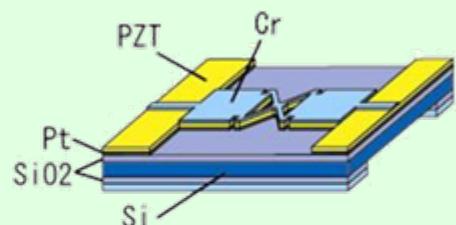
(6) Cr patterning by lift off process  
(Metal mask)



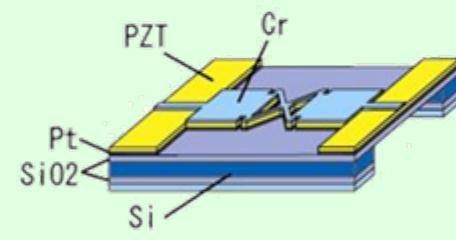
(7) PZT wet etching



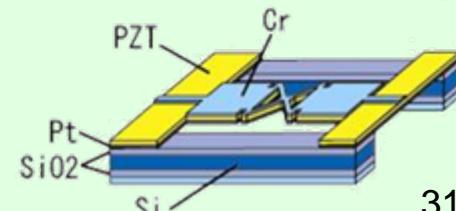
(8) Ti/Pt dry etching (Ar)



(9) SiO<sub>2</sub> dry etching (CF<sub>4</sub>+O<sub>2</sub>)

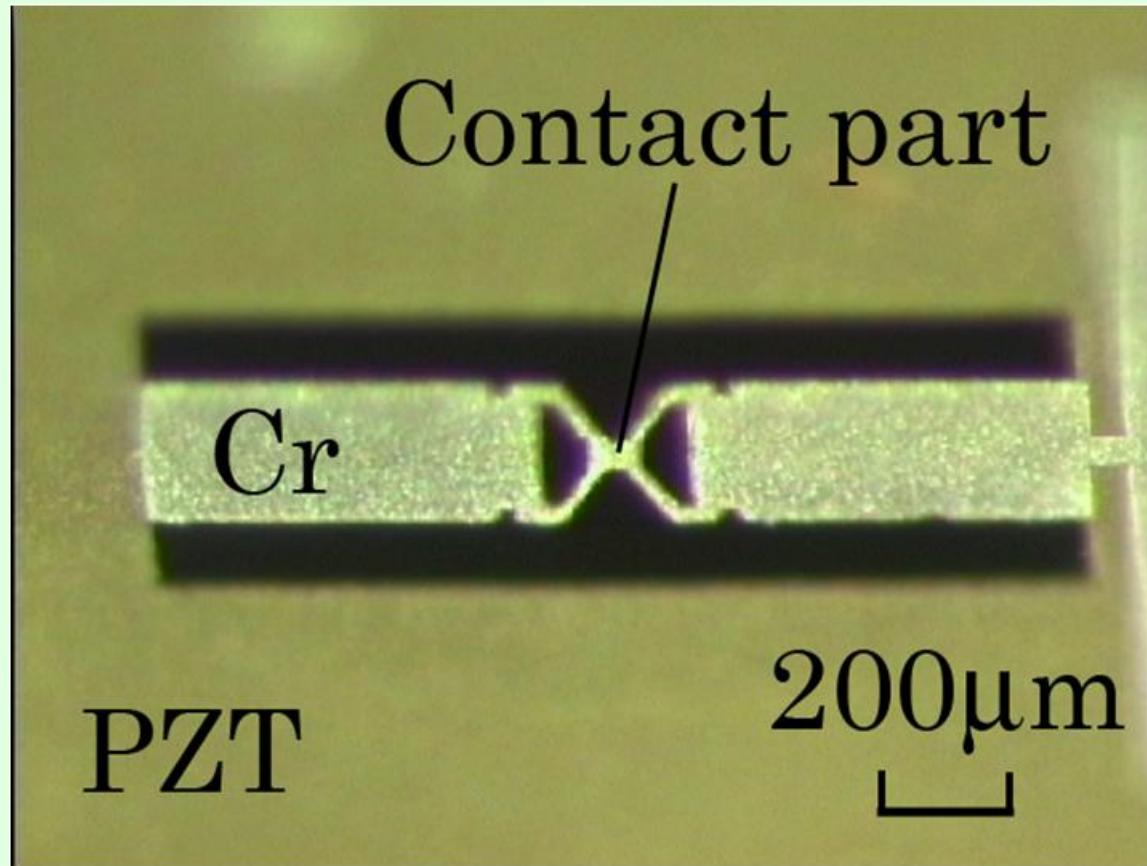


(10) Si dry etching (SF<sub>6</sub>)



(11) SiO<sub>2</sub> dry etching (CF<sub>4</sub>+O<sub>2</sub>)

# Fabricated X-bar actuator



Fabricated X-bar actuator

$800\mu\text{m}$  in length,  $200\mu\text{m}$  in width,

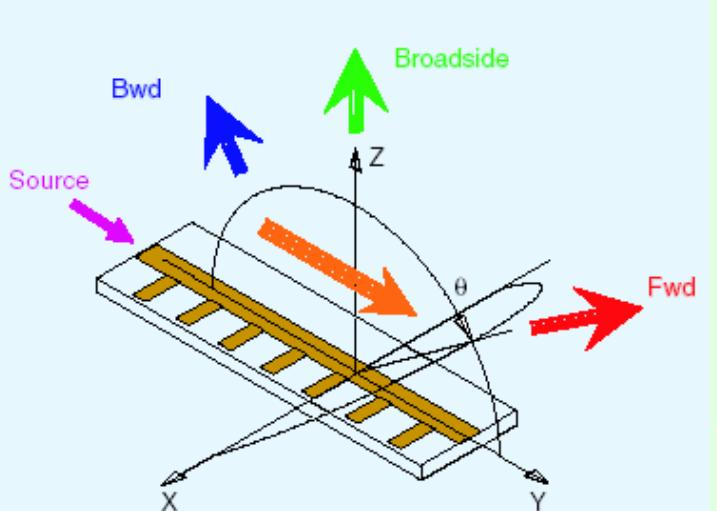
$3.4\mu\text{m}$  in thickness

(Pt:100nm,PZT:2.5 $\mu\text{m}$ ,Cr:0.8 $\mu\text{m}$ )

# Composite Right/Left-Handed Metamaterial and Metastructure for designing the reconfigurable Millimeter wave antenna (M<sup>3</sup>-project)

**Definition:** Metamaterial and Metastructure are artificial structures that can be designed to exhibit specific electromagnetic properties not commonly found in nature.

The Russian physicist Veselago presented about theory of metamaterials with simultaneously negative permittivity ( $\epsilon$ ) and permeability ( $\mu$ ) in 1967, which are commonly referred to as left-handed materials. ( V.Veselago," The electrodynamics of substances with simultaneously negative values of  $\epsilon$  and  $\mu$ ", Soviet Physics Uspekhi, Vol.10,No.4,pp.509-514,1967)



Lai, A.; Itoh, T.; Caloz, C., "Composite right/left-handed transmission line metamaterials", IEEE Microwave magazine, Vol.5, Issue 3.2004 pp. 34- 50

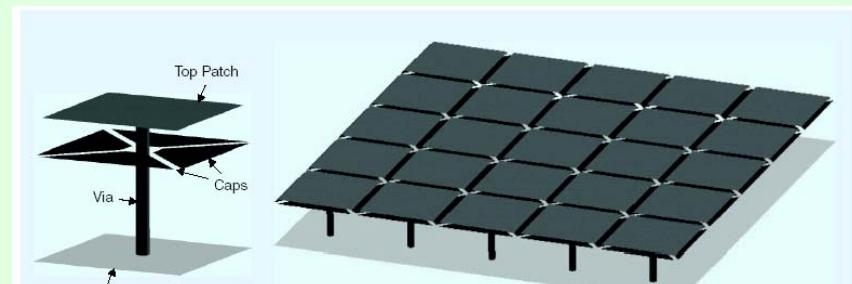
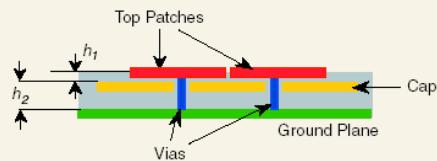
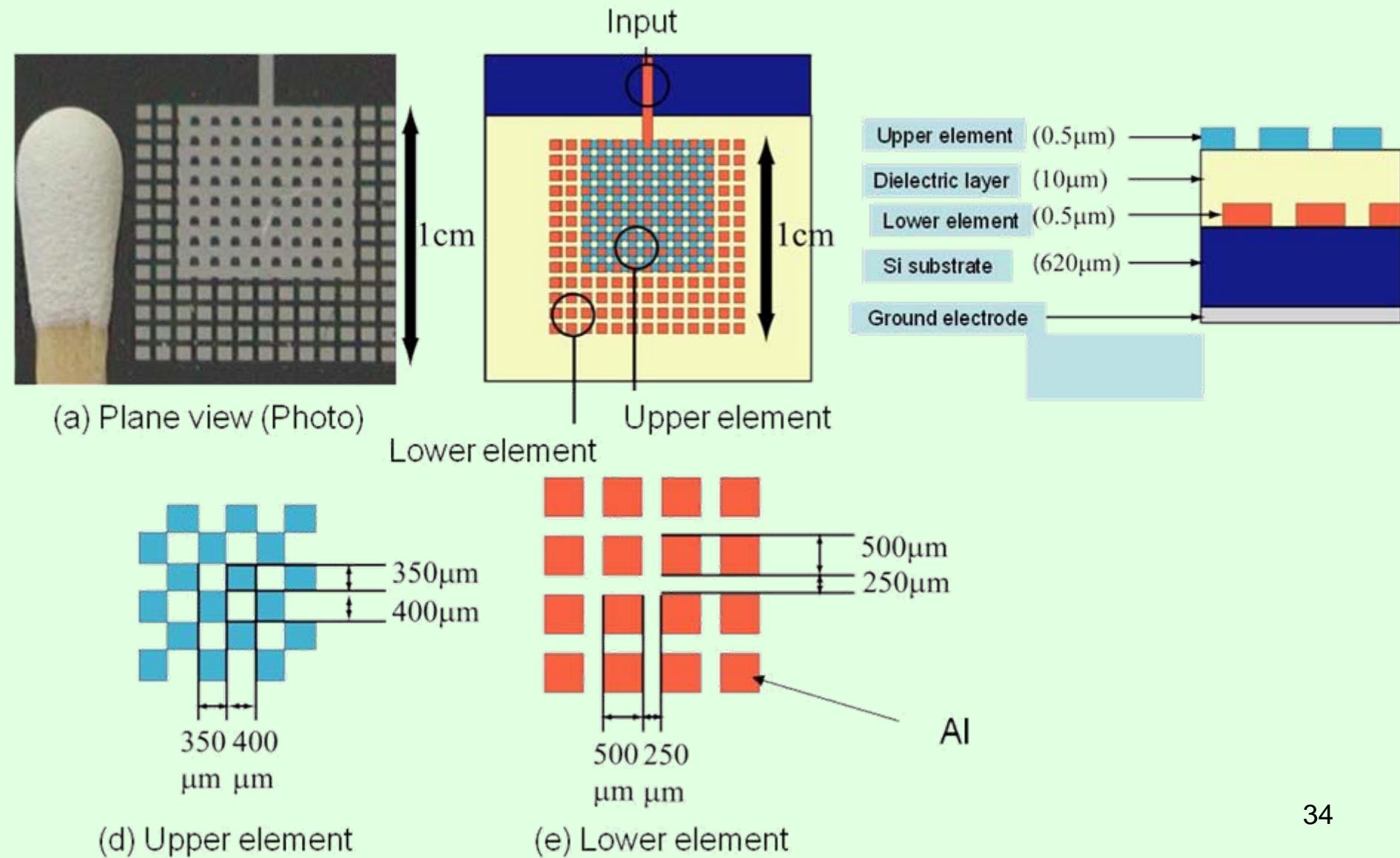


Figure 11. Open 2-D CRLH mushroom structure. (a) Unit cell [14]. (b) 2-D CRLH structure formed by periodic repetition of the unit cell. The caps are floating (not connected to the vias) patches located at a short distance from the connected patch to enhance  $C_L$  contribution [14].



A. Sanada, C. Caloz, and T. Itoh, "Planar distributed structures with negative refractive properties," *IEEE Trans. Microwave Theory Tech.*, vol. 52, pp. 1252–1263, Apr. 2004.

# Structure of DLME antenna



## Phased array antenna type 1

### Horn-array type Millimeter wave antenna

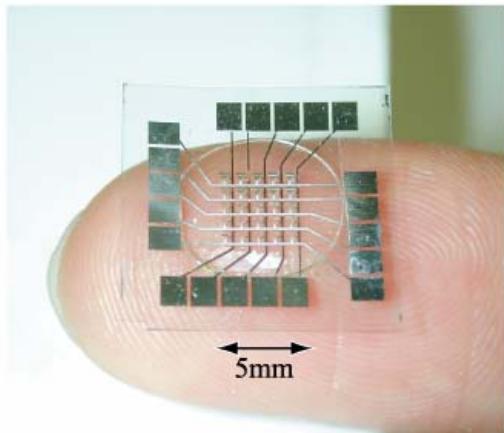


Figure1.Horn array antenna

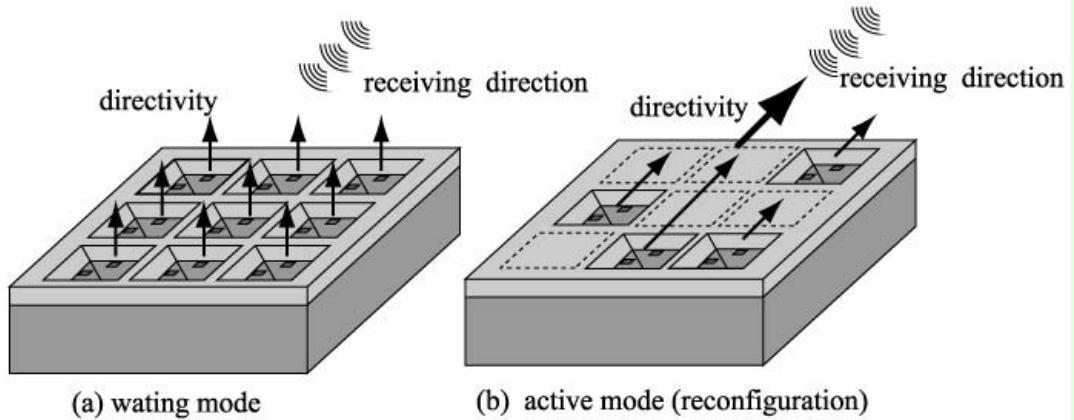


Figure3. Reconfigurable directivity by calculated receiving wave strength

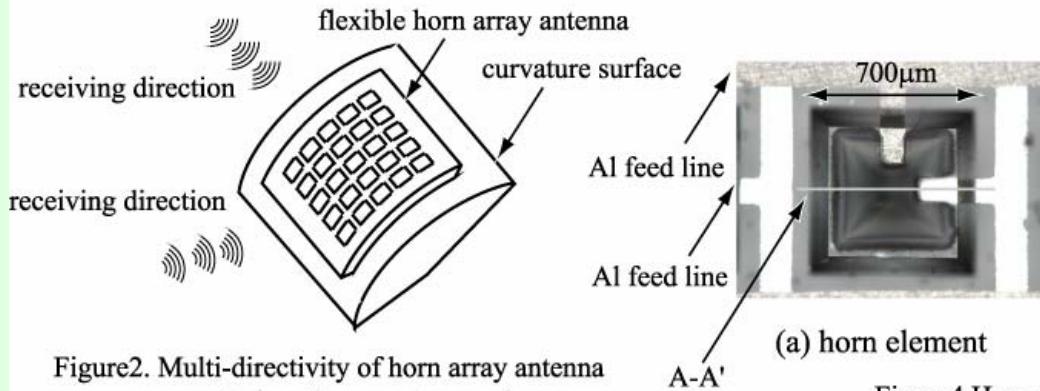


Figure2. Multi-directivity of horn array antenna mounted on the curvature surface

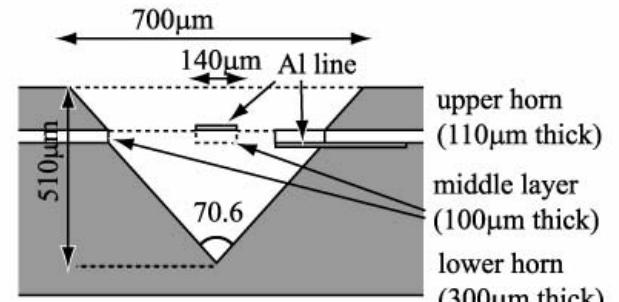
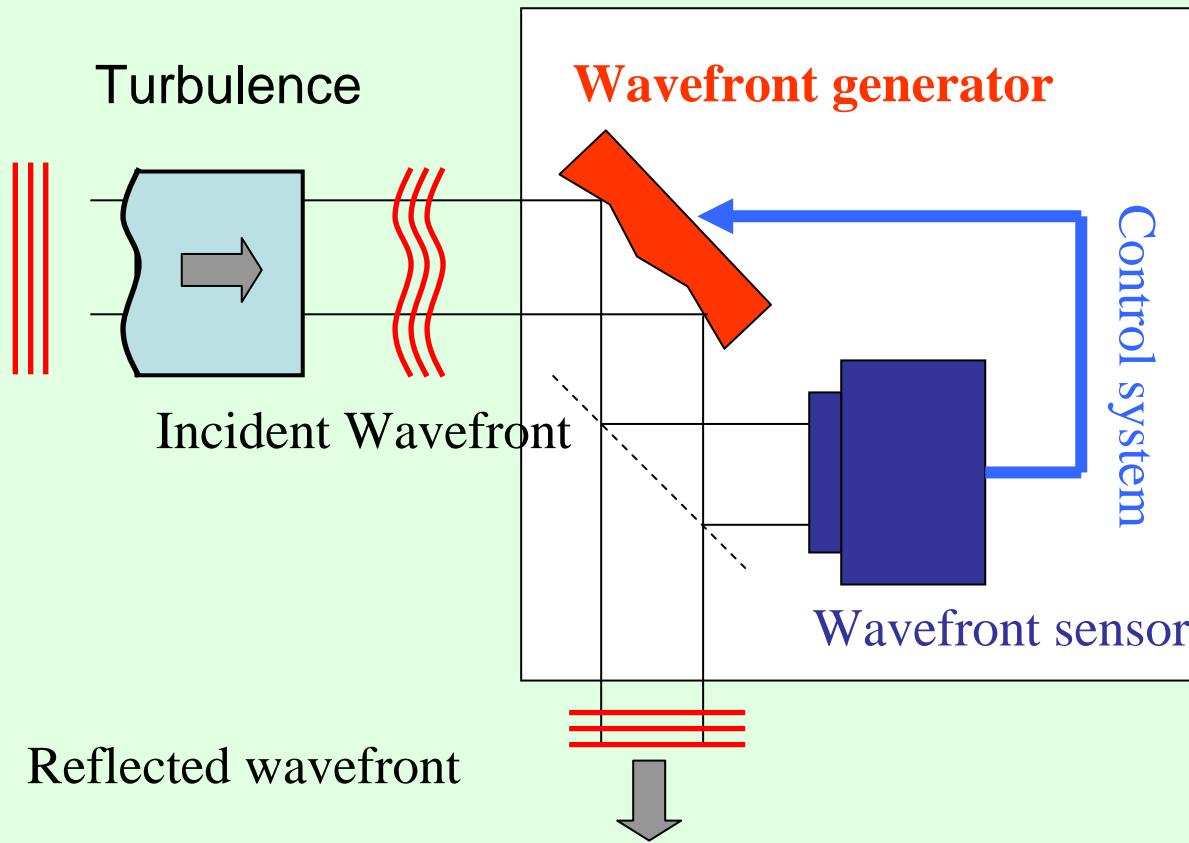


Figure4.Horn array antenna composed of three layers

# Adaptive Optics system

Adaptive optics is used for correction of disturbed wave front.  
This technology has been developed in astronomy.

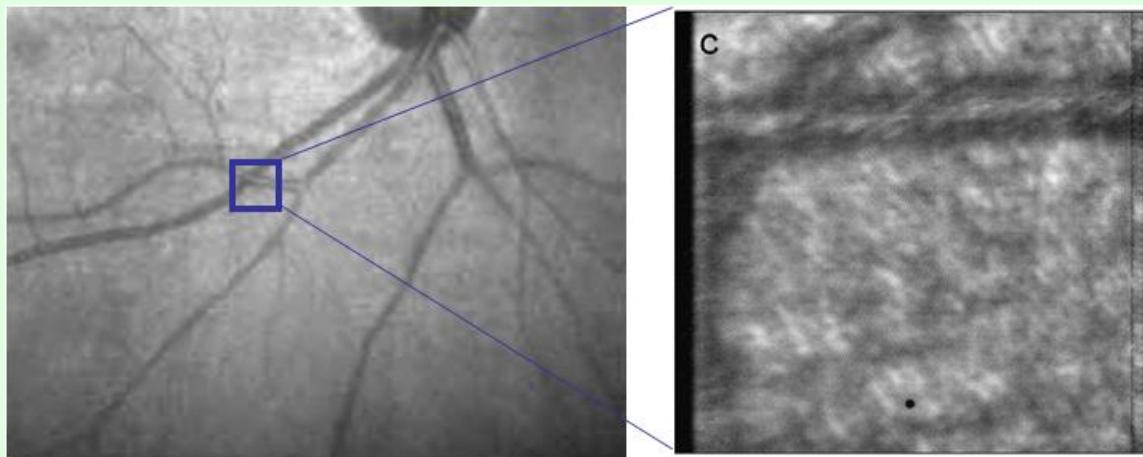


# 眼底検査

眼底の検査

↓ 診断

網膜はく離, 緑内障  
糖尿病, 動脈硬化



眼底画像(走査型レーザー検眼鏡で撮影)

Daniel X. Hammerら撮影

眼科だけでなく  
内科などの他診療科に  
とって基本&重要

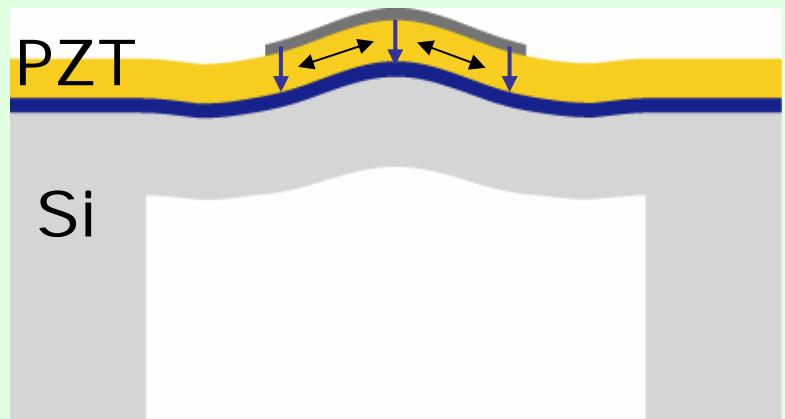
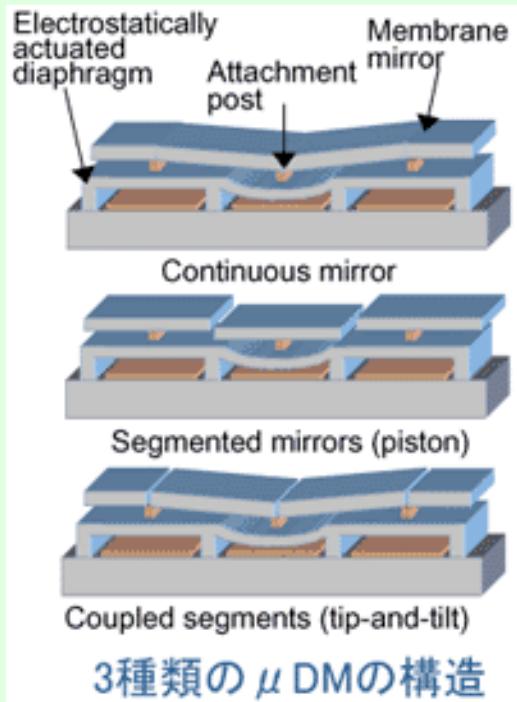
眼球は生体の中でもとりわけ  
透明度の高い伝播媒質

しかし

検査光は眼球内部で歪み,  
波面収差を持つ

補償光学装置で波面収差を  
取り除くことが必要

# Structure of Piezoelectric Deformable Mirror

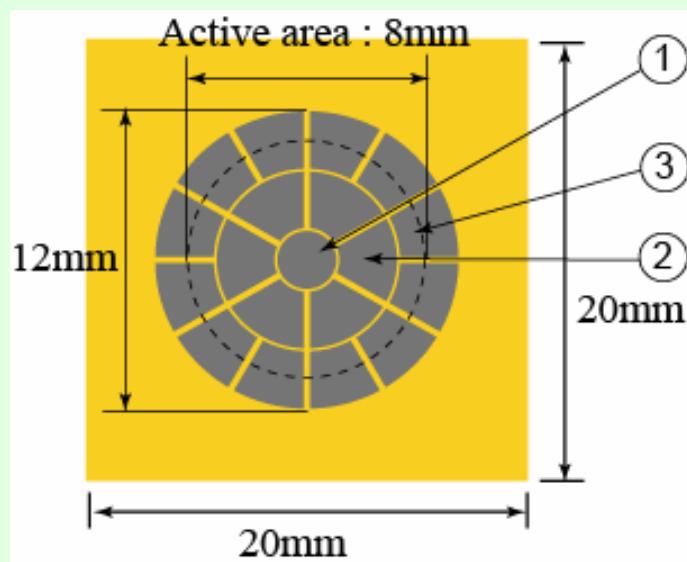
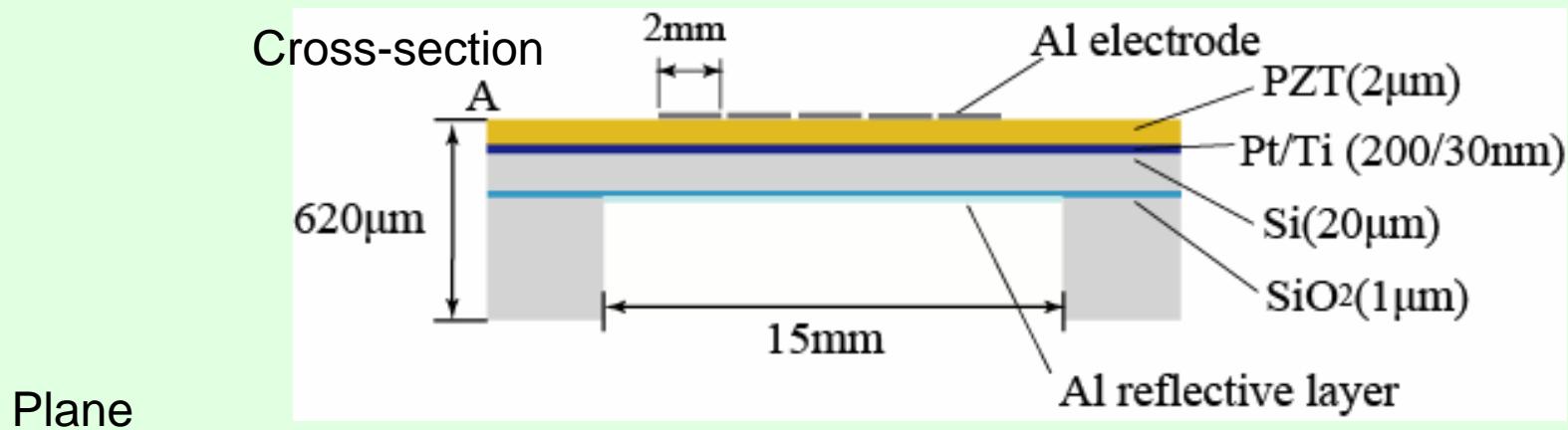


## Principle & structure

Boston MEMS  
Electrostatic Actuator

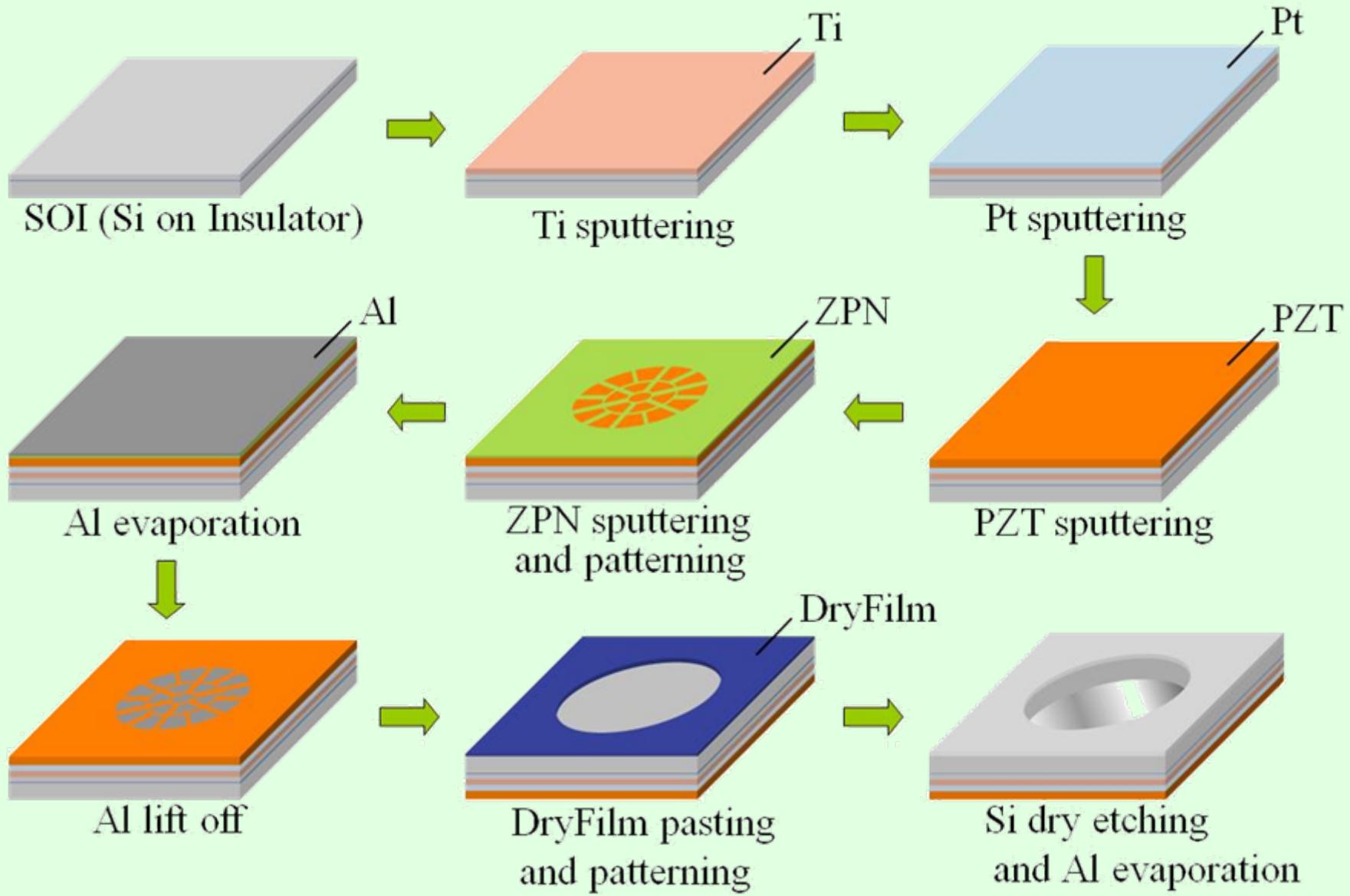
Piezoelectric thin film  
→  $\pm 10V$ ,  $> 1\text{ KHz}$ , Simple structure

# Structure



- Unimorph actuator array is composed of PZT films (2  $\mu$  m) and Si(20  $\mu$  m)
- 19 segmented ring electrode on PZT film
- Al reflective layer on SiO<sub>2</sub> in SOI

# 作製プロセス

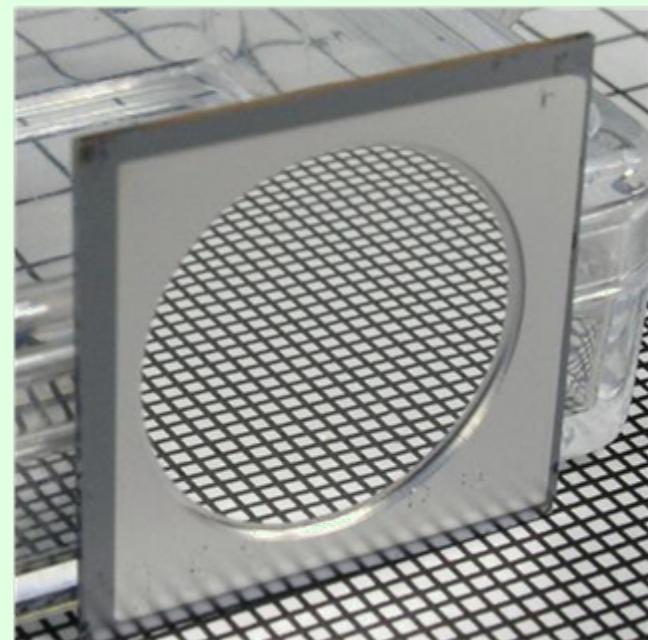


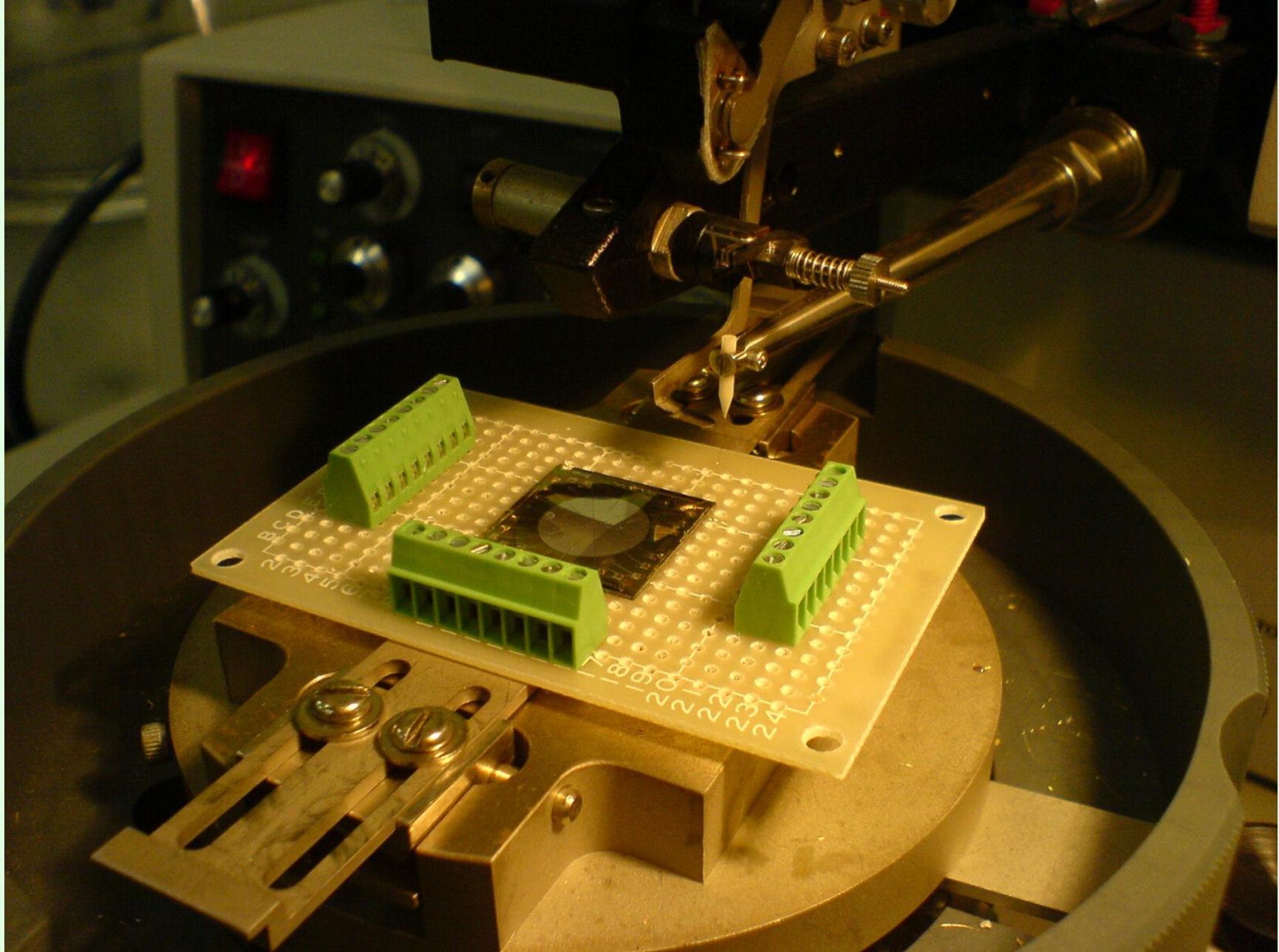
# Photographs of mirror

Actuator side



Mirror side

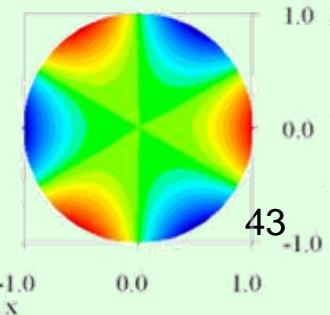
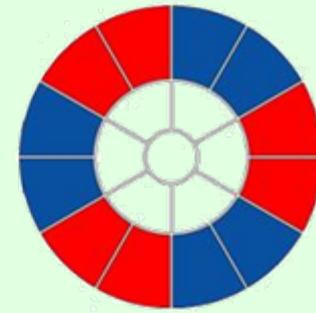
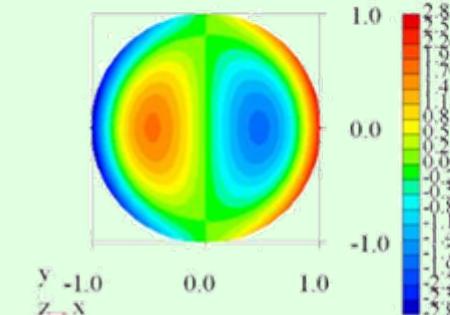
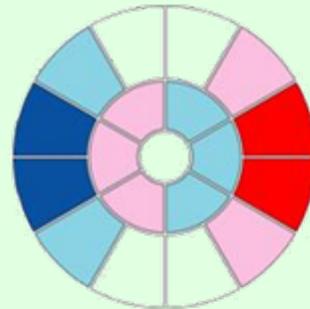
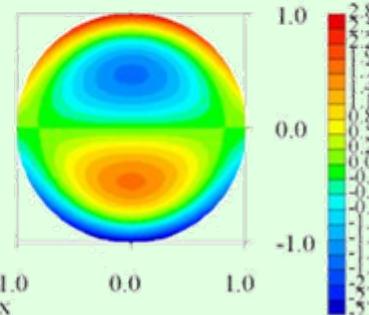
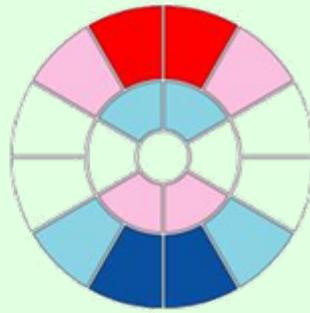
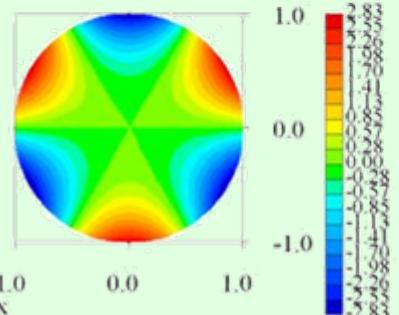
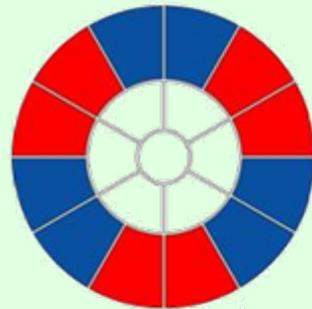
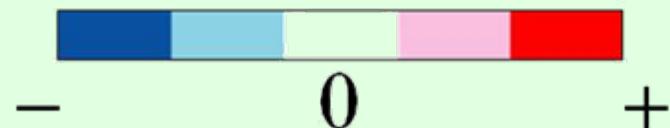




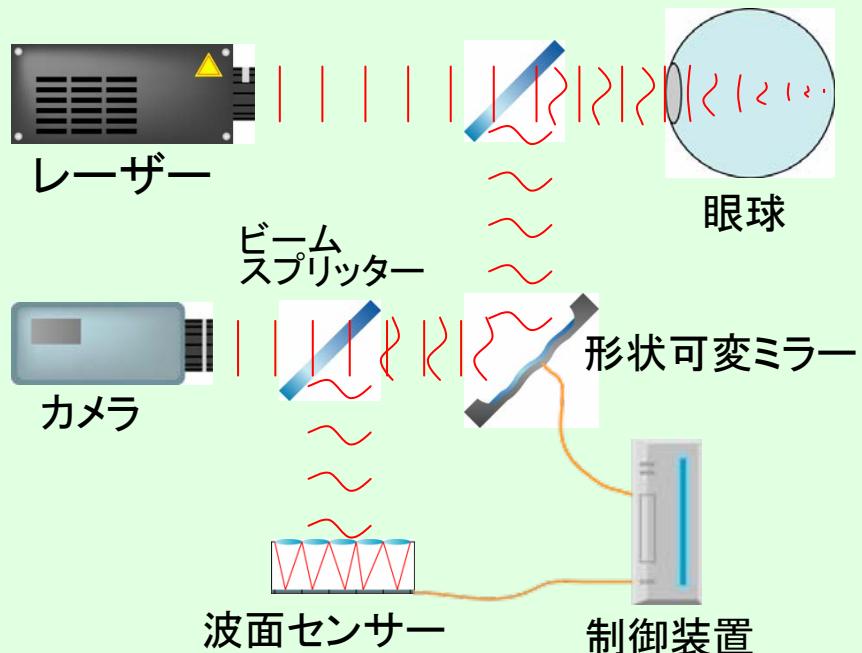
# 上部電極の設計

## ゼルニケ形状3次の再現を考え設計

上部電極の印加電圧



# 波面補償光学装置

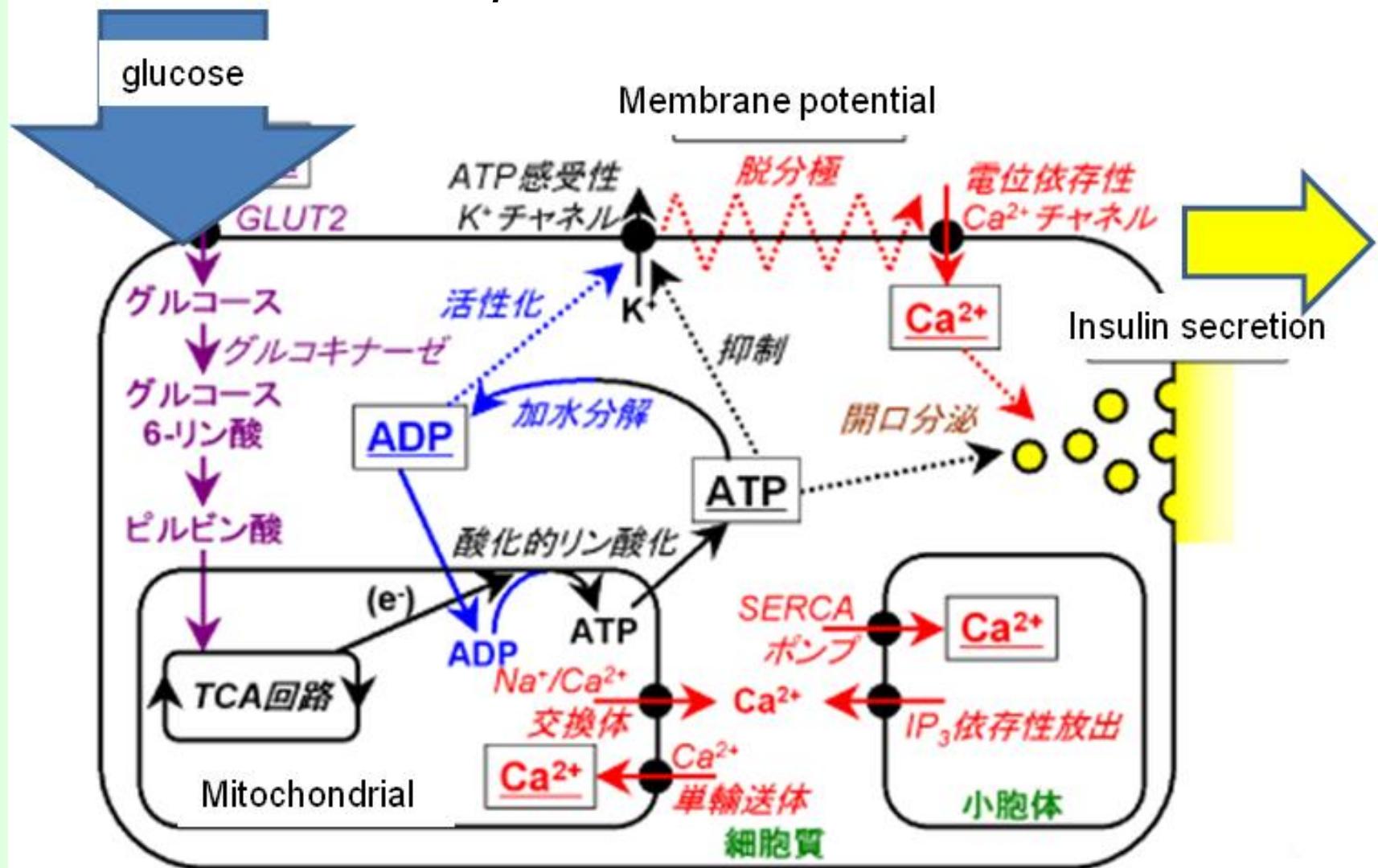


## システム図

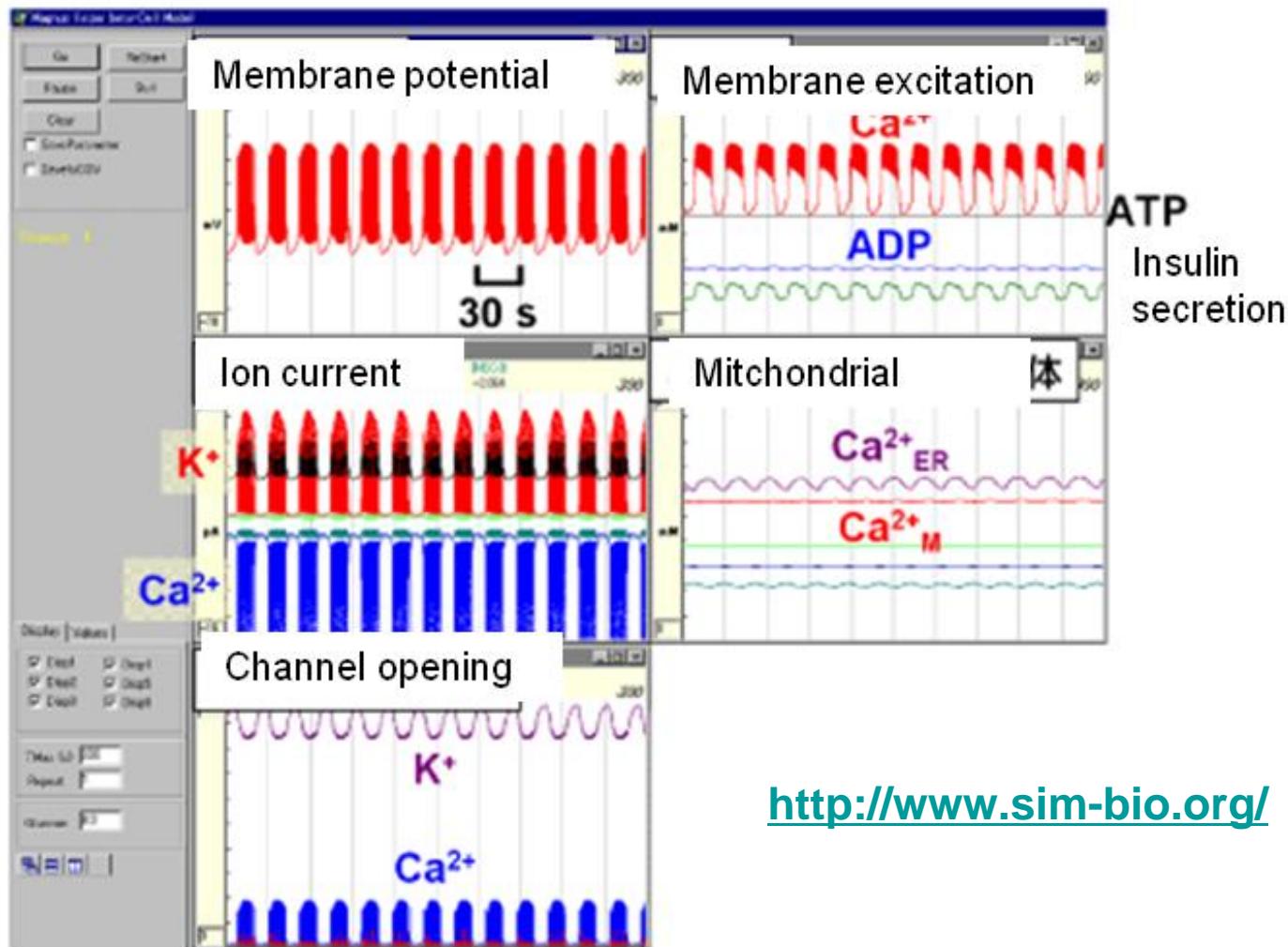
- ①眼底からの反射光を  
波面センサーによって測定
- ②波面収差を打ち消すように  
光路中に置いた形状可変  
ミラーを変形させる
- ③反射光は波面収差を  
補正される

# Measuring Cell–Cell Communication and Regeneration of tissue

# Pancreas $\beta$ cell (insulin secretion)



# Bio Simulator



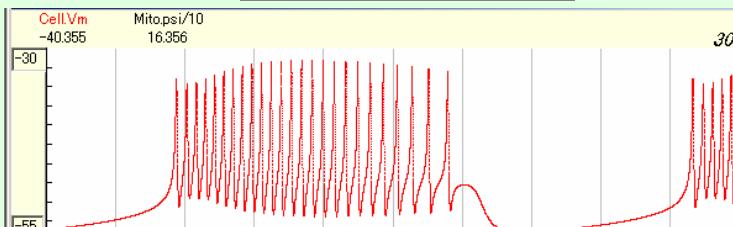
<http://www.sim-bio.org/>

# Pancreas $\beta$ cell (insulin secretion): Type 2 Diabetes

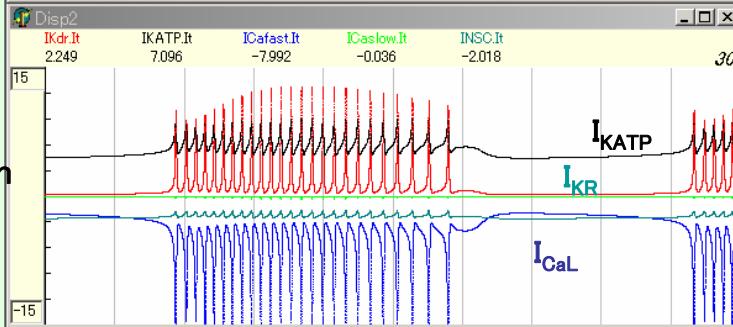
Normal glucose

High glucose

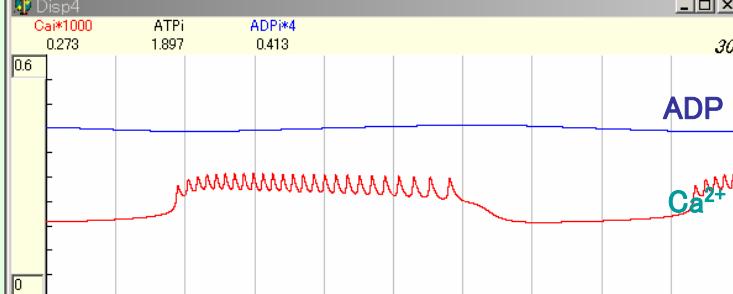
Membrane potential



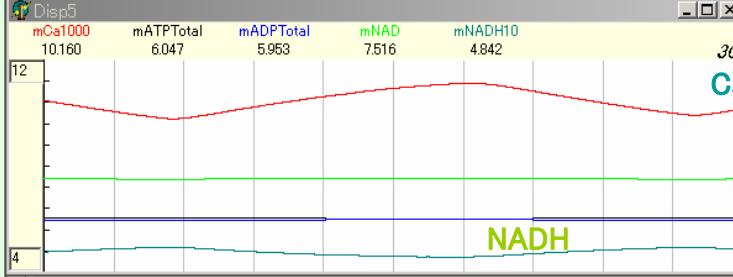
Channel protein actuation



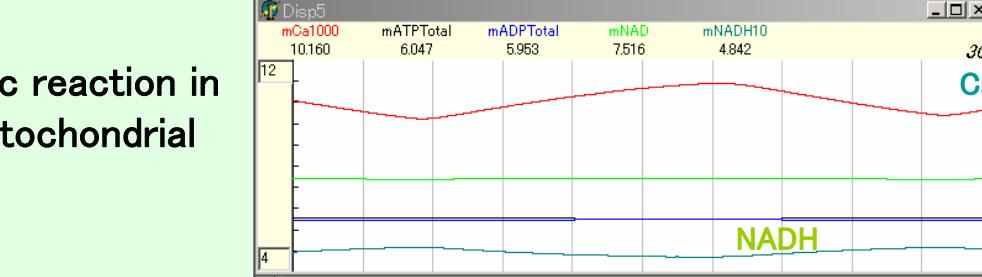
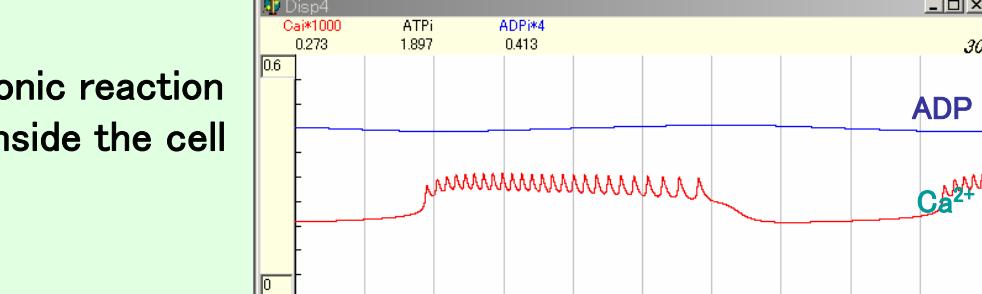
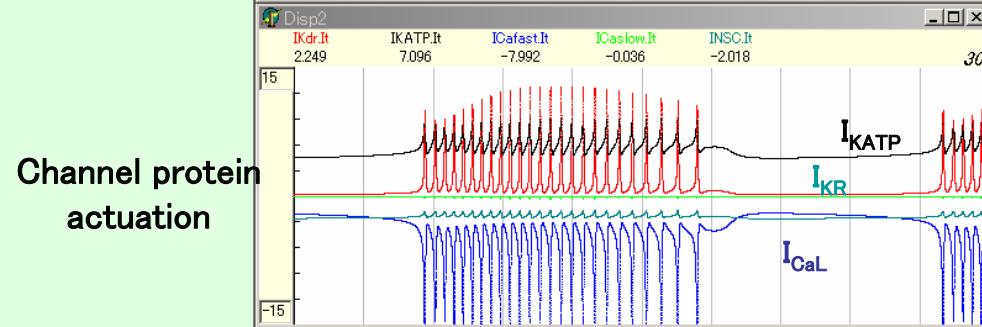
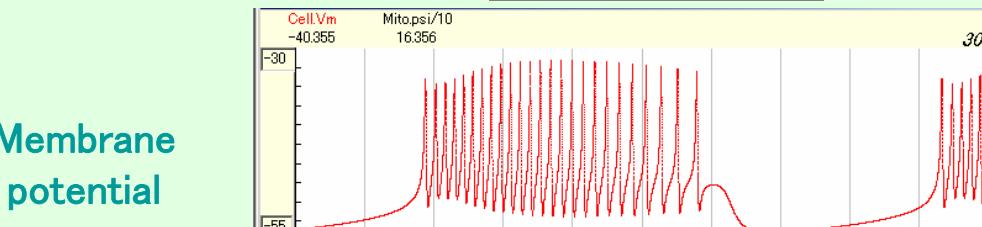
Ionic reaction inside the cell



Ionic reaction in mitochondrial



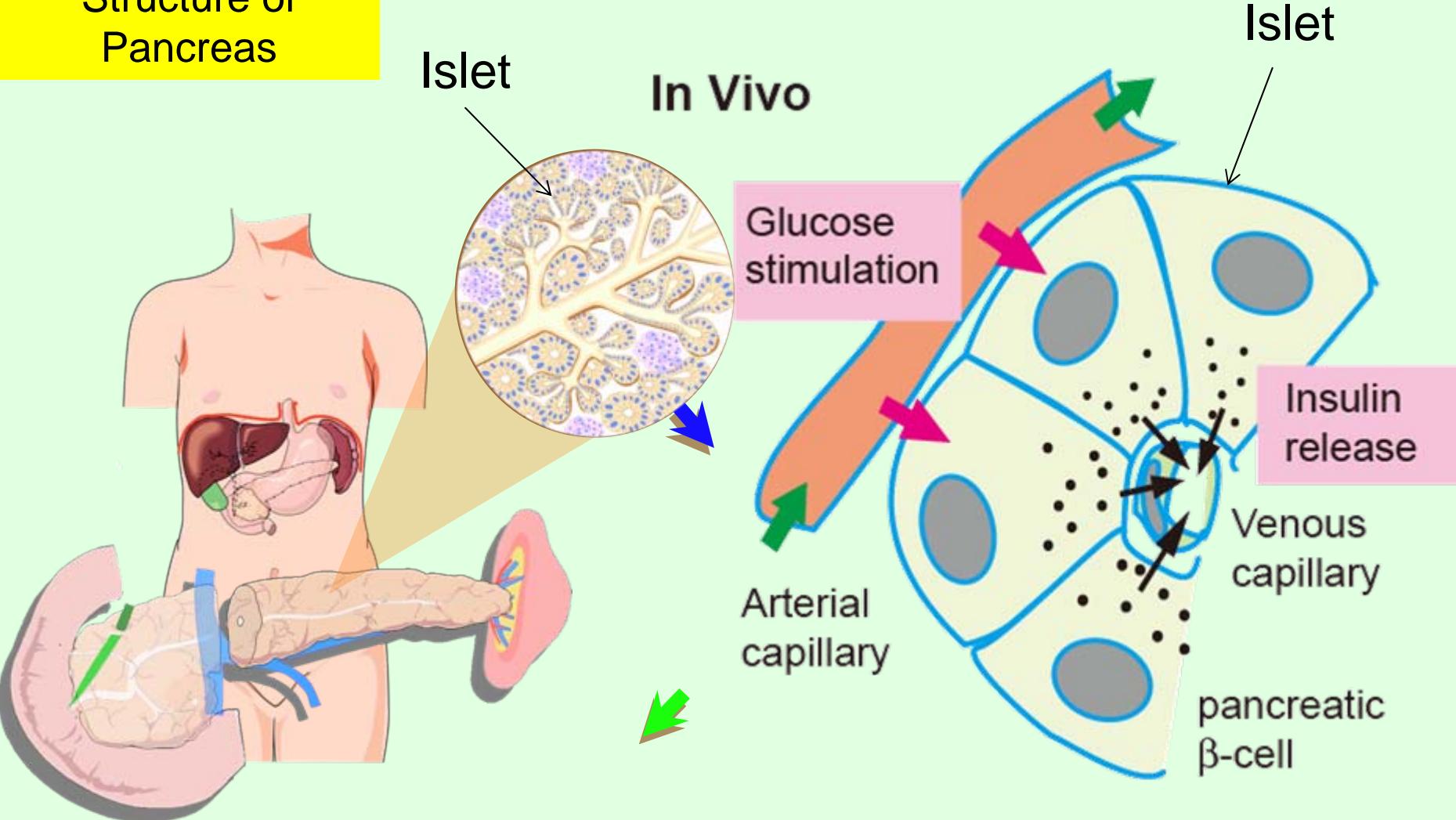
High glucose



48

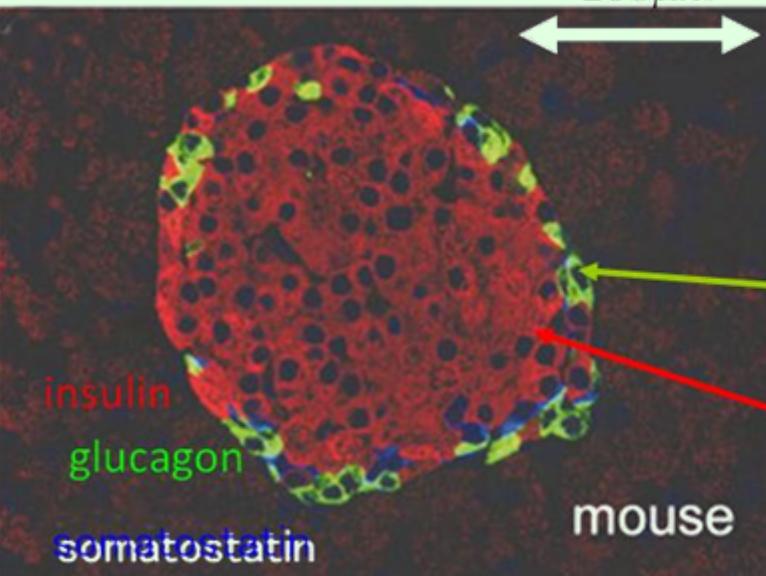
# Measuring Cell–Cell Communication and Regeneration of tissue

Structure of Pancreas



Bonner-Weir S, *Insulin Secretion*, 1989

**Q: How the cell response for the Glucose stimulation?**



## Structure of ISLET (Mouse)

- Aggregating Cells with Different Functions
  - 3D-Construction to Function Effectively
  - Secret hormones to regulate blood glucose
- $\alpha$ -Cells : Glucagon (Blood glucose↑)

Cell-Cell interaction:

Glucagon Secretion from  $\alpha$ -cells inhibits Insulin secretion from  $\beta$ -cells

- $\beta$ -Cells : Insulin (Blood glucose↓)

Aggregating  $\beta$ -Cells secrete more dose of insulin than that in total from the same number of isolated  $\beta$ -Cells.

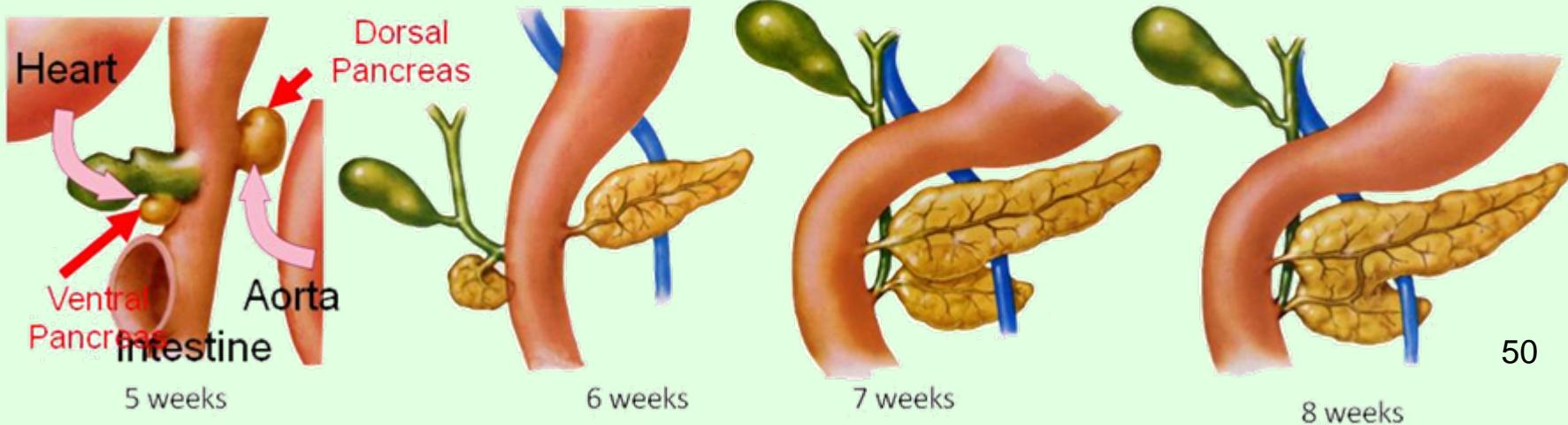
→ Cell-Cell Interaction

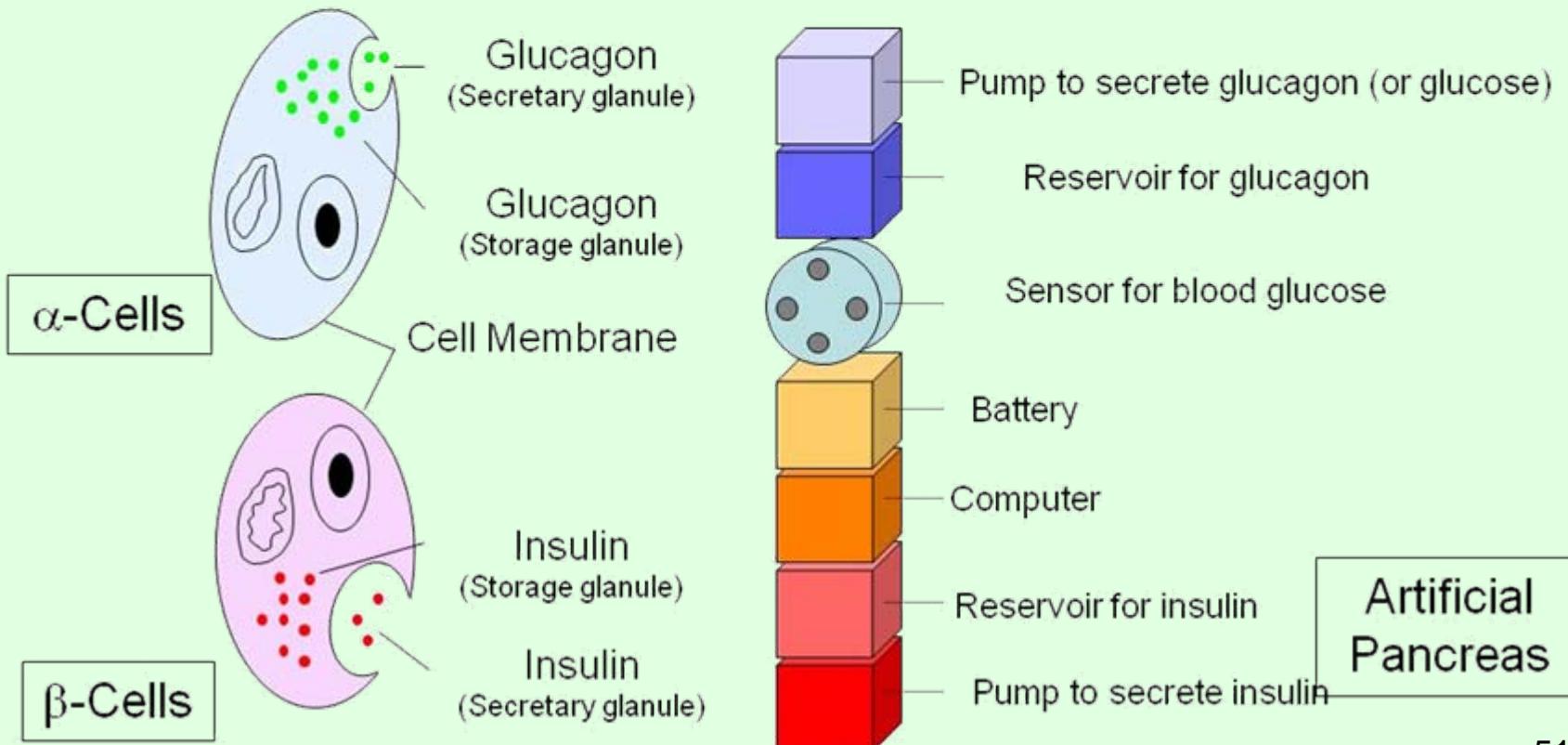
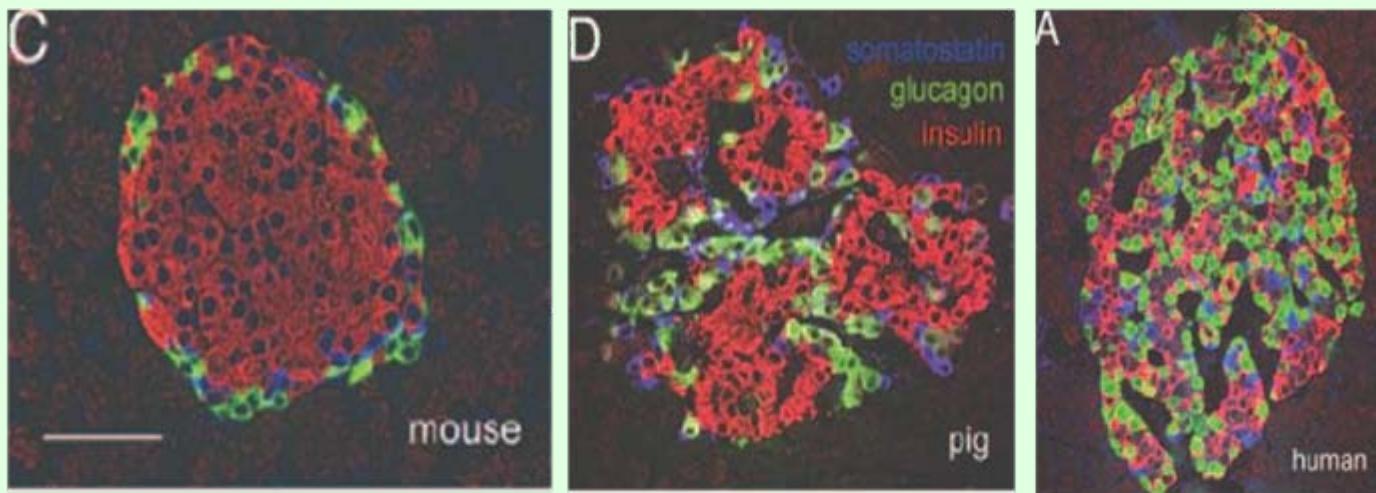
Patient Number of Diabetes :

Type 1: 50000

Type 2: 1 00000000

## Development of Pancreas

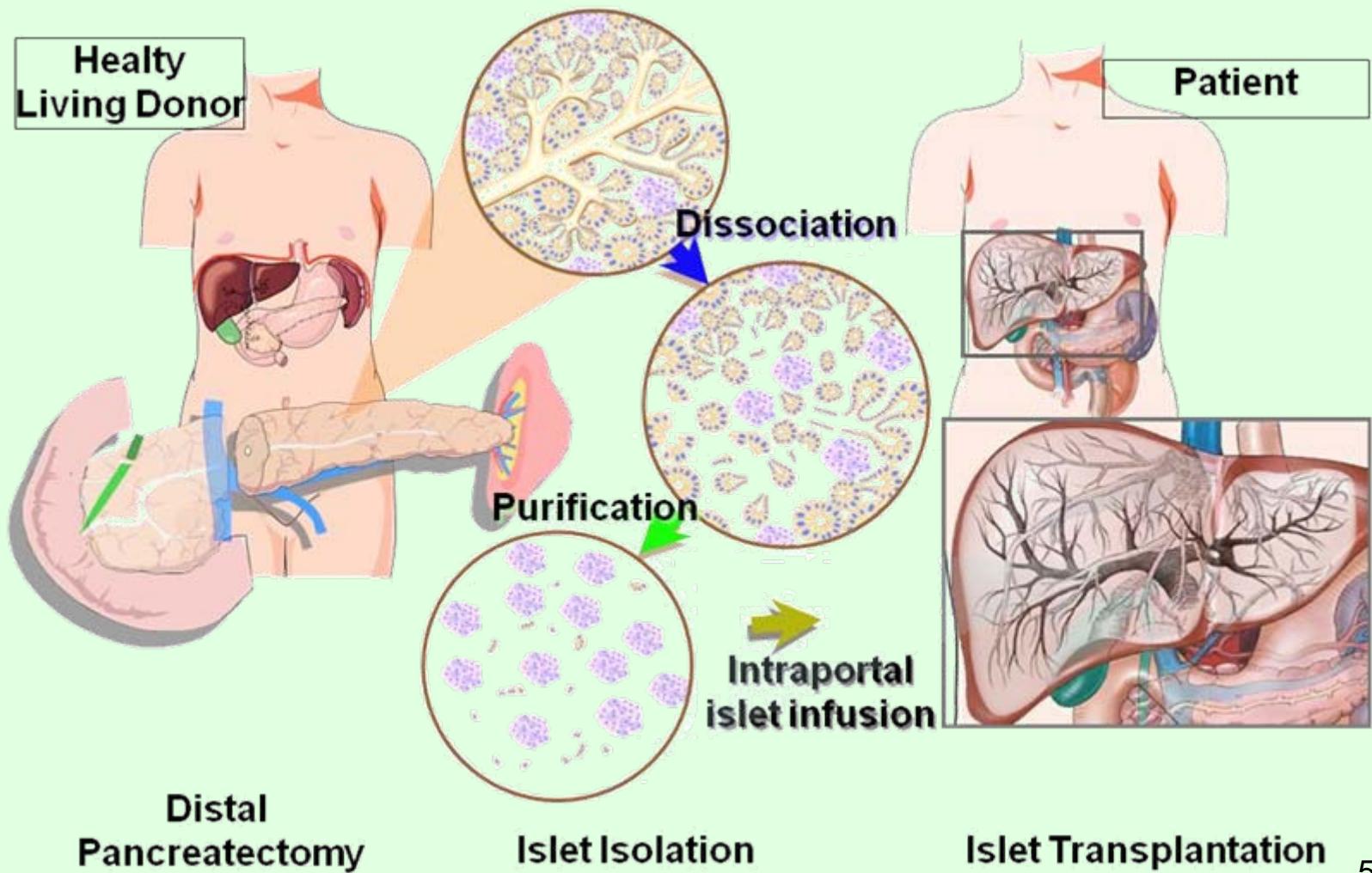




Essential specifications for the artificial pancreas to mimic pancreatic β-Cells and α-Cells

# Clinical Application of Regenerative Medicine

## - Islet Transplantation -

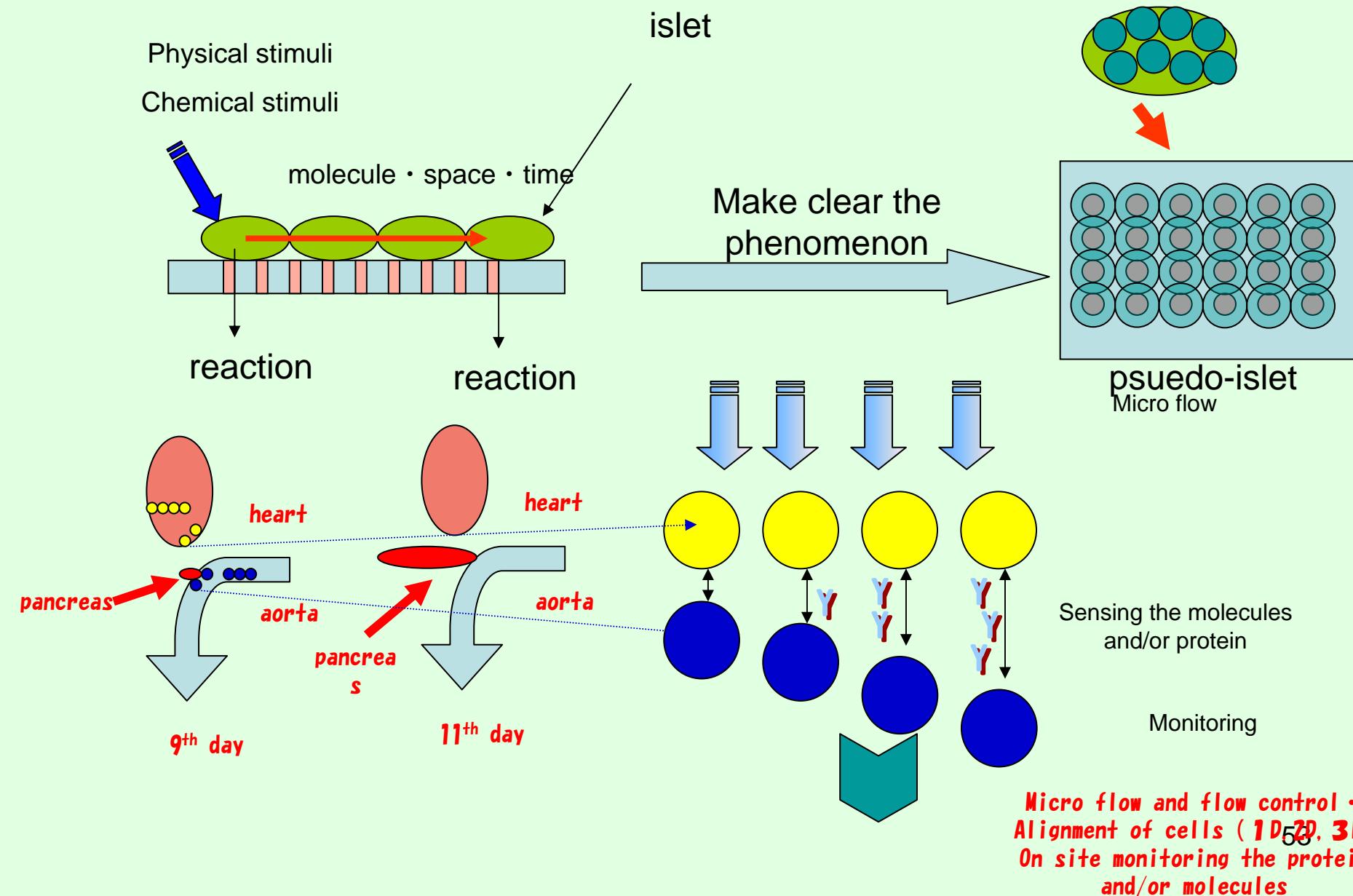


Distal  
Pancreatectomy

Islet Isolation

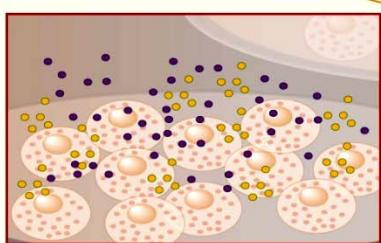
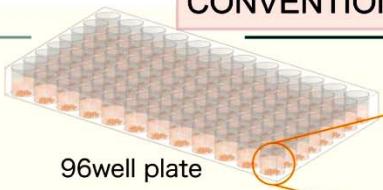
Islet Transplantation

# Micro/Nano devices for measuring the cell-cell communication and regenerate islet islet



## CONVENTIONAL

### (1) Evaluating single cells

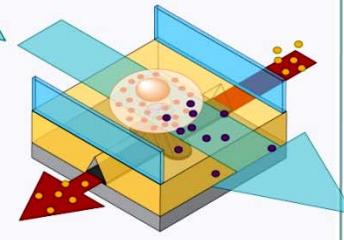
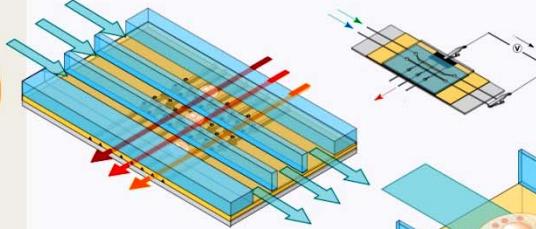


Multiple objectives •

Uncertain Stimulus •

Qualitative

## $\mu$ TAS



### Features

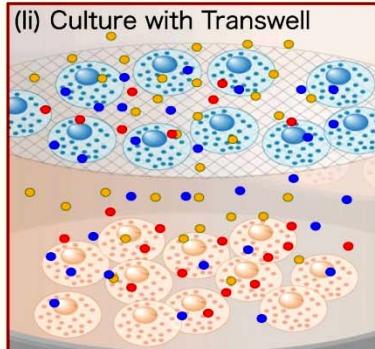
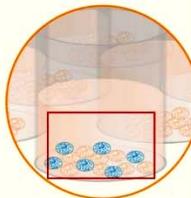
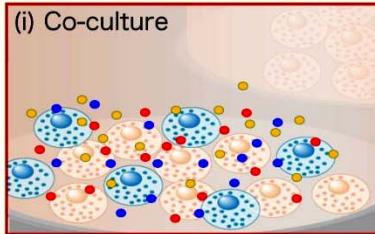
- Singular objectives

- Secured Stimulus

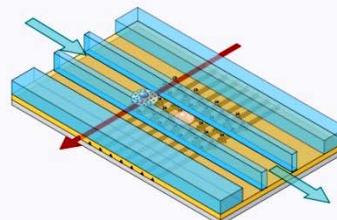
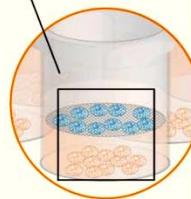
- Quantitative

○ : Stimulator   ● : Responder

### (2) Evaluating multiple cells



Transwell



Undirected cell-cell communication •

Unspecific objectives to stimulate •

No real-time evaluation •

Qualitative •

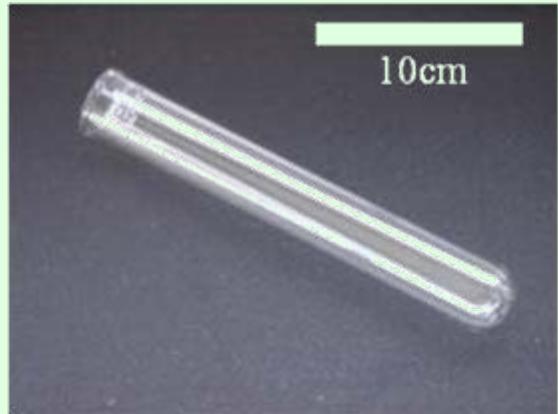
### Features

- Directed cell-cell communication

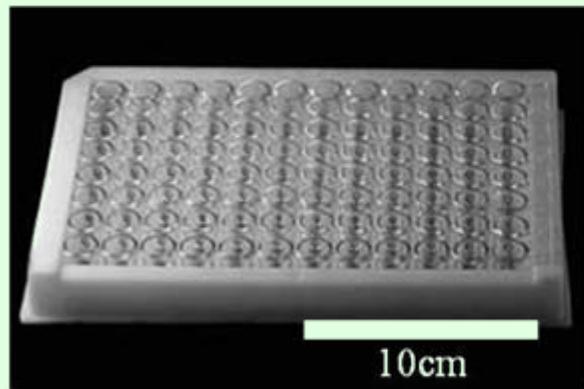
- Specific objectives to stimulate

- Real-time evaluation

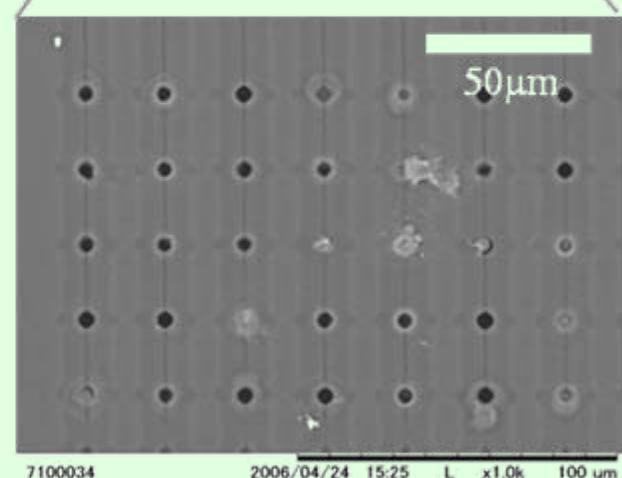
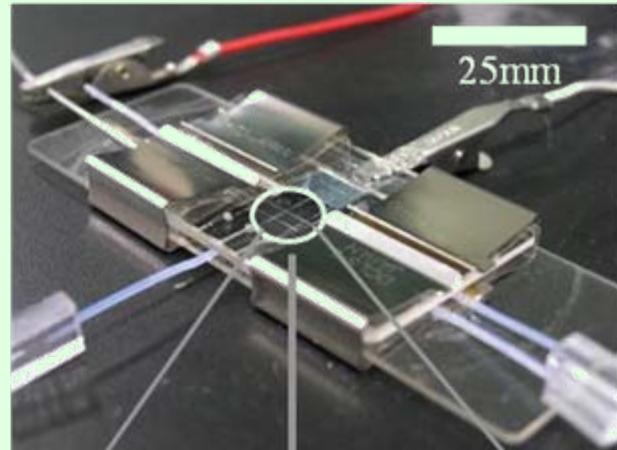
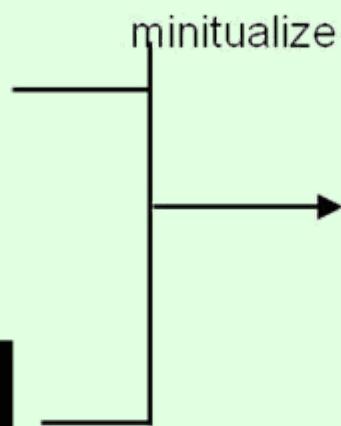
- Quantitative



boiling tube



Multi -well Plate

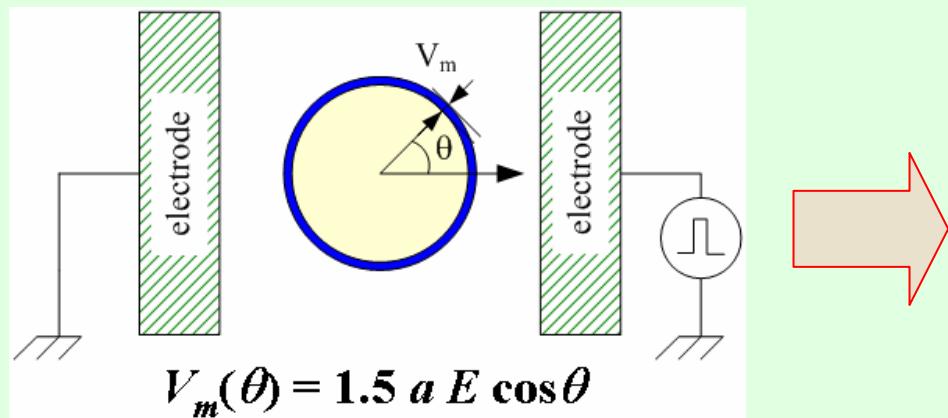


Bio nano Platform

# Insert the chemical stimulus by Micro electroporation

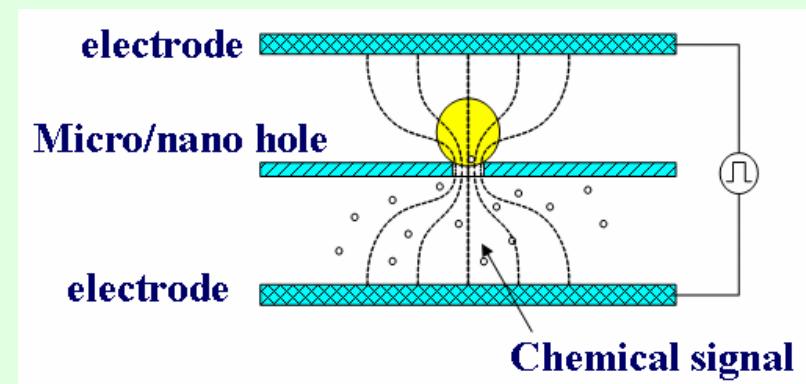
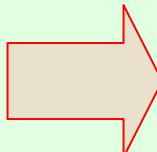


Hold the cell at micro hole ( $\sim 2\mu\text{m}$ ) insert the chemical signal by electroporation  
\* Measuring electric signal



conventional

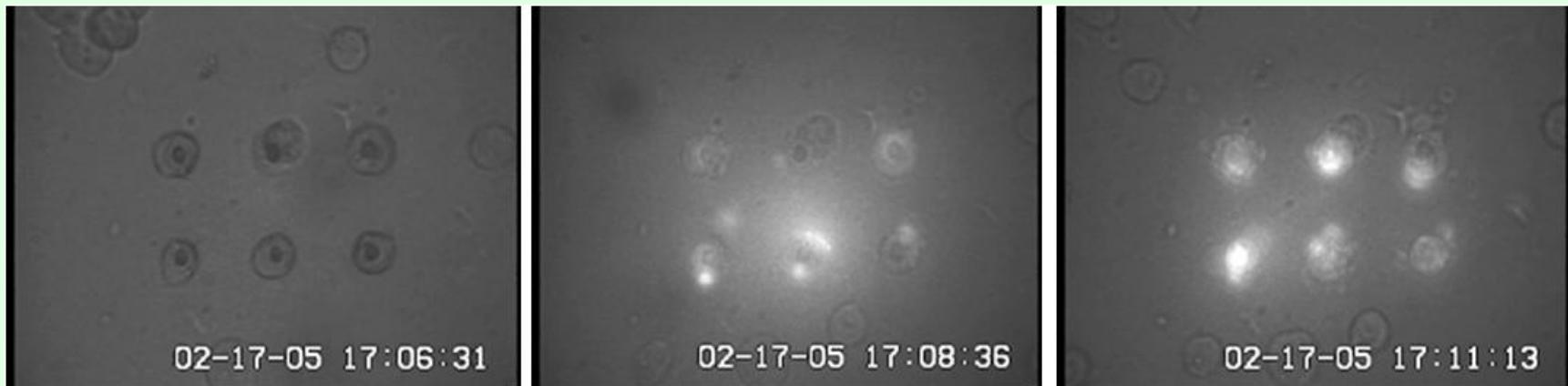
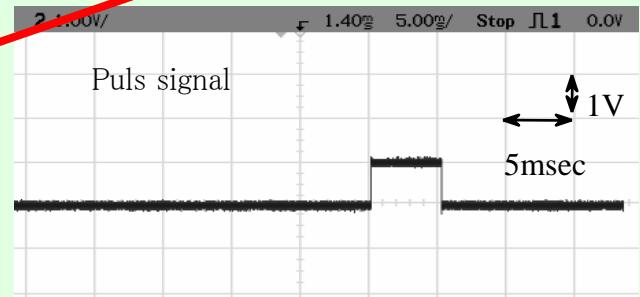
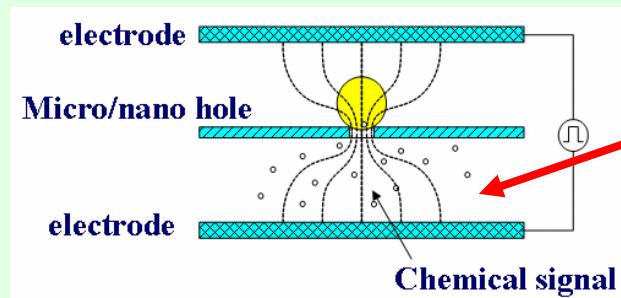
- 1)  $a = 10 \mu\text{m} \rightarrow E = 10^5 \text{ V/m}$   
(1000V/cm)
- 2) Keep the cell membrane?



Micro-TAS

- 1) Low voltage 1–6V
- 2) Electrode + micro hole + micro channel
- 3) Holding mechanizm

Cell U937 :  
Cell suspension : RPMI medium  
buffer solution : RPMI medium +10 mM YO-PRO-1



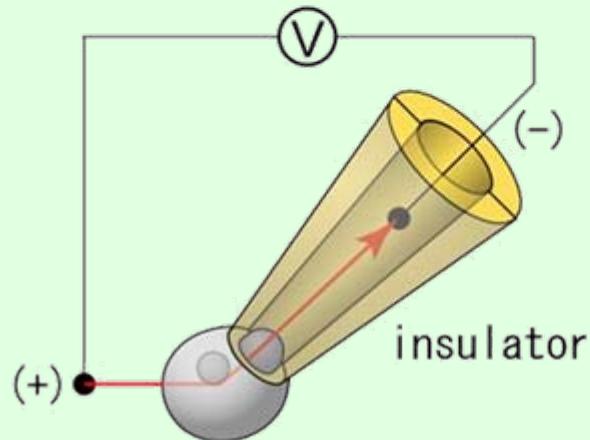
Initial

1V x 30 times

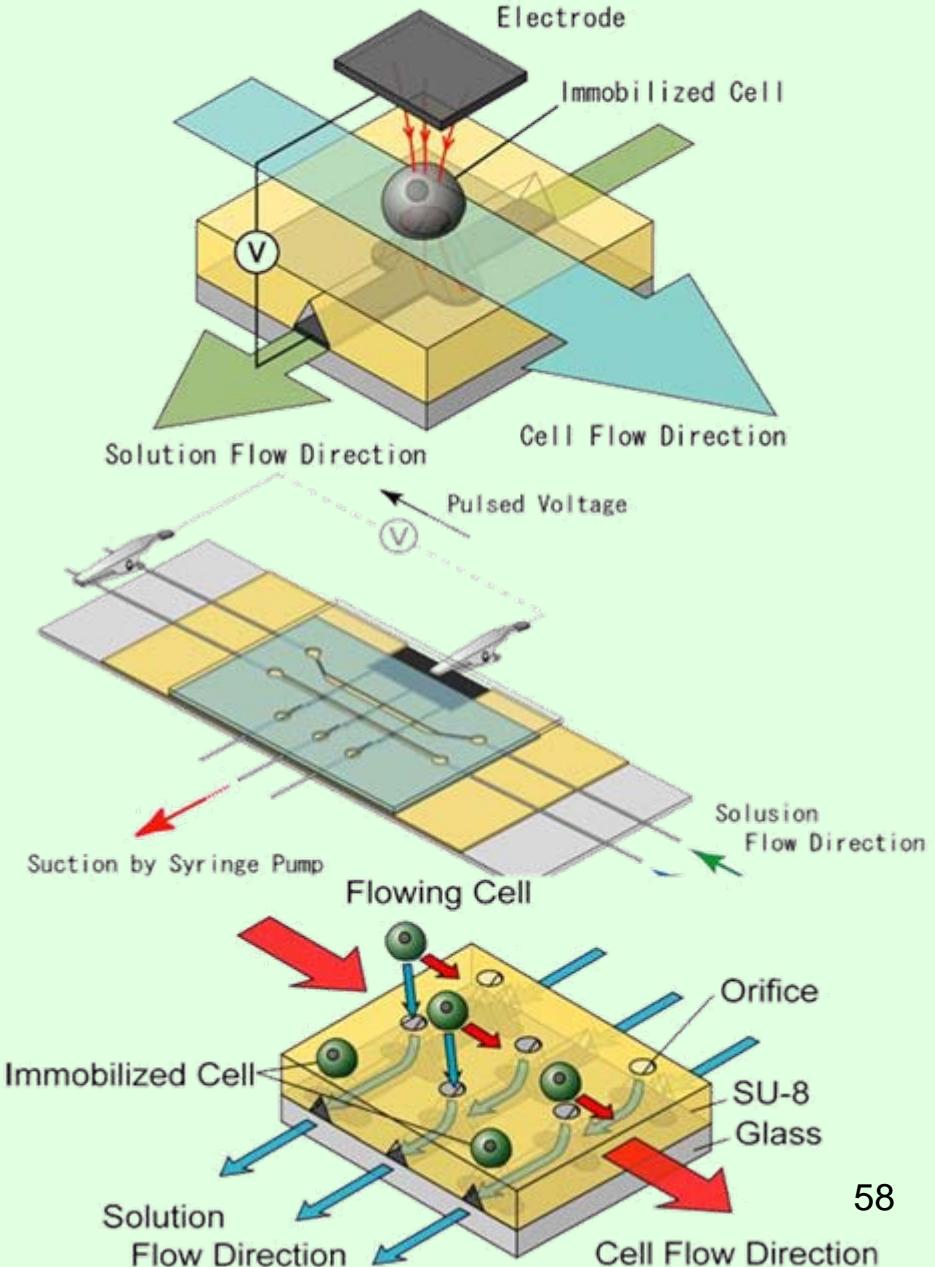
2V x 20 times

conventional

$\mu$ -TAS

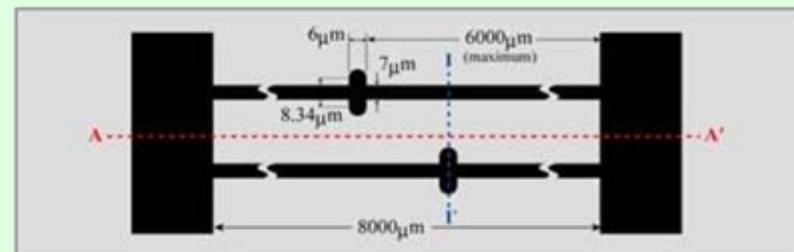
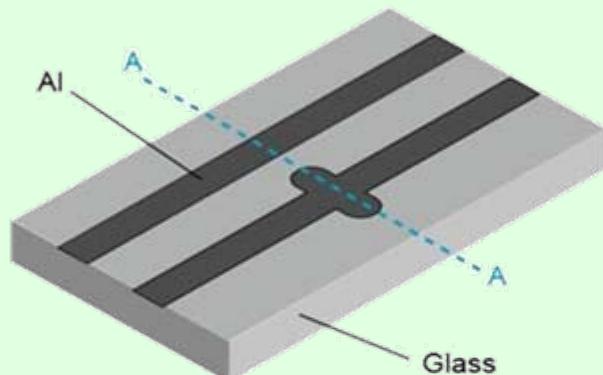


- micro pipette



# Single-mask inclined UV lithography

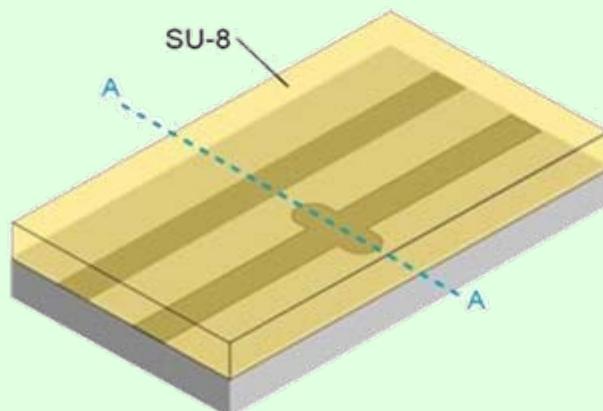
## 1) Pattern Al on glass substrate



- Evaporating Al on a glass substrate
  - Spin coating ZEP (EB resist)
  - Exposure with electron beam
  - Wet etching Al with phosphoric acid



## 2) Spin Coat & Soft bake SU-8

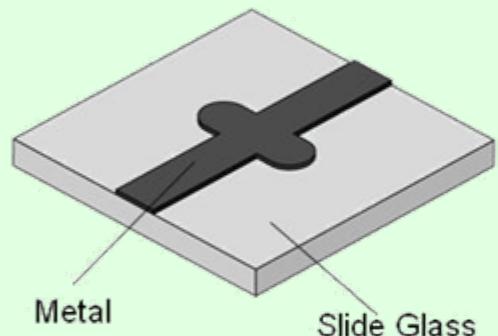


- Spin coating negative photoresist SU-8 (MICRO CHEM Corp.)
- Thickness of photoresist: 10–100 μm
  - Soft bake

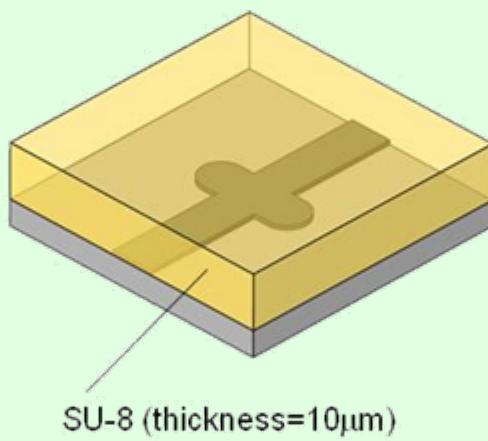


# Single-Mask Inclined UV-Lithography

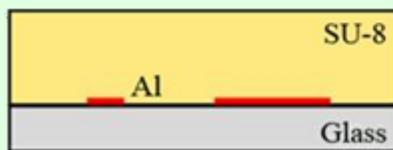
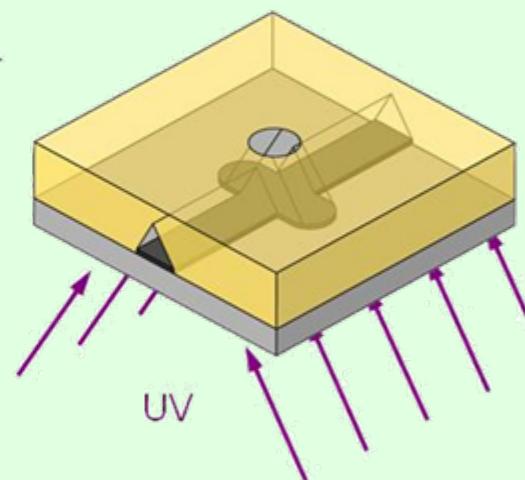
① Metal mask is patterned on glass



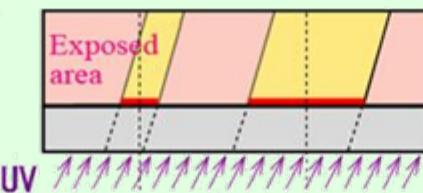
② SU-8



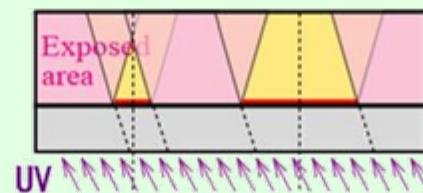
③ Inclined exposure by UV light



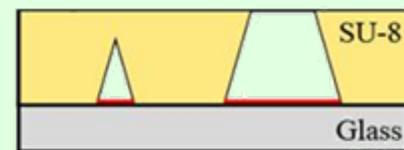
(a) Spin-coat and Soft bake



(b) First expose



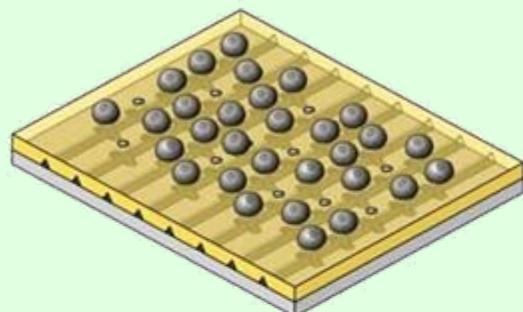
(c) Second expose



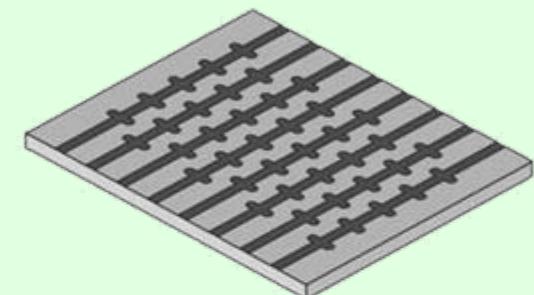
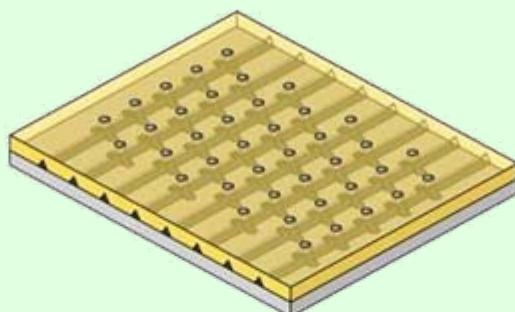
(d) Post exposure bake and Development

# Electroporation chip

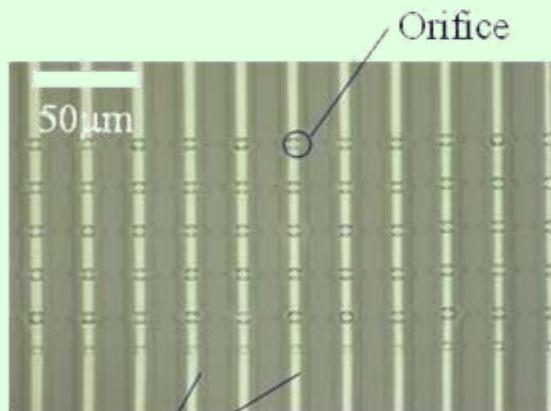
Micro channel. Orifice and electrode is fabricated simultaneously



Cell array

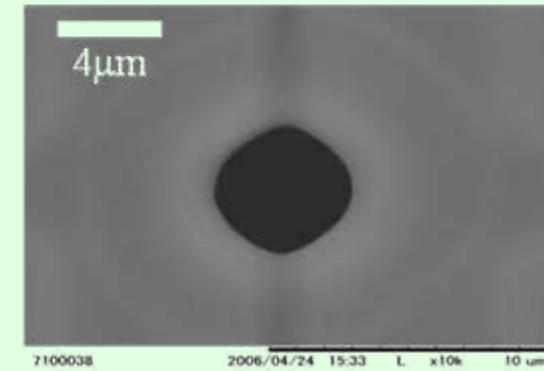
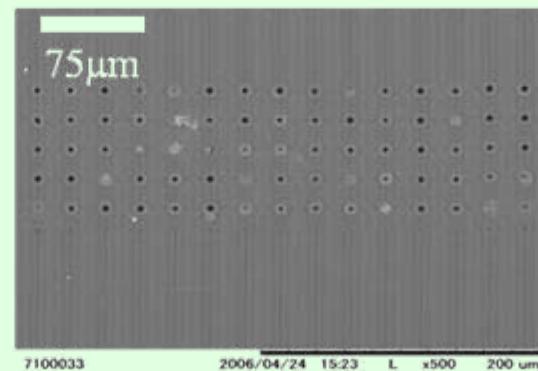


Mask Pattern on Slide Glass

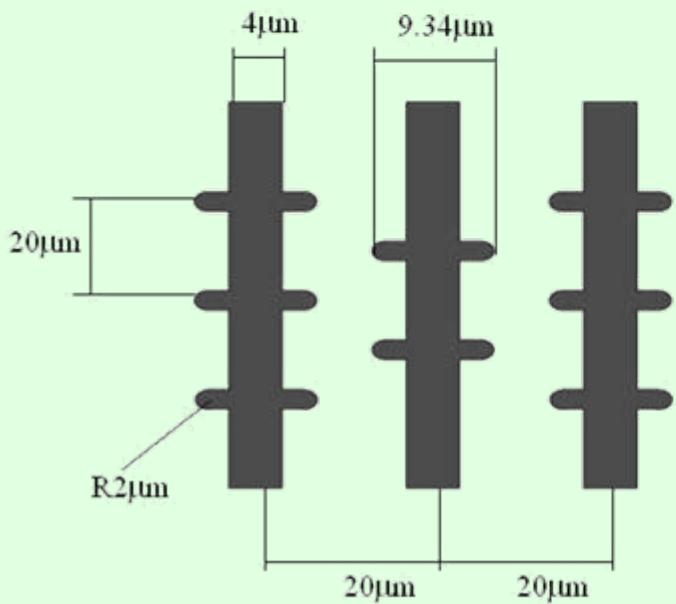
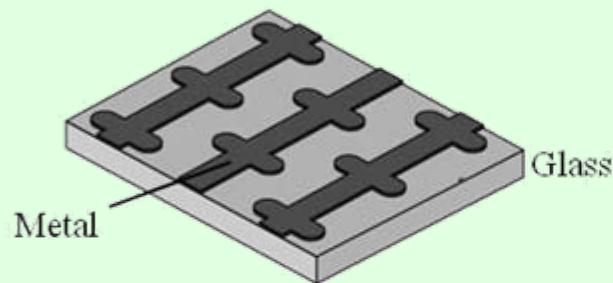
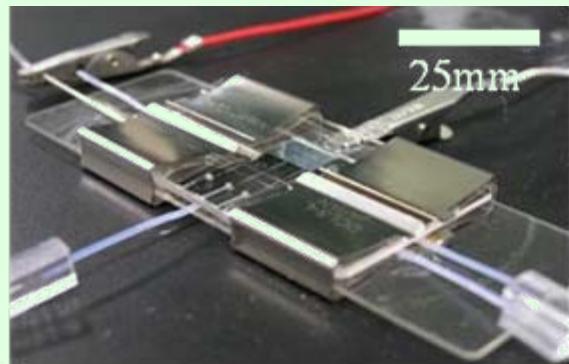


Micro-channel

Optical Image (x50)



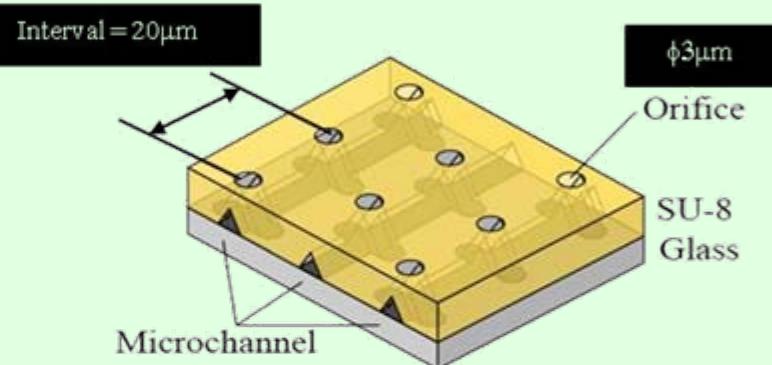
SEM Images



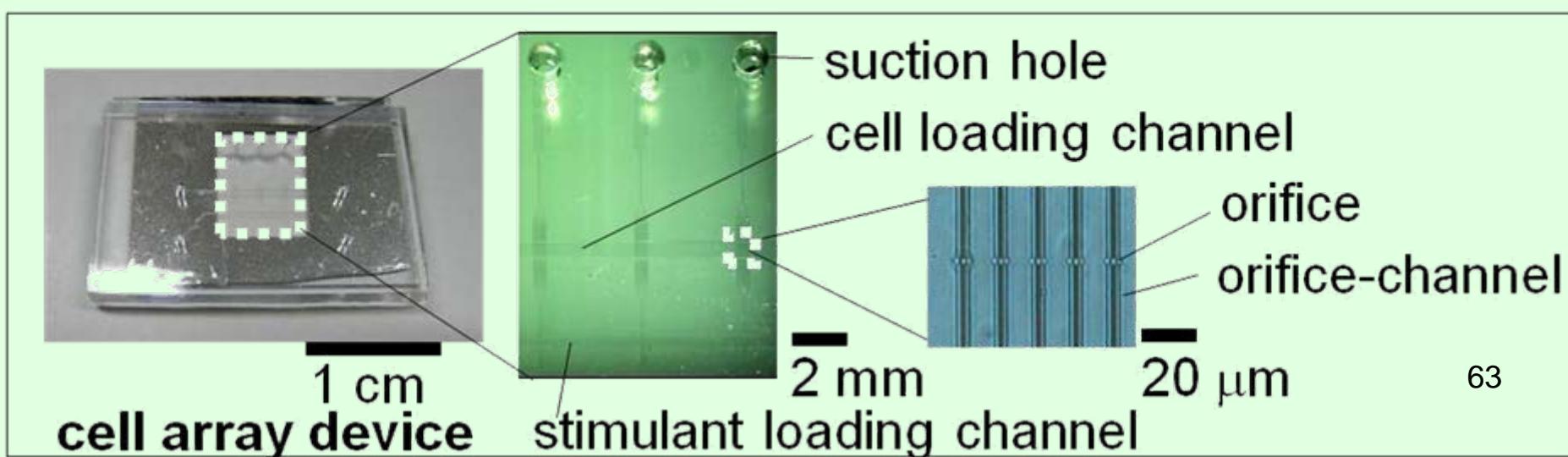
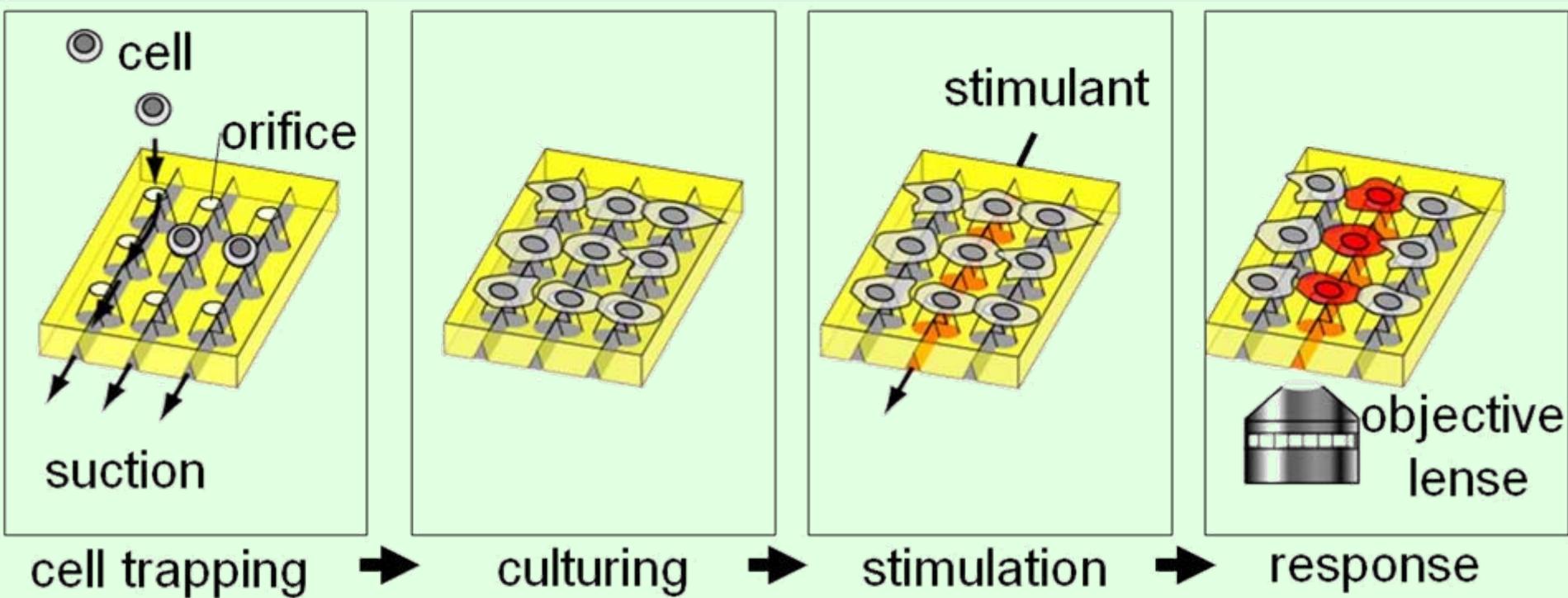
More than ten thousands of cells are measured parallel on one chip



Single-MASK Inclined UV Lithography



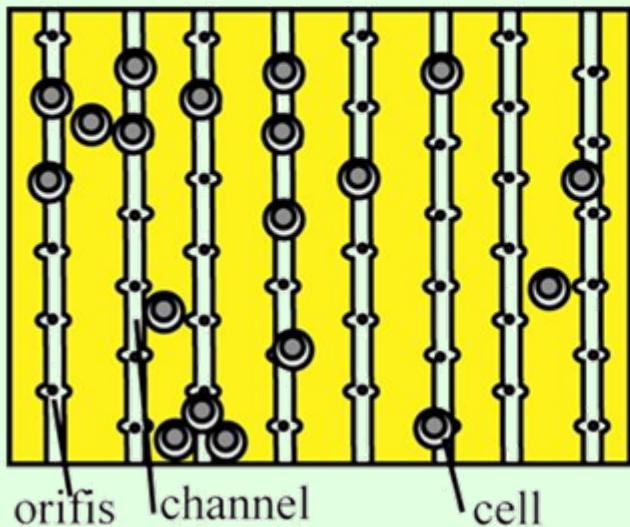
# $\beta$ -Cell (Min 6 m9) humoral transmission



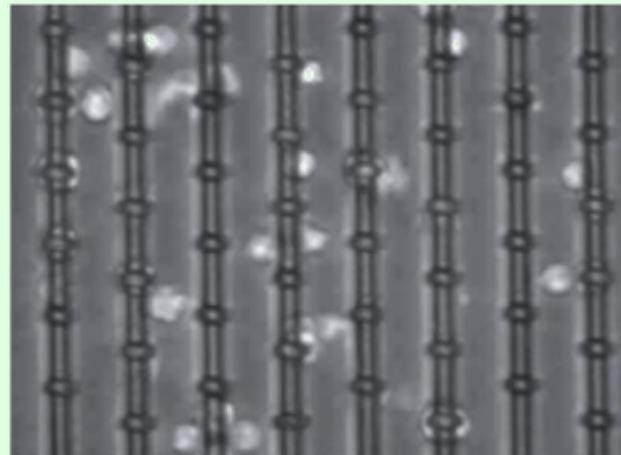
**cell array device**

**stimulant loading channel**

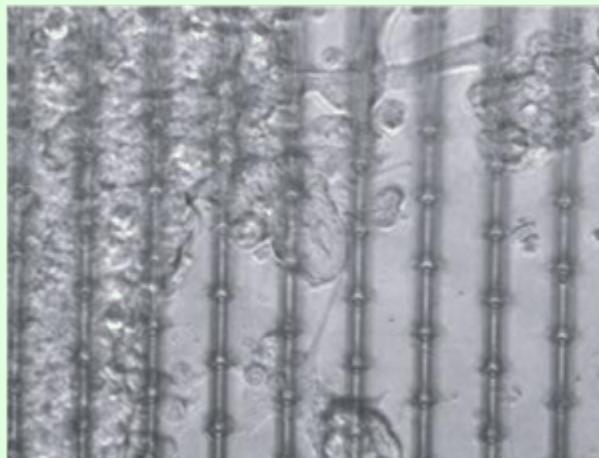
# Cell trapping & Culturing



(a) schematic of cell trapping

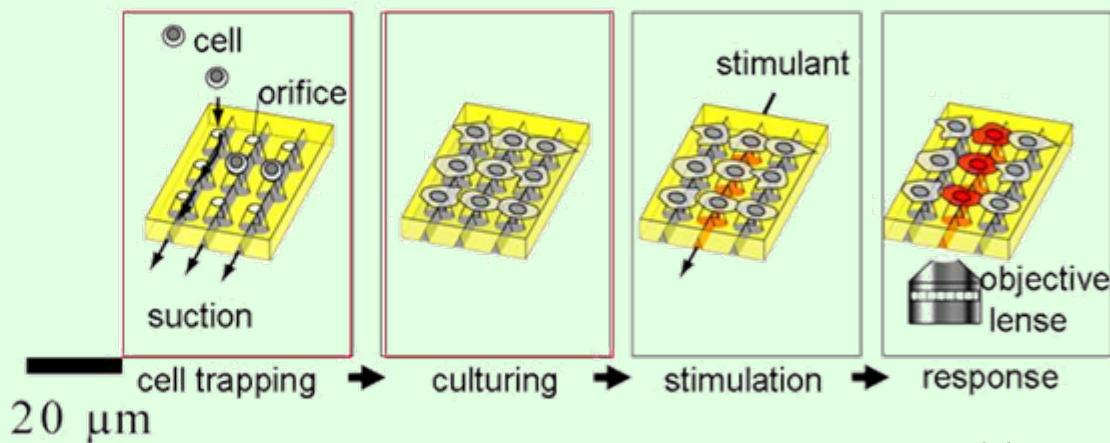


(b) phase contrast image of cell trapping



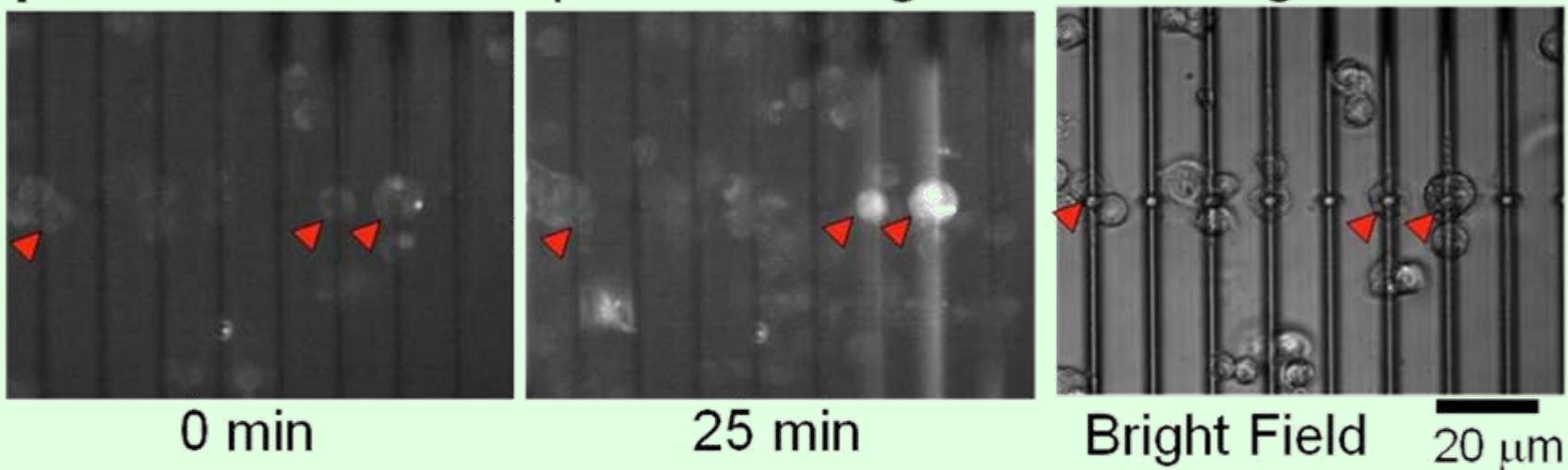
(c) culturing of trapped MIN-m9 cells for 3days

## Experimental procedure

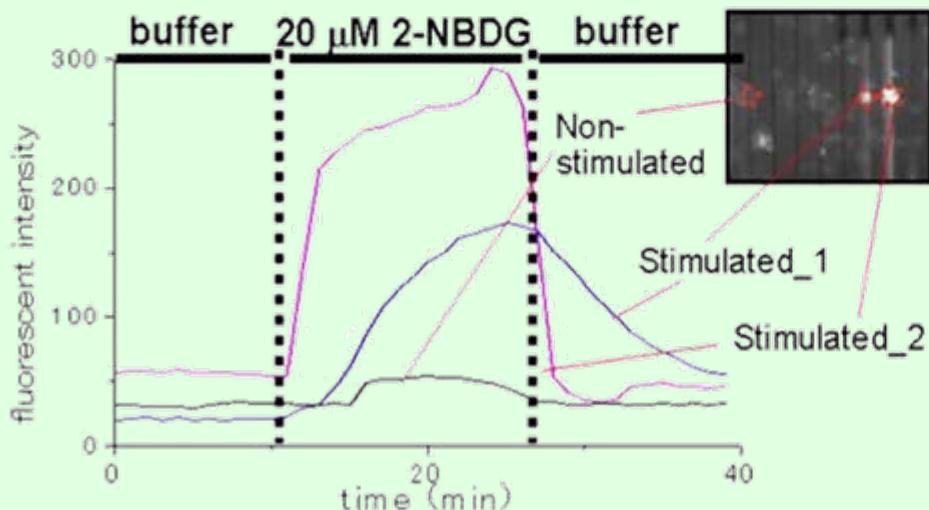


# Stimulation

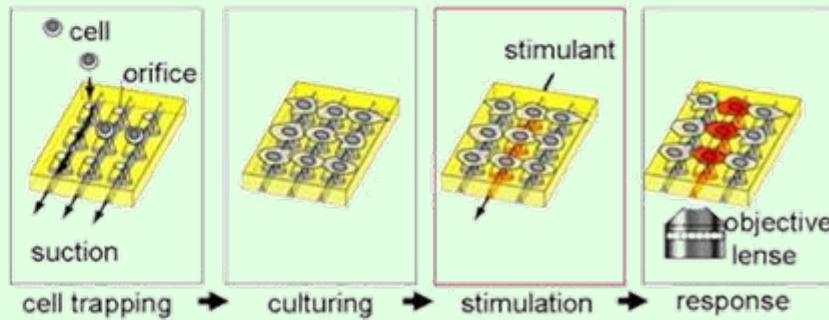
Uptake of a stimulus (fluorescent glucose analogue: 2-NBDG)



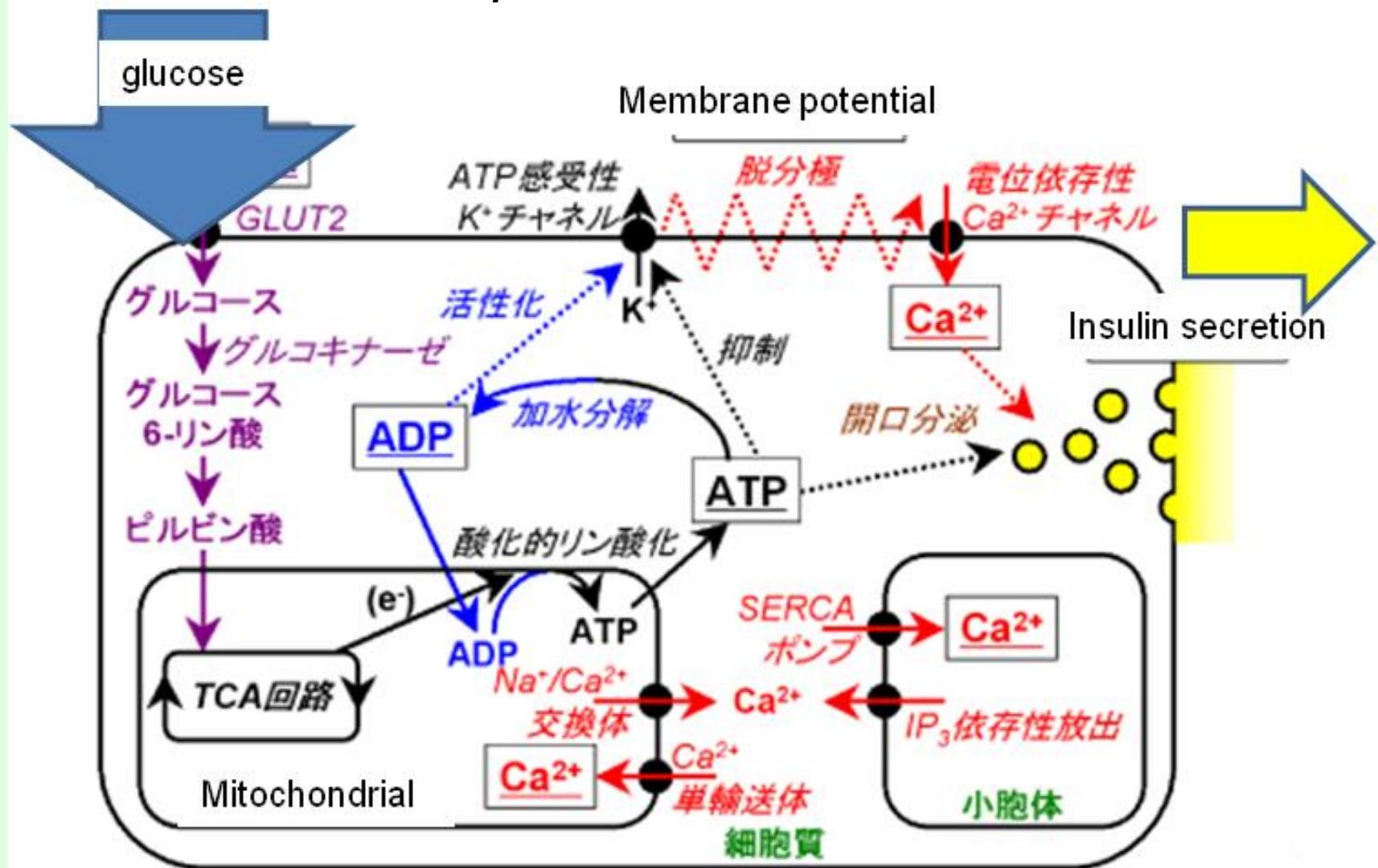
Time course of the uptake of 2-NBDG



Experimental procedure

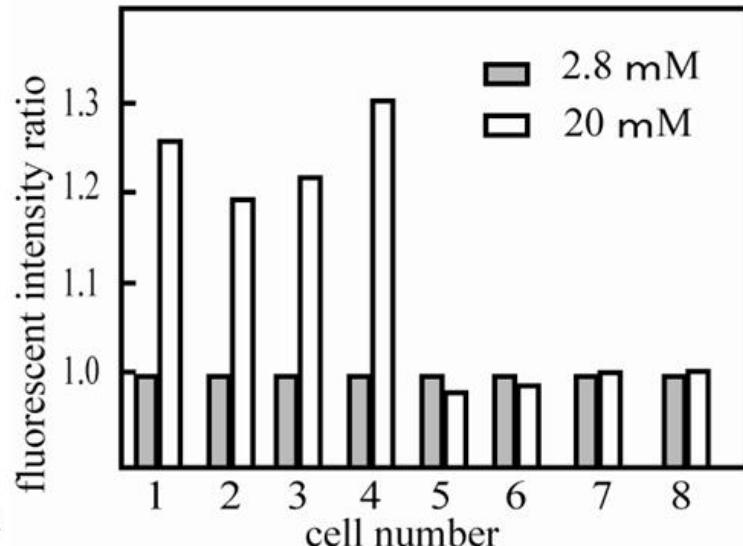
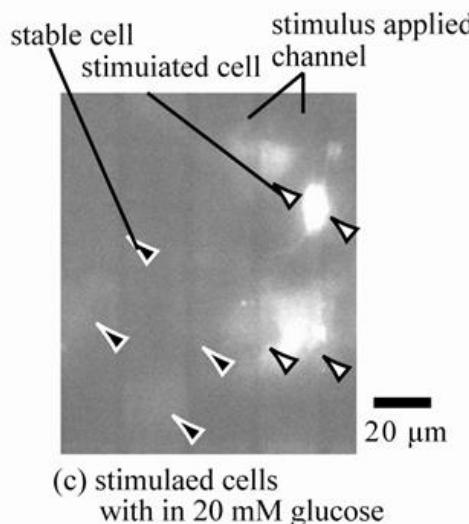
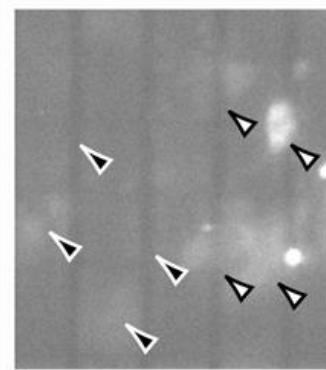
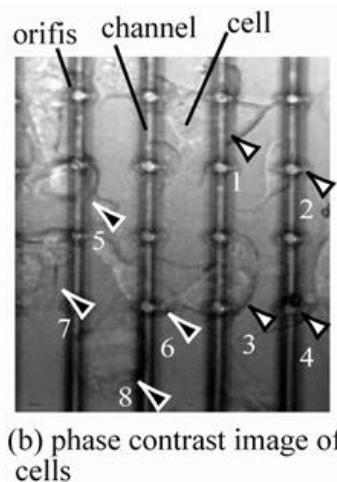
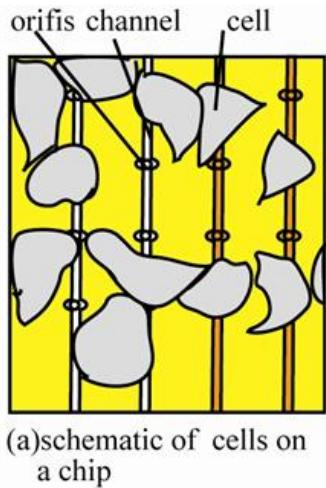


# Pancreas $\beta$ cell (insulin secretion)



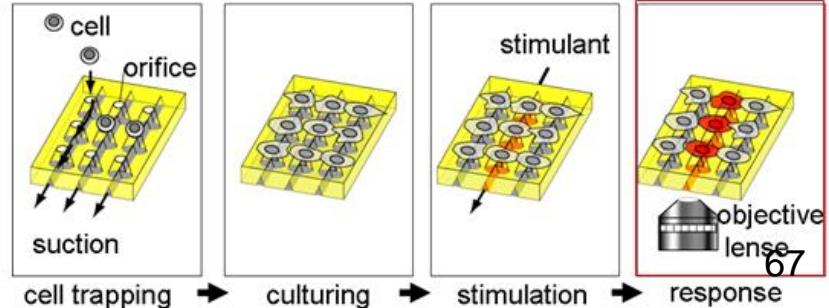
# Responsive reaction

## glucose-induced rise in cytosolic $\text{Ca}^{2+}$ concentration



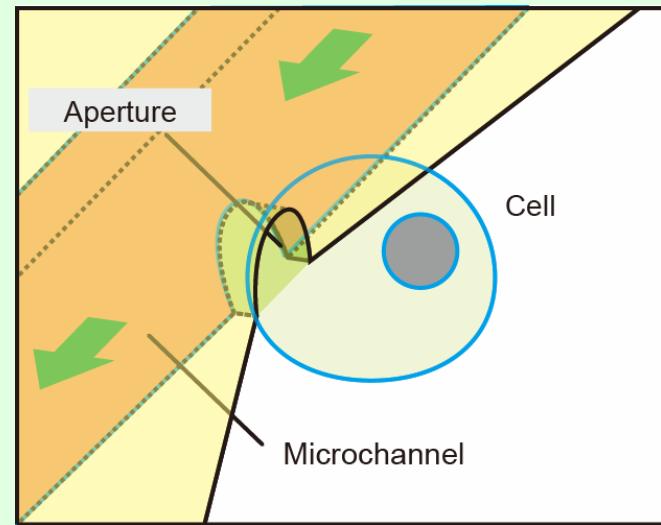
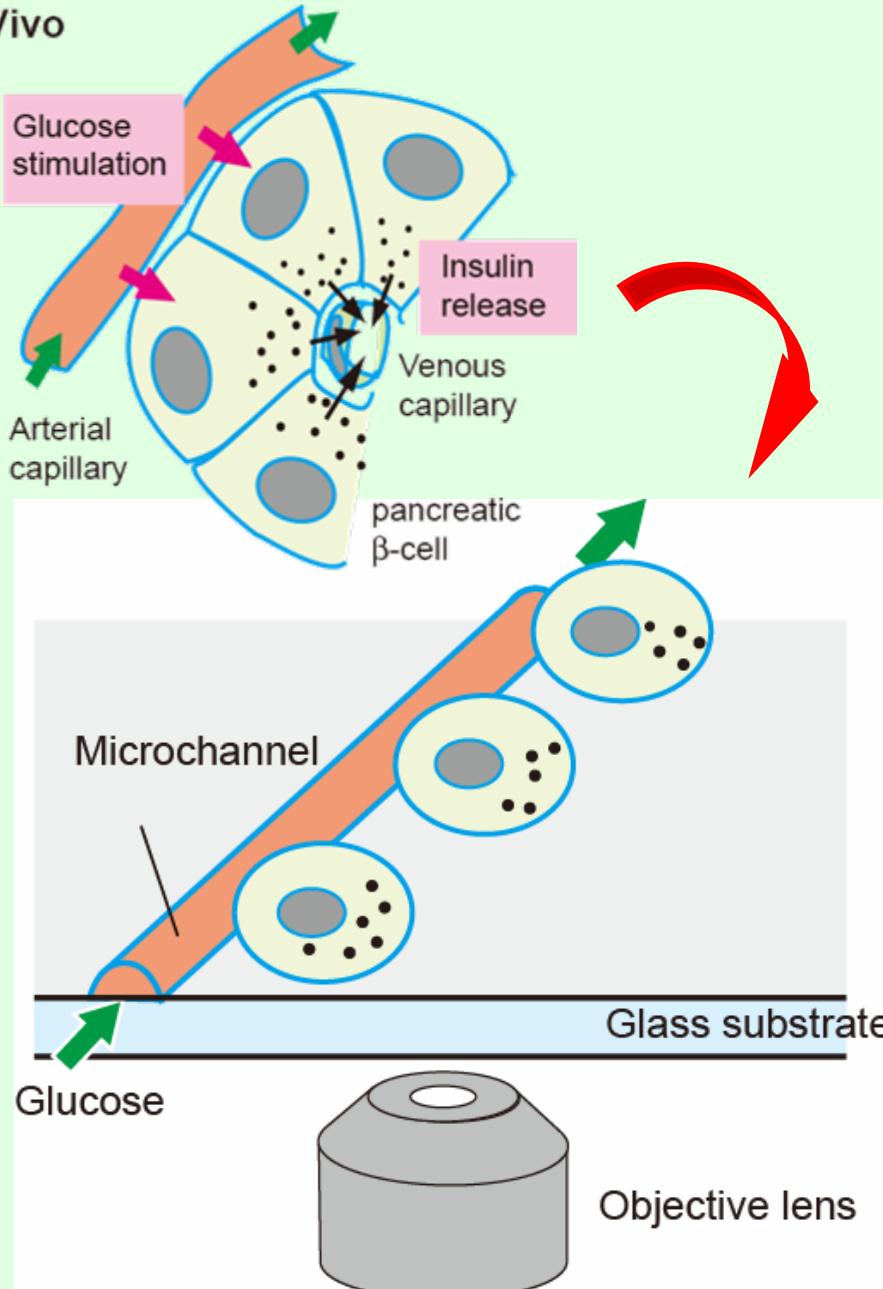
(e) the fluorescence intensity change in response to glucose stimulation

### Experimental procedure



# Mimicked Tissue Micro-environment

In Vivo

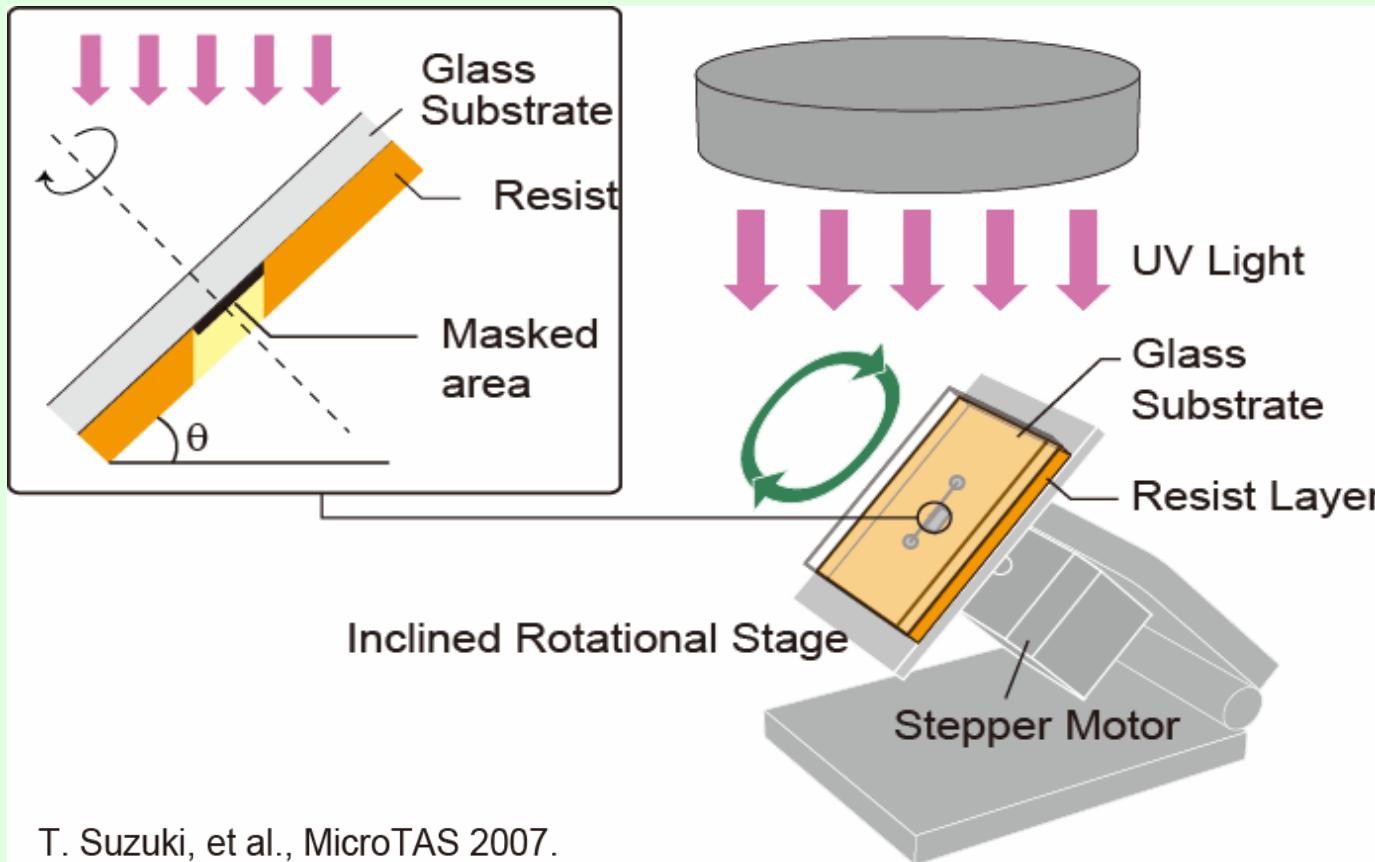


**Localization and control mechanism of secreting direction**

- 1. Apply localized stimuli**  
Stimulate through  
“Pseudo-arterial capillary”
- 2. Measure intracellular response**  
4D imaging ( $x,y,z$  and time)

# Fabrication

## Multi-Directional UV Lithography.

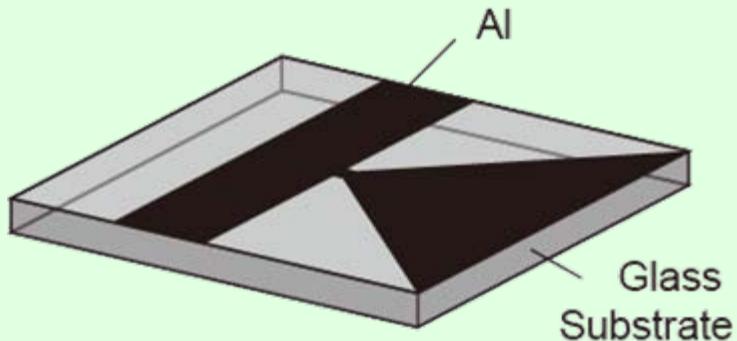


T. Suzuki, et al., MicroTAS 2007.

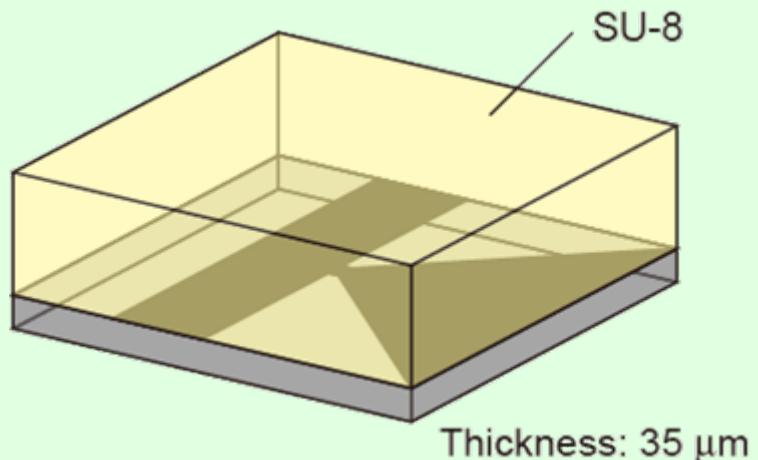
- Complex micro channel from *Single* photo mask
- No mask alignment process

# Fabrication

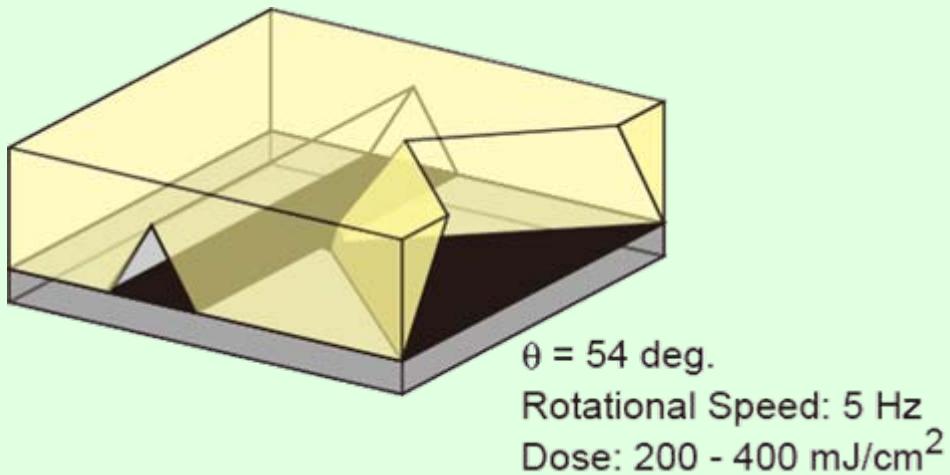
## 1. Al Patterning



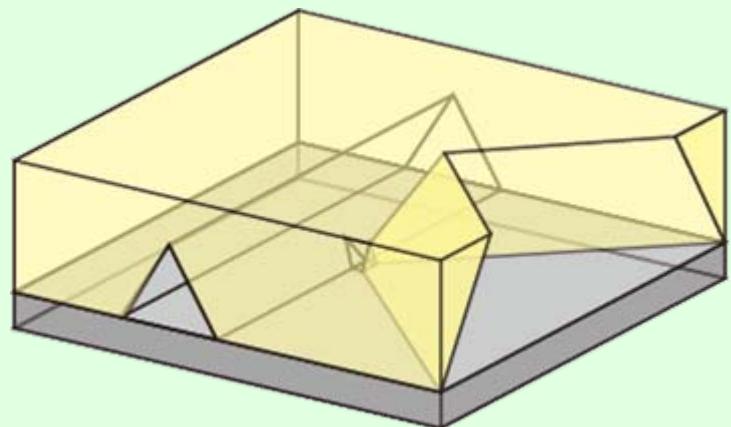
## 2. Spincoat SU-8



## 3. Multidirectional Lithography

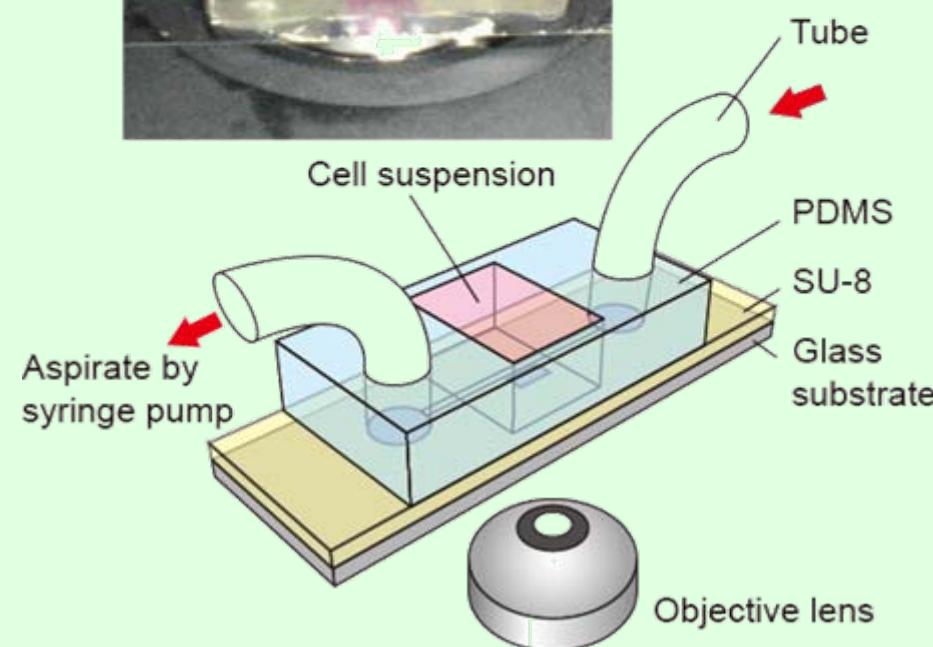
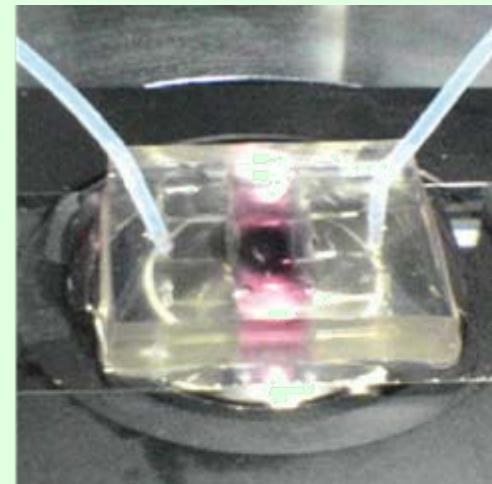
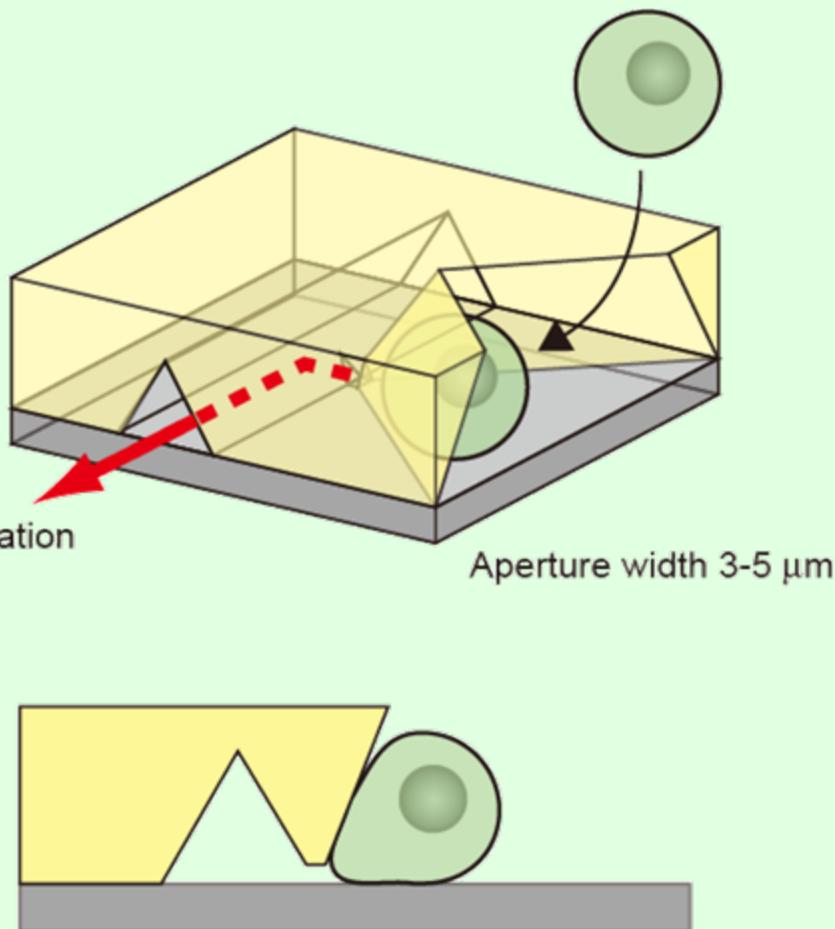


## 4. Al Etching



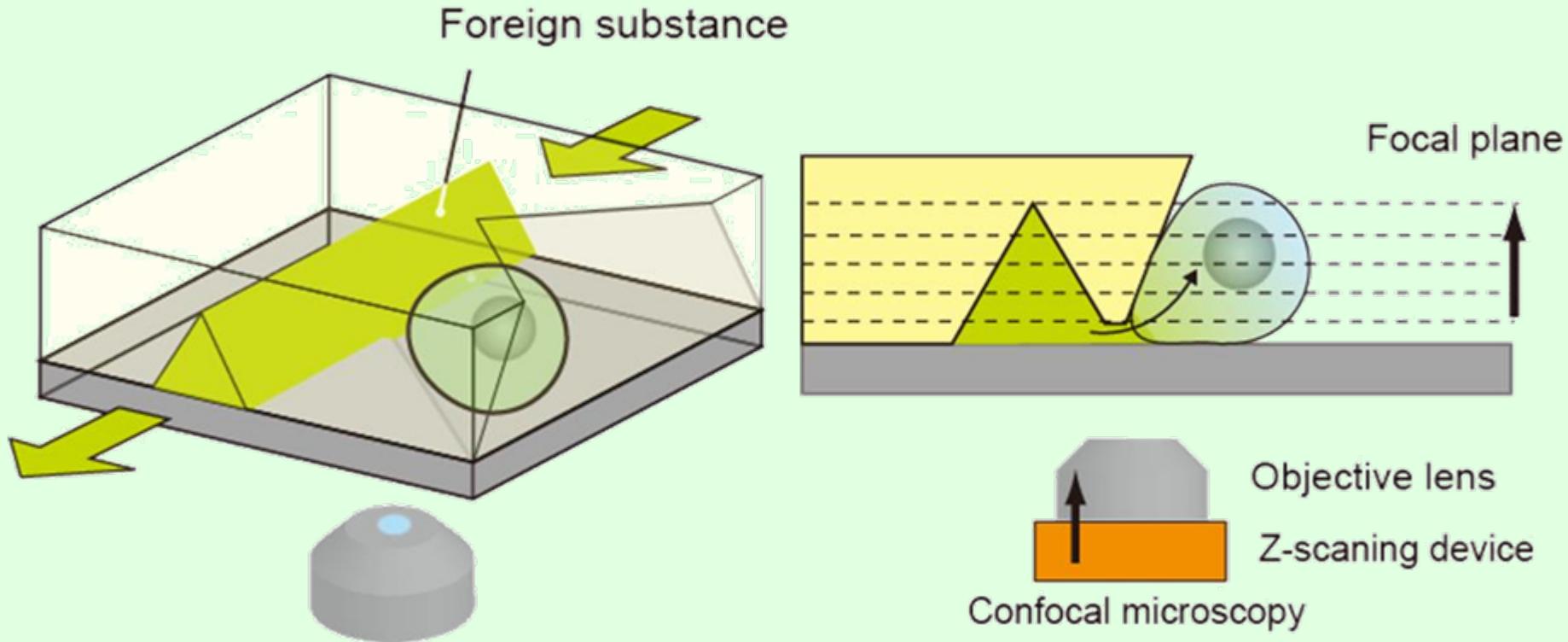
# Positioning of single cell

Pancreatic  $\beta$  Cell (MIN6)  $\phi 10 \mu\text{m}$



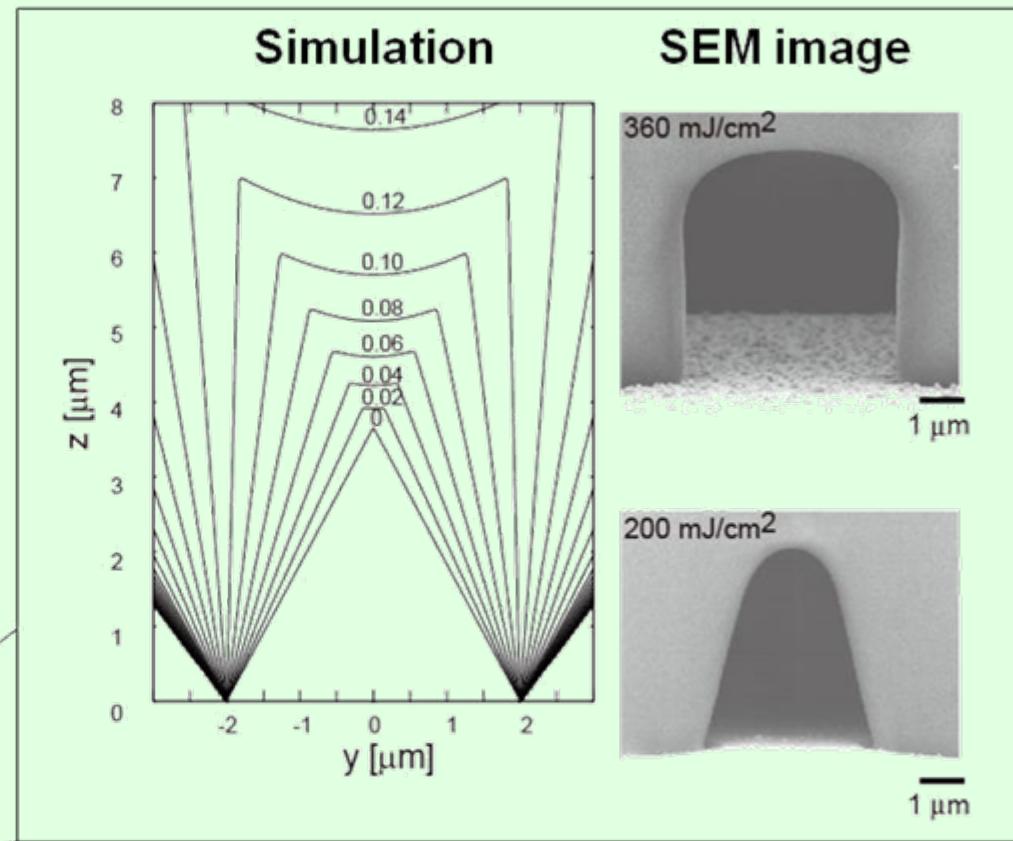
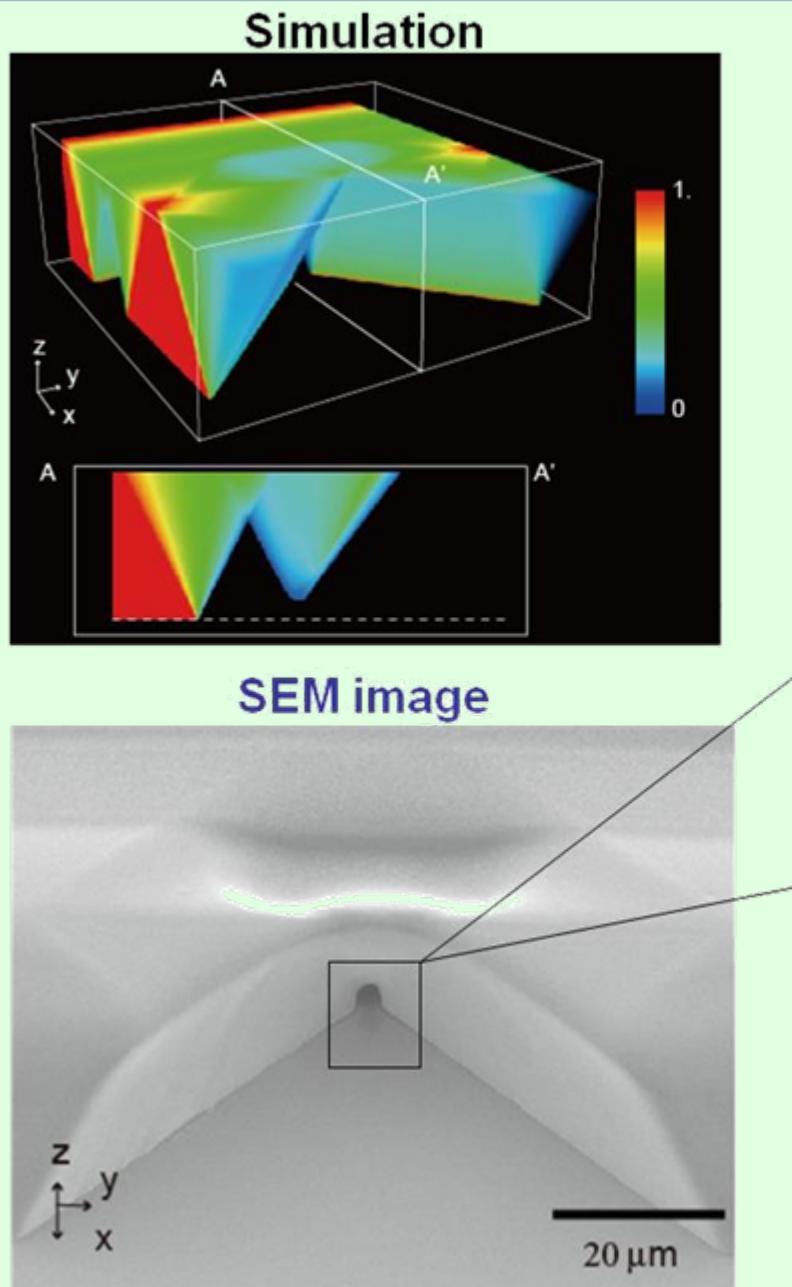
**Trap single cell by aspiration through micro channel.**

# Setup for measuring localization and secretion



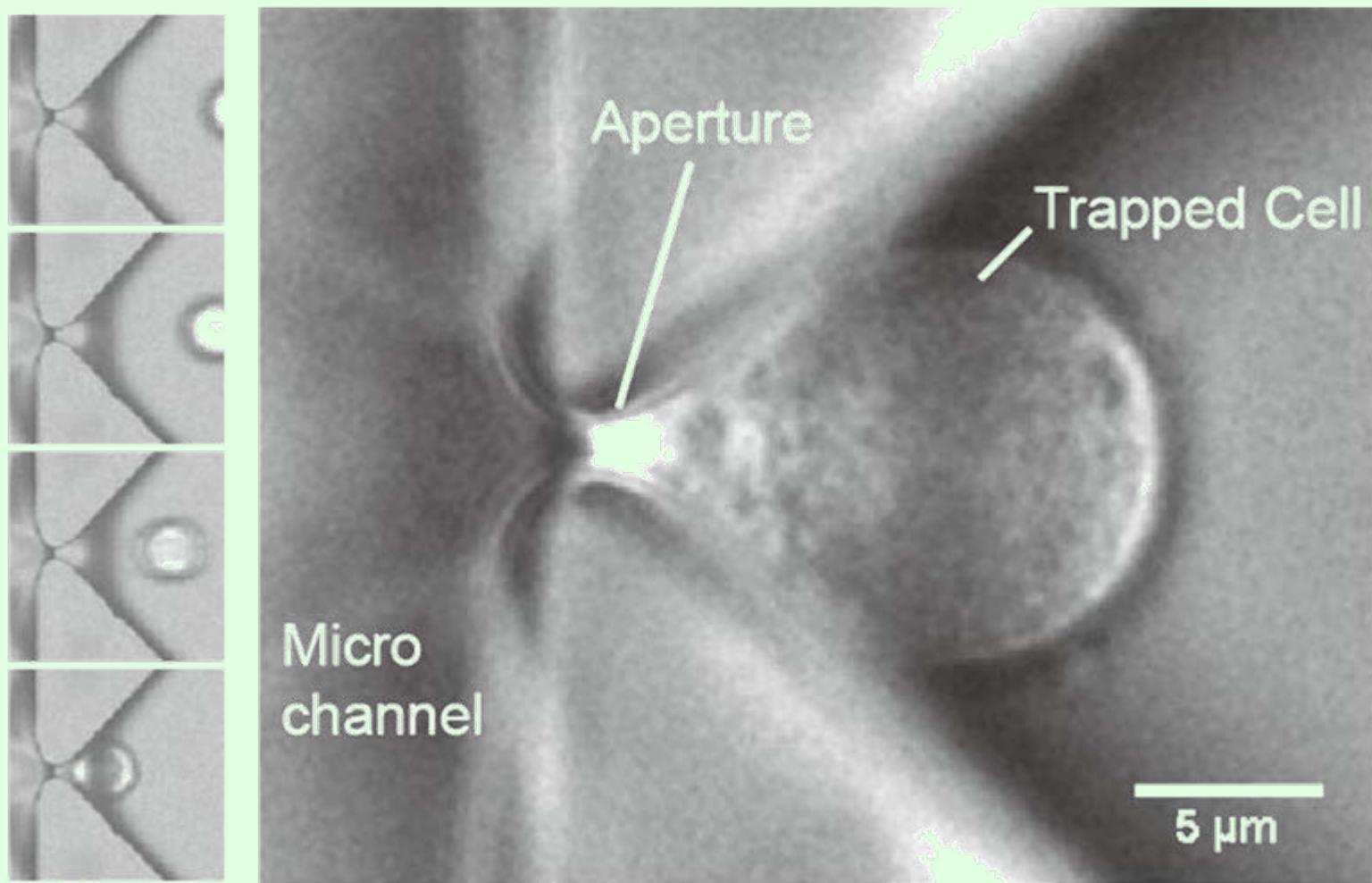
- Localized stimuli introduction into trapped cell
- 4D imaging of its uptake and intracellular responses

# Micro channel and hole



- Aperture-size/shape control by exposure dose

# Cell positioning

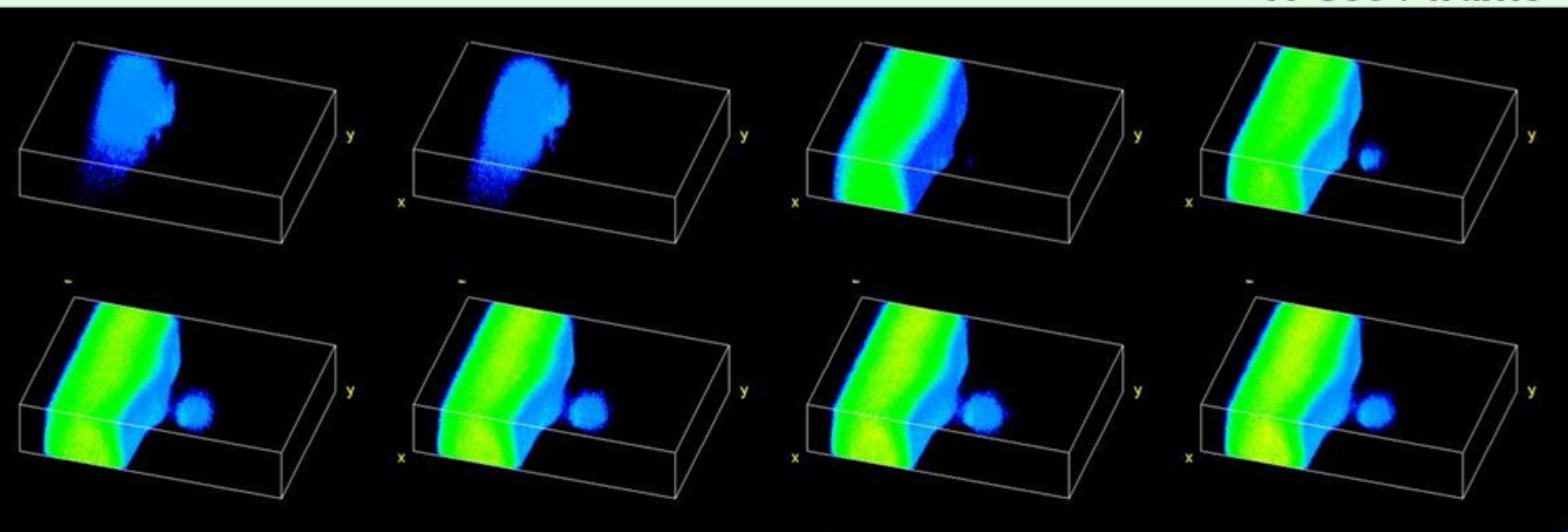


160 ms/frame

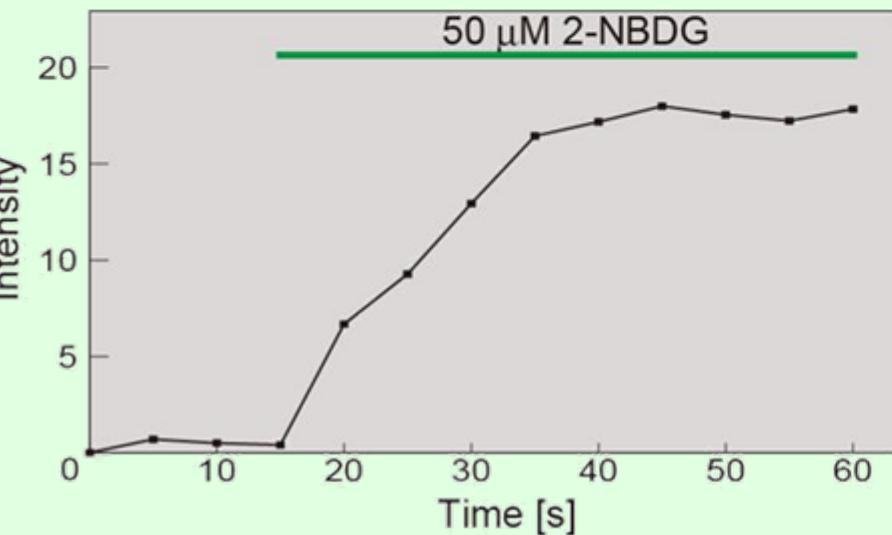
**Single cell is positioned at an aperture.**

# Glucose instability and localization inside cell

10 sec / frame

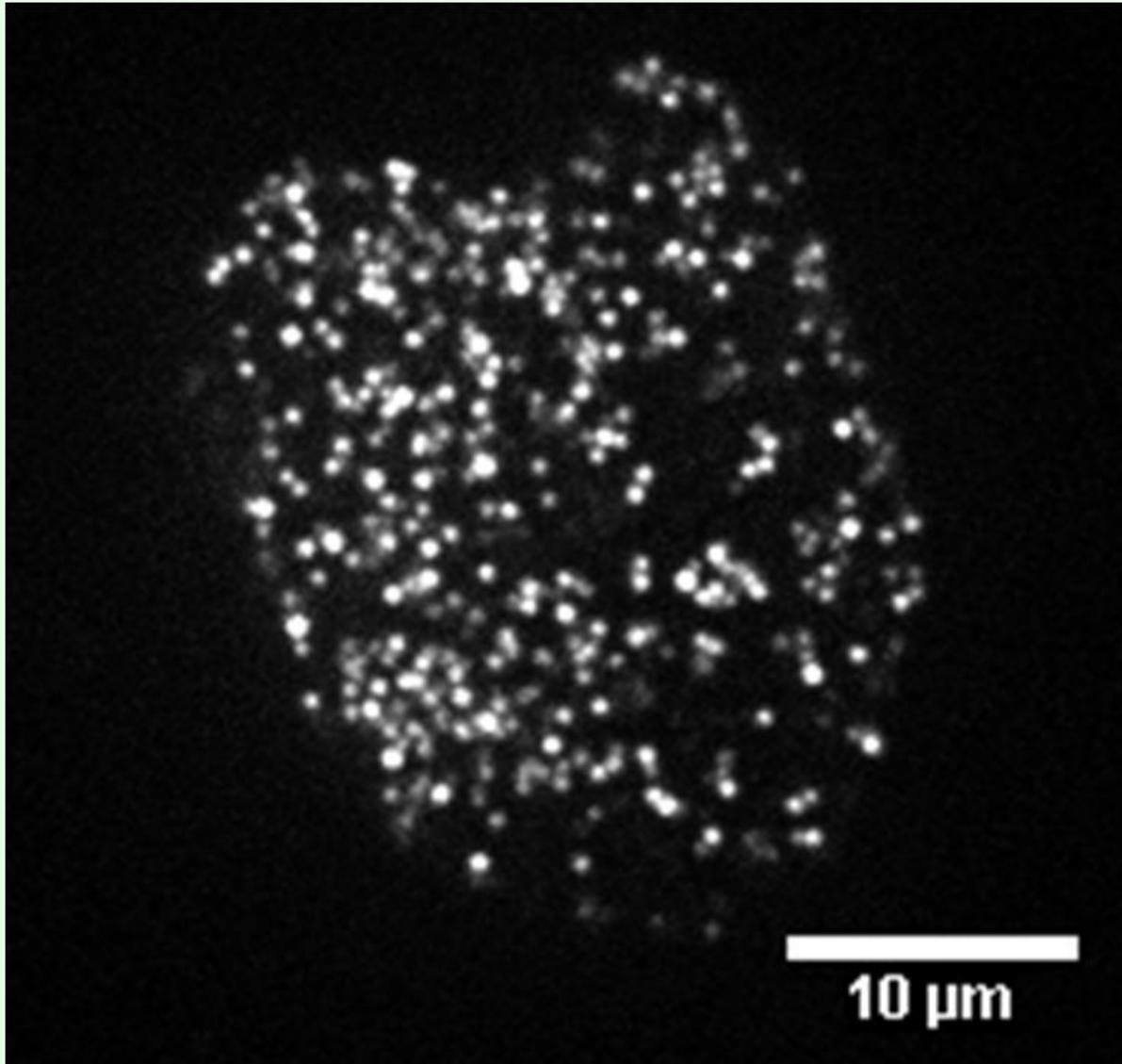


50  $\mu$ M 2-NBDG (fluorescence glucose analog)



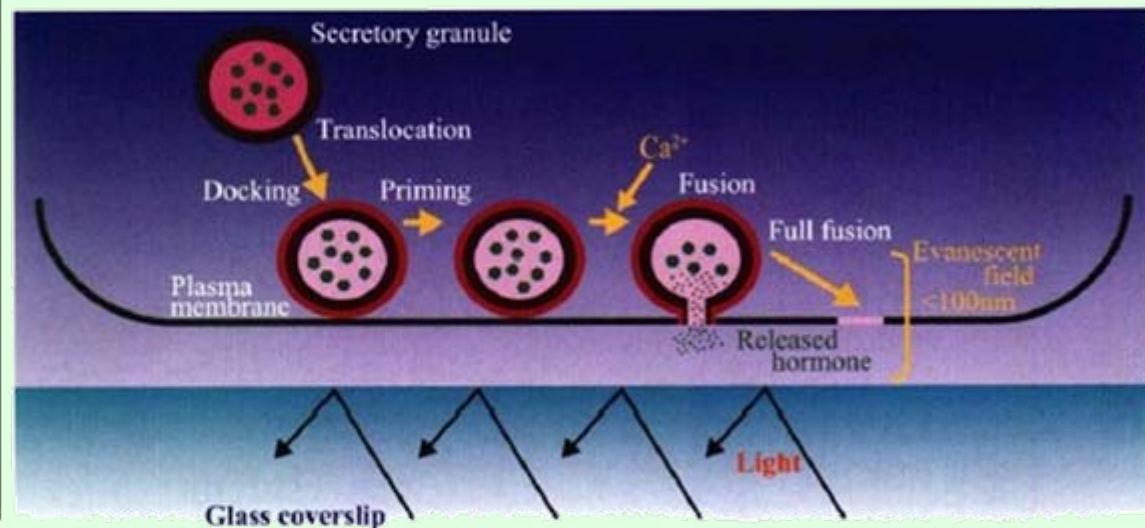
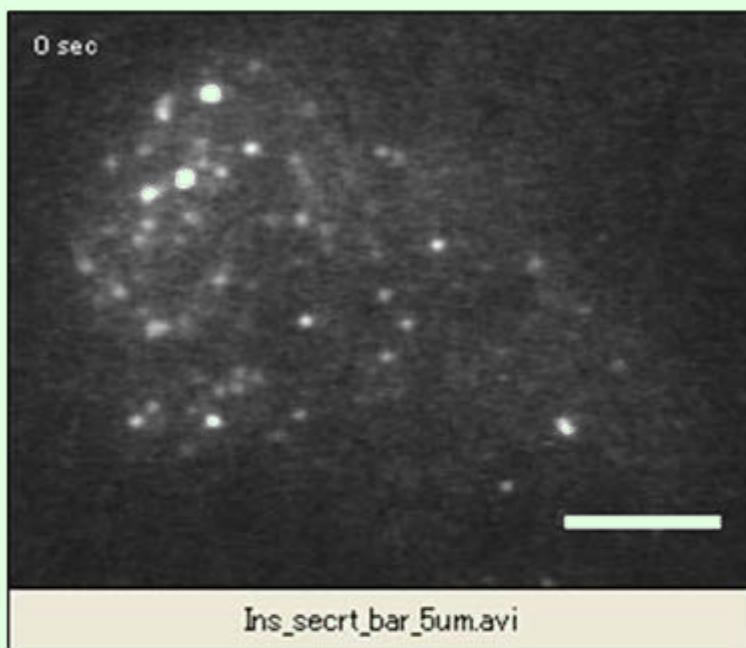
- External substances is introduced
- Glucose uptake is visualized with 4D (x,y,z and time) resolution.

# Insulin GFP is introduce and imaged in $\beta$ cell



Insulin-eGFP / MIN6 cell

# Insulin Secretion

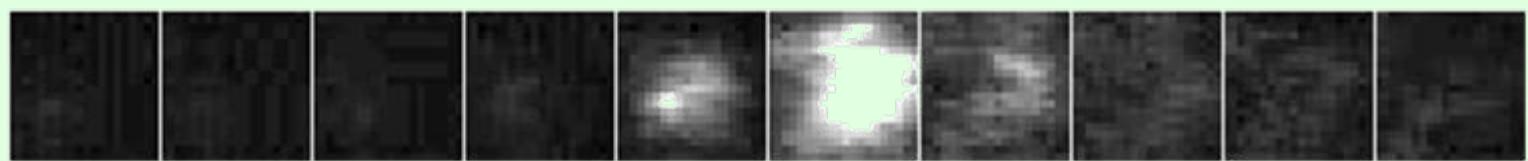


Insulin-eGFP / MIN6 cell

resident

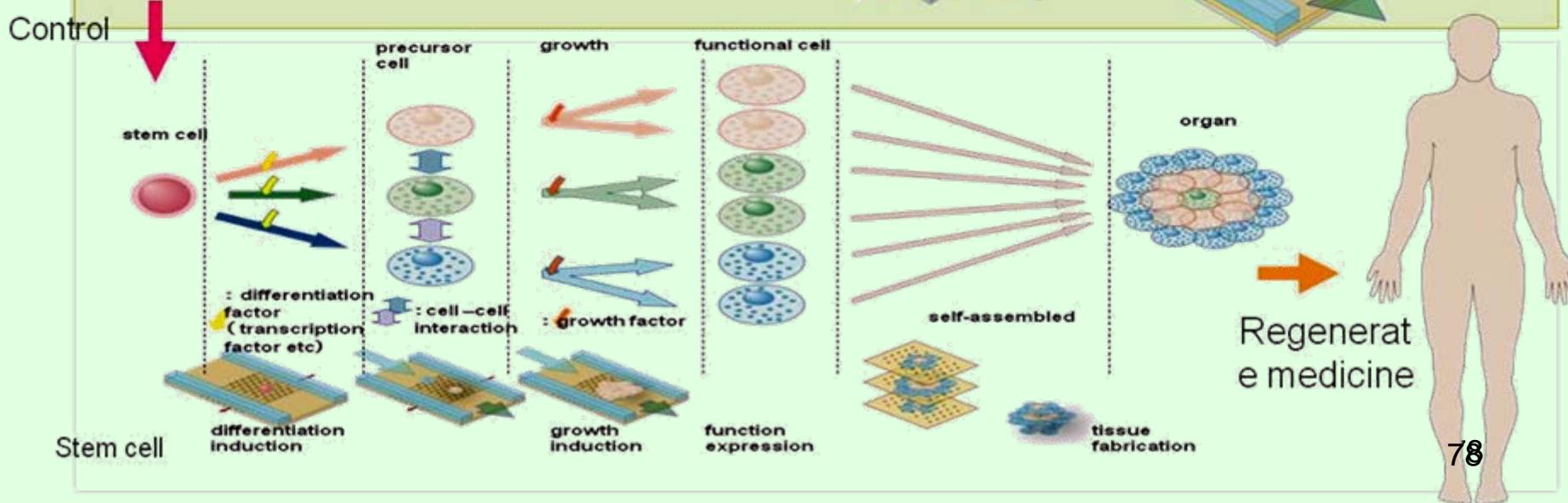
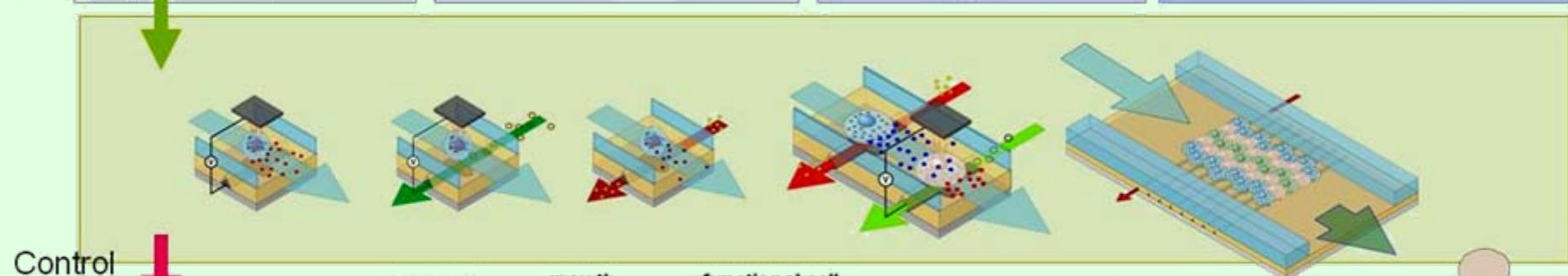
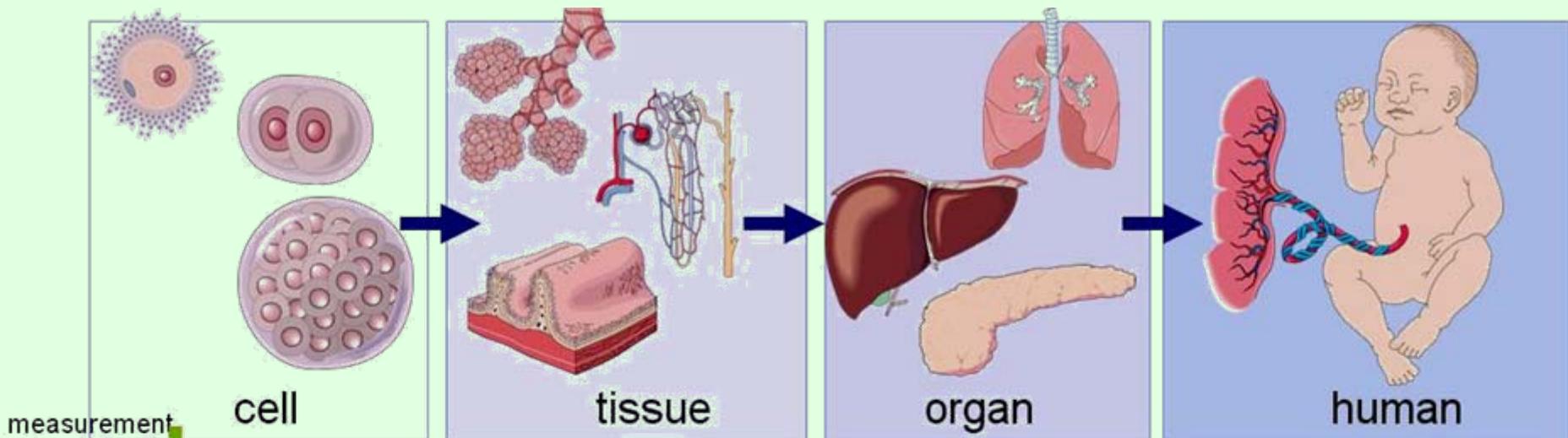


newcomer



33 msec/frame

77  
1  $\mu\text{m}$



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Assistant Prof. Satoshi Matsuoka; MD.

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Associate Prof. Amano

Associate Prof. Takashi Tada

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Development of bio/nano hybrid platform technology towards regenerative medicine

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